

Gold-Ceramic Thin Films: The New Gold Standard

for High Performance Electrical Sliding Contacts

Presented by Nicolas Argibay

Collaborators:

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Albuquerque NM, USA



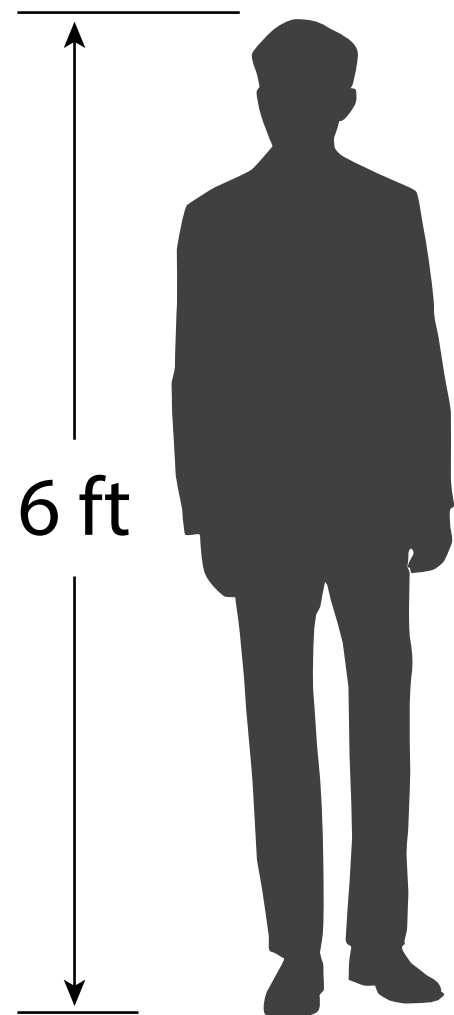
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Brief aside: just how relevant is gold as a tribological coating?

An estimated **300 metric tons/year** of gold used in electronics related applications, most of it in electroplated connectors and contacts (**11% of yearly amount mined**)

Equivalent to a cube comprised of ~25,000 standard gold bars (12 kg/26.4 lb each) *per year*...

2.6 m (8.5 ft) wide



6 ft

**~ US\$13.7 BILLION
spent in 2010 alone on
raw material**

*2.6 m (8.5 ft) deep

2.6 m (8.5 ft) tall

... or enough to clad the entire surface of the Eiffel Tower with pure gold 70 μm thick *every year*



Reference: Gold Survey, Gold Fields Mineral Services Ltd., 2010

What is a common theme in the vast majority of electrical contacts?

MEMS: 1-2 μm thick gold and gold alloy films are typical

printed circuit boards (PCBs): 200 - 500 nm thick electroless gold films on soldered connections to prevent oxidation on PCBs

aerospace: 1 - 3 μm thick hard gold (ASTM/MilSpec) used to achieve predictable friction AND contact resistance over years or decades

	silver 47	
Pd 106.42	Ag 107.87	Cd 112.41
platinum 78	gold 79	mercury 80
Pt 195.08	Au 196.97	Hg 200.59
ununnium 110	ununium 111	unubium 112
	[272]	

What is electroplated “hard gold”?

Nominally gold with the addition of Ni/Co/Fe not exceeding 1 wt. %

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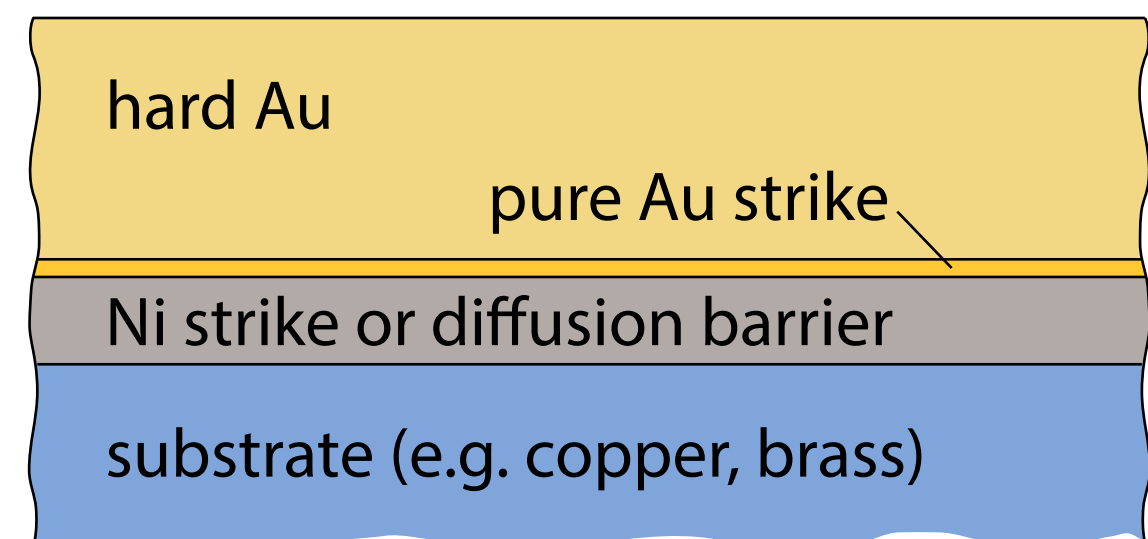
Why? Critical to performance are:

- **oxidation resistance** YES

- **ductility** YES

- **electrical conductivity** YES

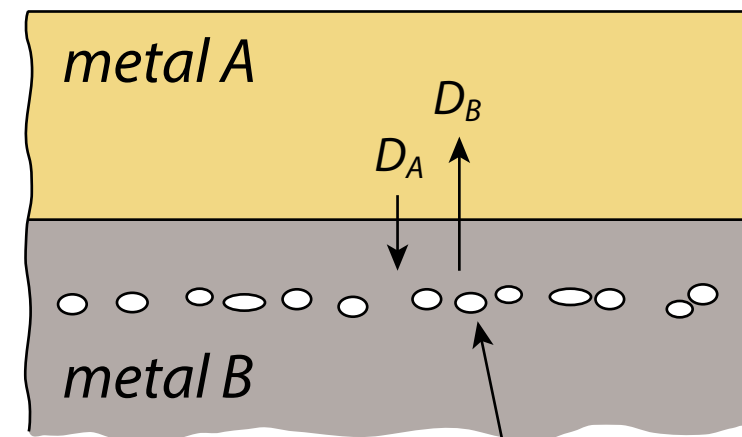
...but low friction/wear? **use alloys (hard gold)**



What materials aging phenomena are relevant to tribological contacts?

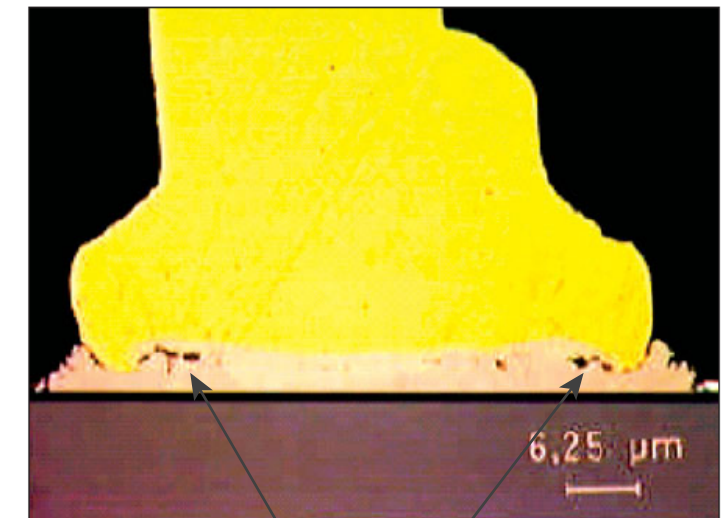
Kirkendall *porosity* (voiding) and the formation of *intermetallics* (embrittlement):

$D_A < D_B$ results in
asymmetric flux of material



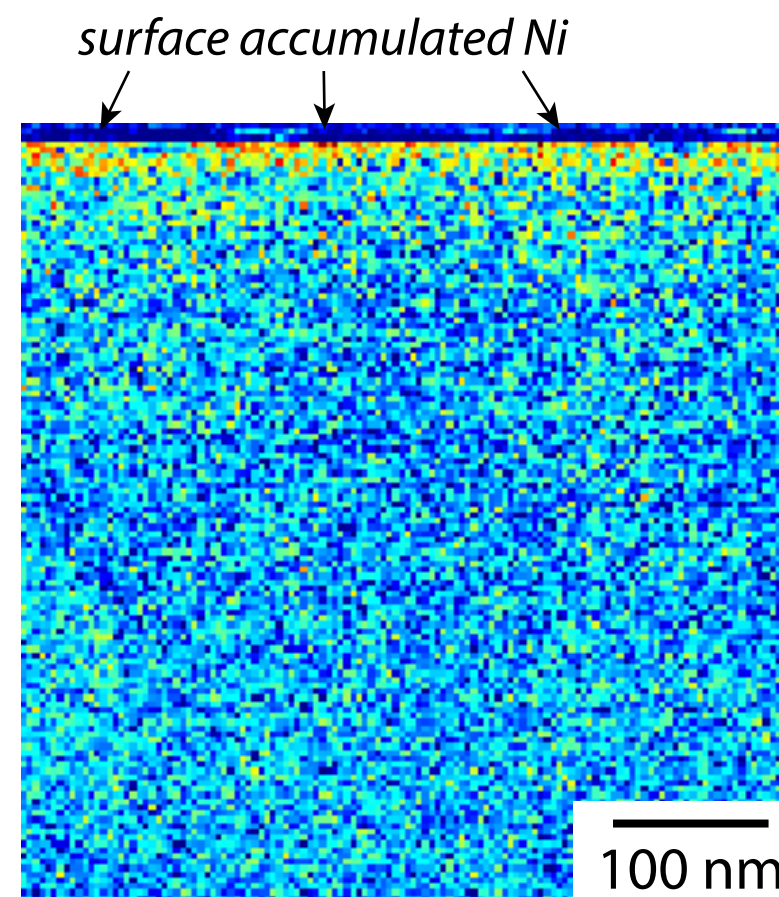
pore formation due
to defect accumulation

aged Au-Al ball bond used in
flip chip bonding



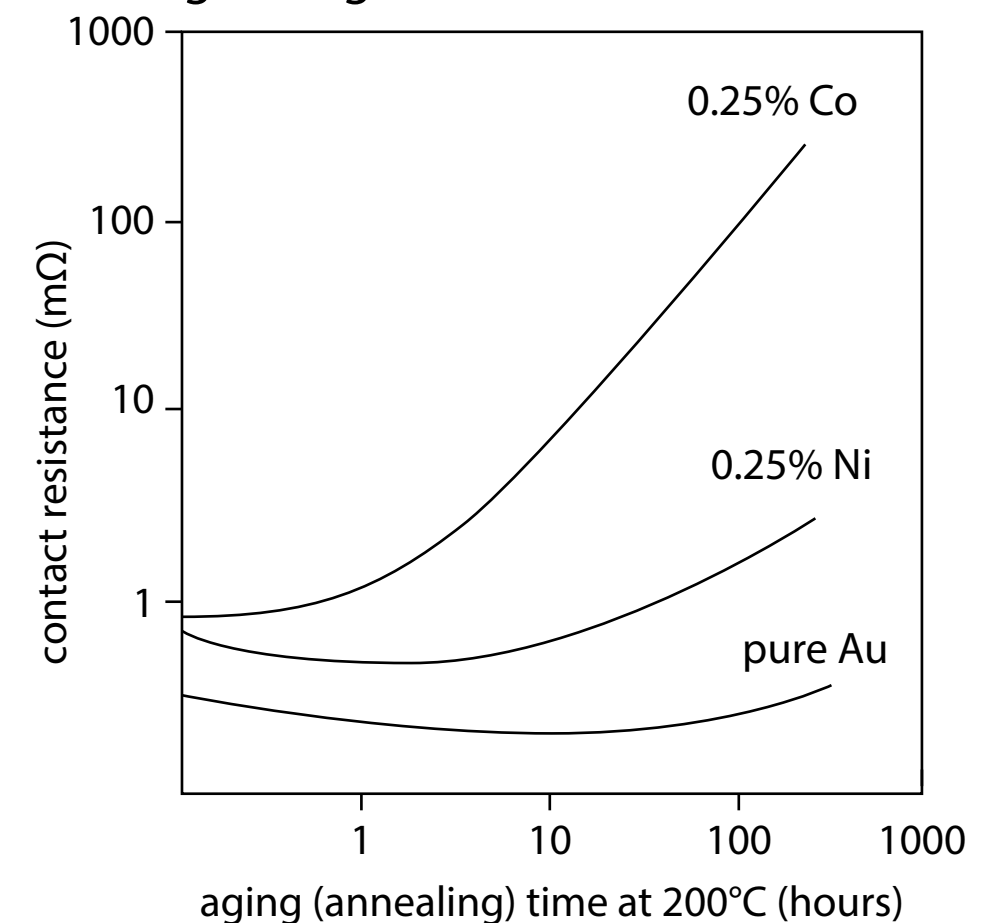
formation of voids and
interfacial fractures driven
by formation of intermetallics

Surface accumulation of
underlayer and codeposited species:



relative Ni concentration in a hard Au film
aged at low temperature

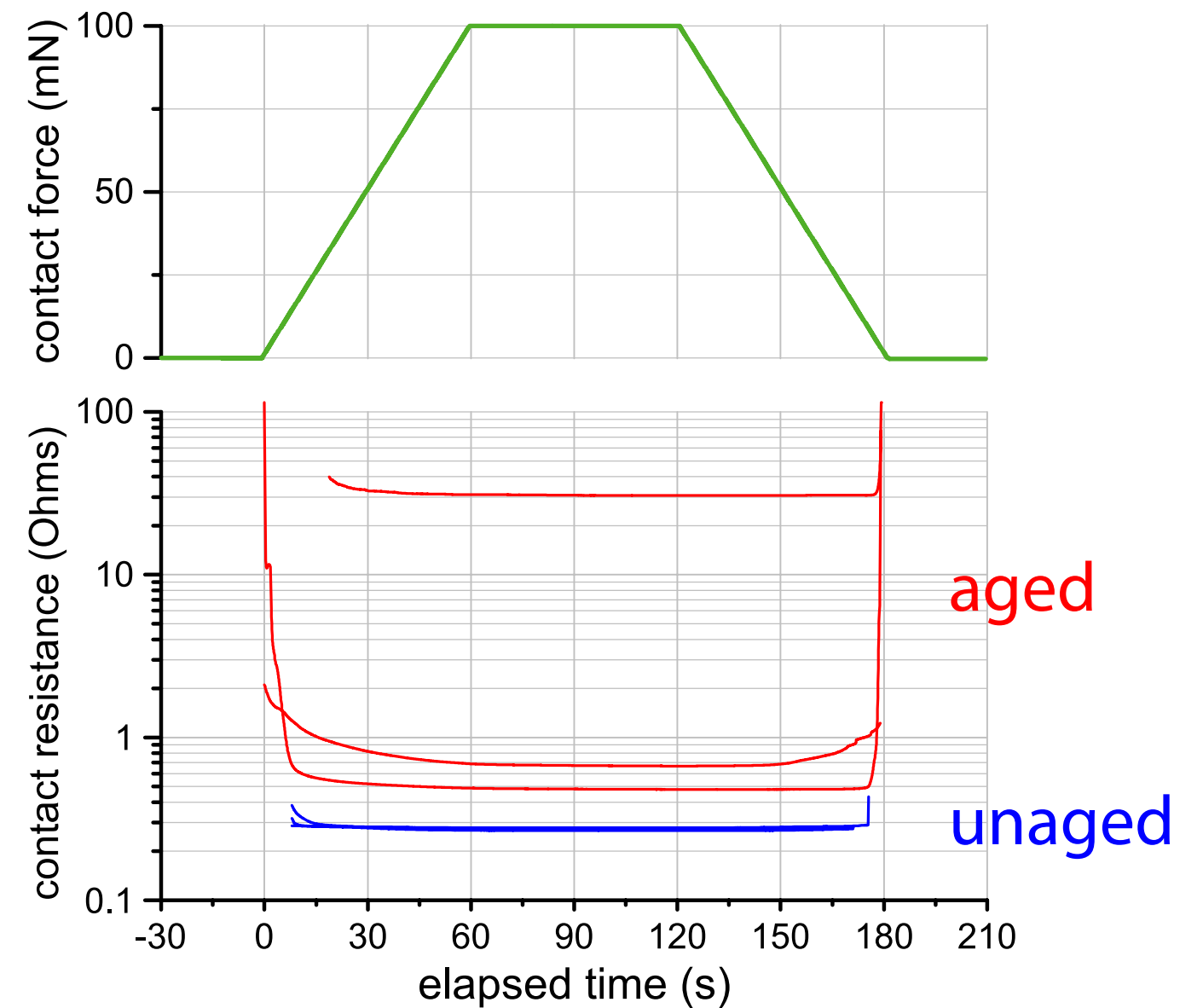
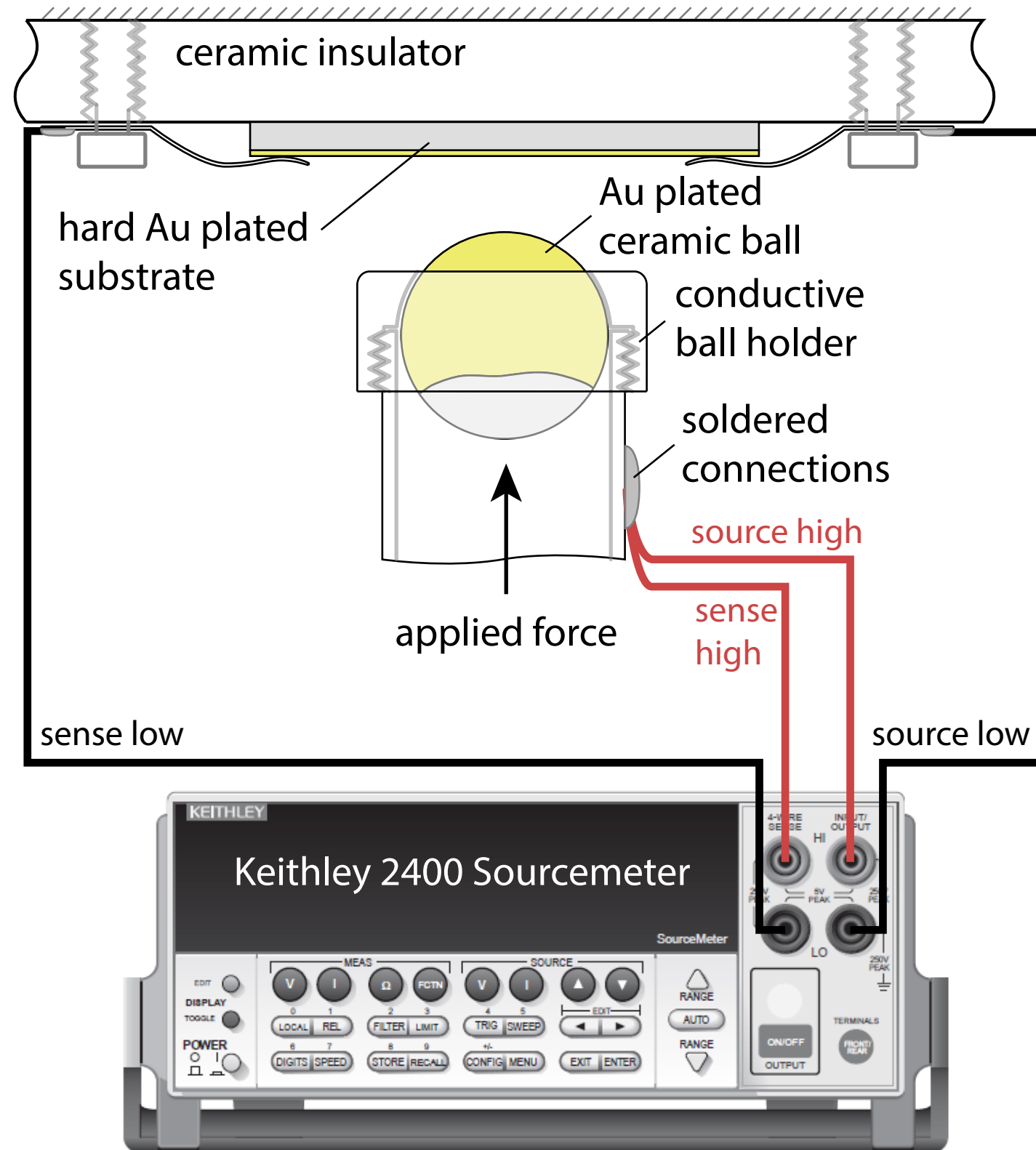
aging of **bulk** pure and alloyed
gold ingots:



Reference: M. Antler, Plating and Surface
Finishing, 1998

Surface accumulation and oxidation can significantly affect ECR

Electrical contact resistance of aged type I hard Au plated Fe-Ni substrate aged at 250°C for 42.5 hours in air:



- film thickness $\sim 2 \mu\text{m}$ type I hard Au on a $5\text{-}7 \mu\text{m}$ Ni strike
- 1 mA current
- ball radius : $1/32''$ ($\sim 0.79 \text{ mm}$)

several order of magnitude changes in contact resistance can occur quickly

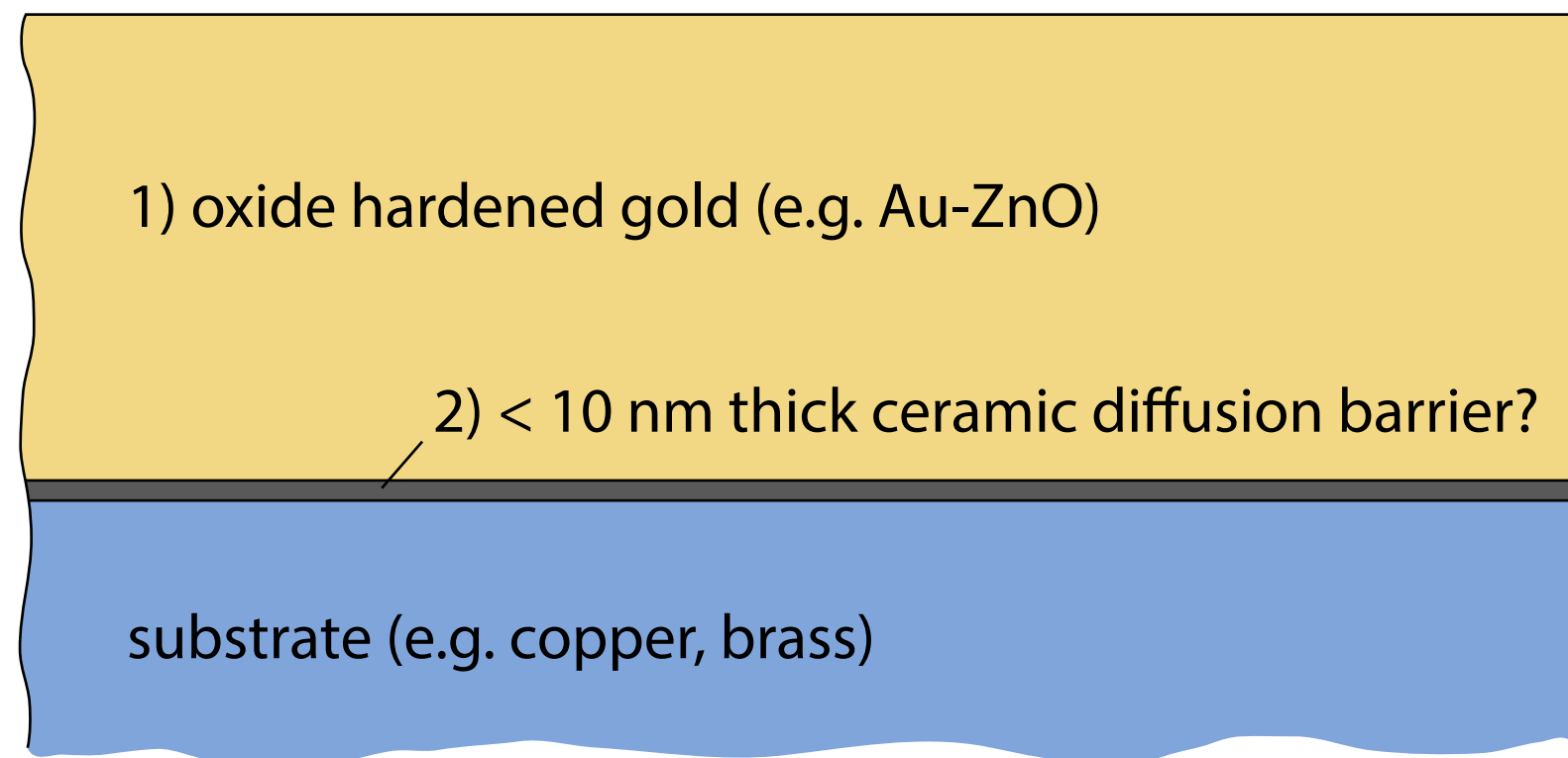
New routes for mitigating aging in gold electrical contacts?

Traditionally: mitigate the aging phenomena, increase the service life of a contact by,

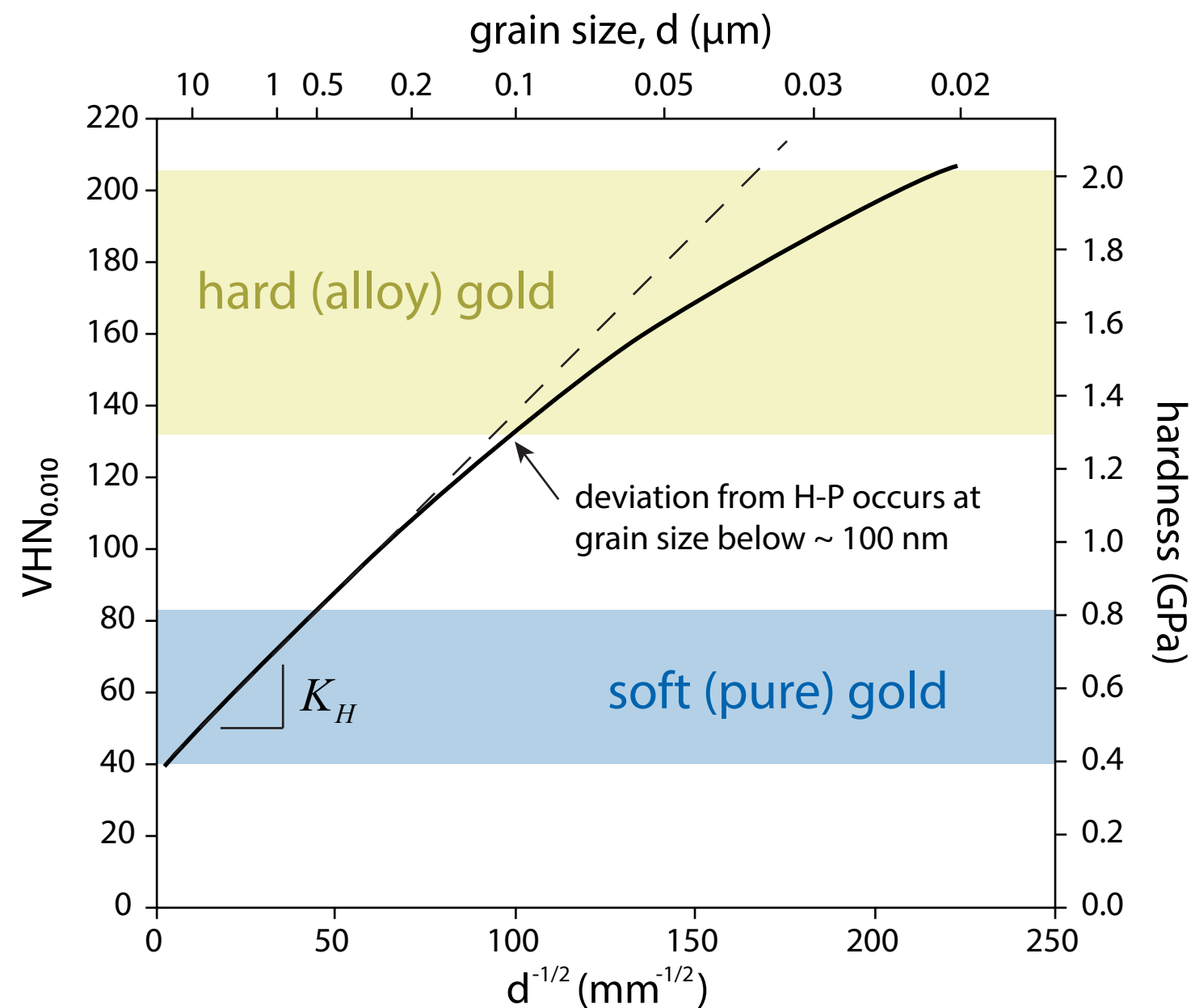
1. using sufficiently thick gold films
2. use an inert environment

Proposed: shut down solid diffusion of codeposited and underlayer materials via,

1. ceramics to harden Au in place of non-noble metals
2. introduce electron transparent ceramic diffusion barrier layers



Hard gold hardens primarily via Hall-Petch strengthening (grain refinement)

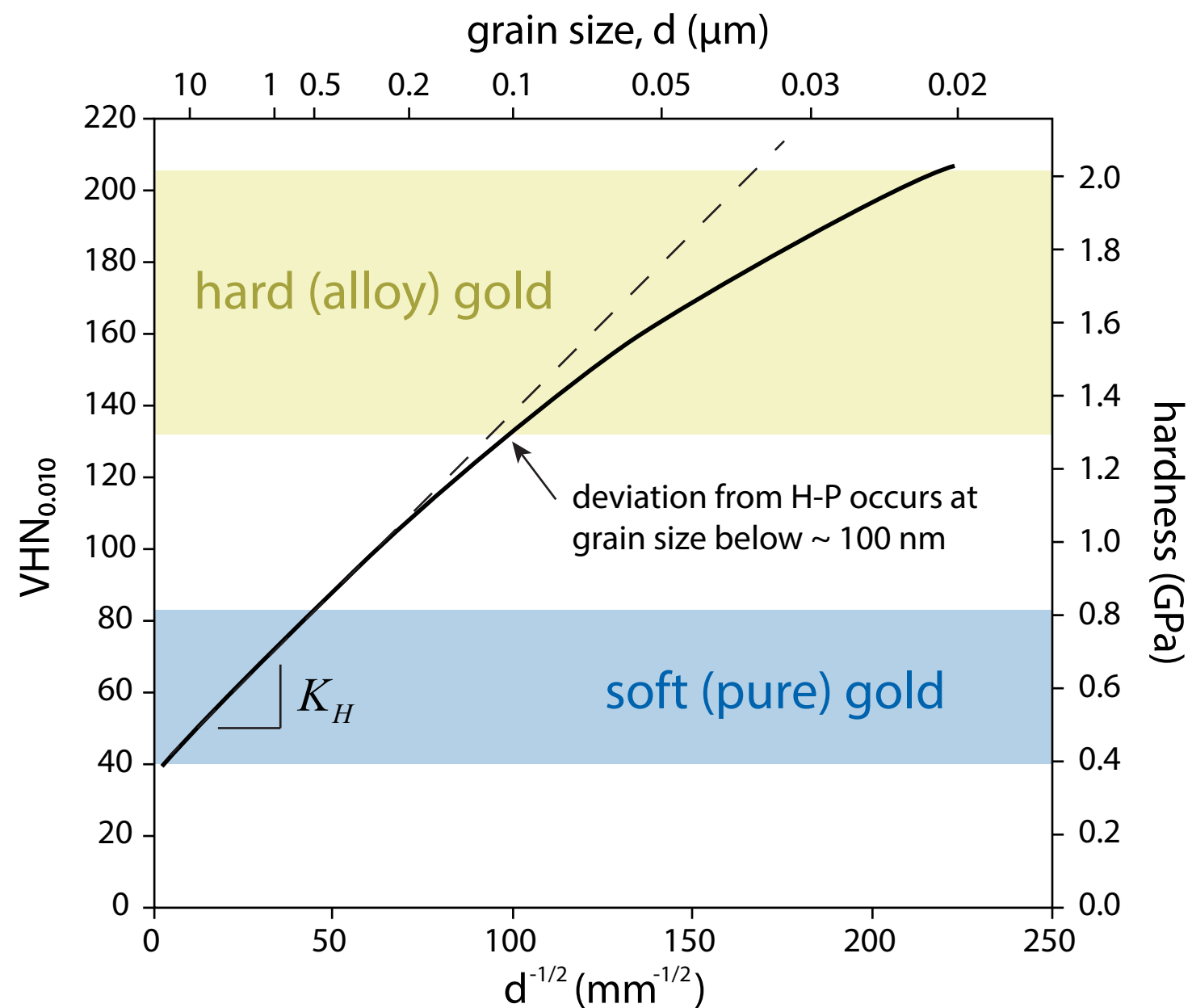


Reference: C. Lo, J. Augis, and M. Pinnel, JAP (1979)

Contact area to hardness relationship: $A_r \cong \frac{F_n}{H}$

Hall-Petch hardness to grain size relationship: $H = H_0 + K_H d^{-1/2}$

Zener pinning GB segregated second phase limits grain growth

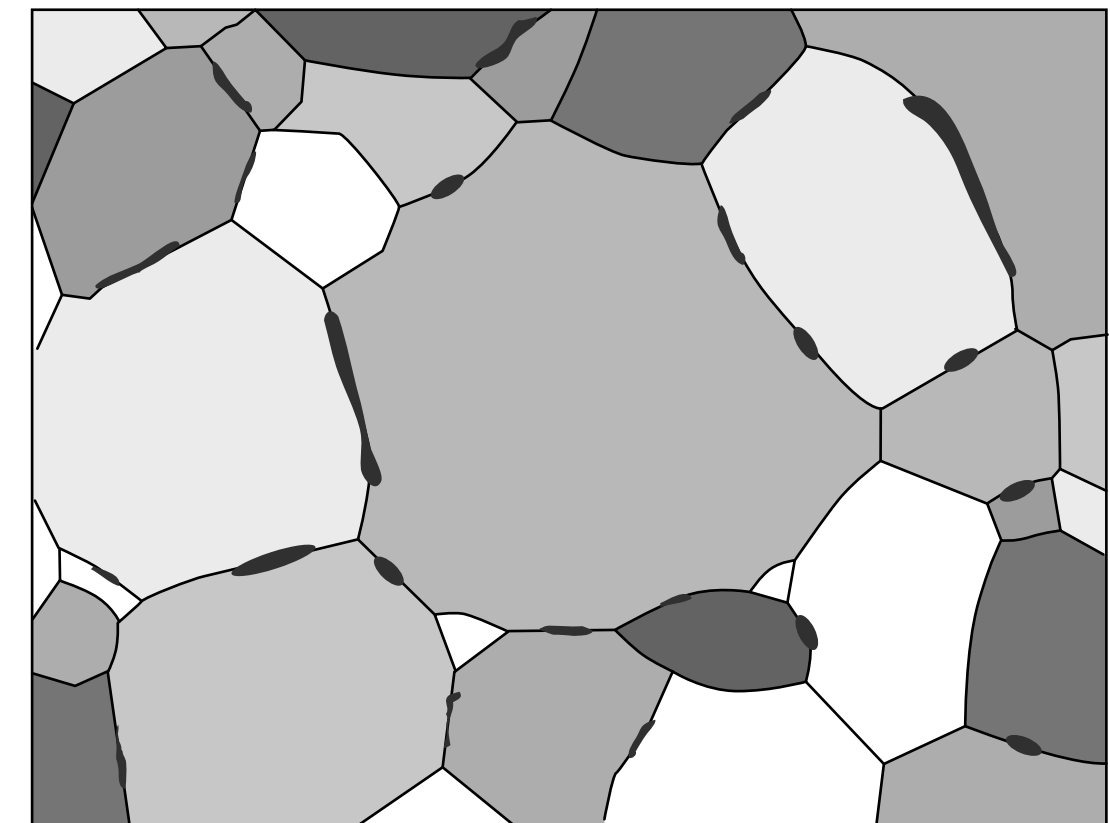


Reference: C. Lo, J. Augis, and M. Pinnel, JAP (1979)

Contact area to hardness relationship: $A_r \cong \frac{F_n}{H}$

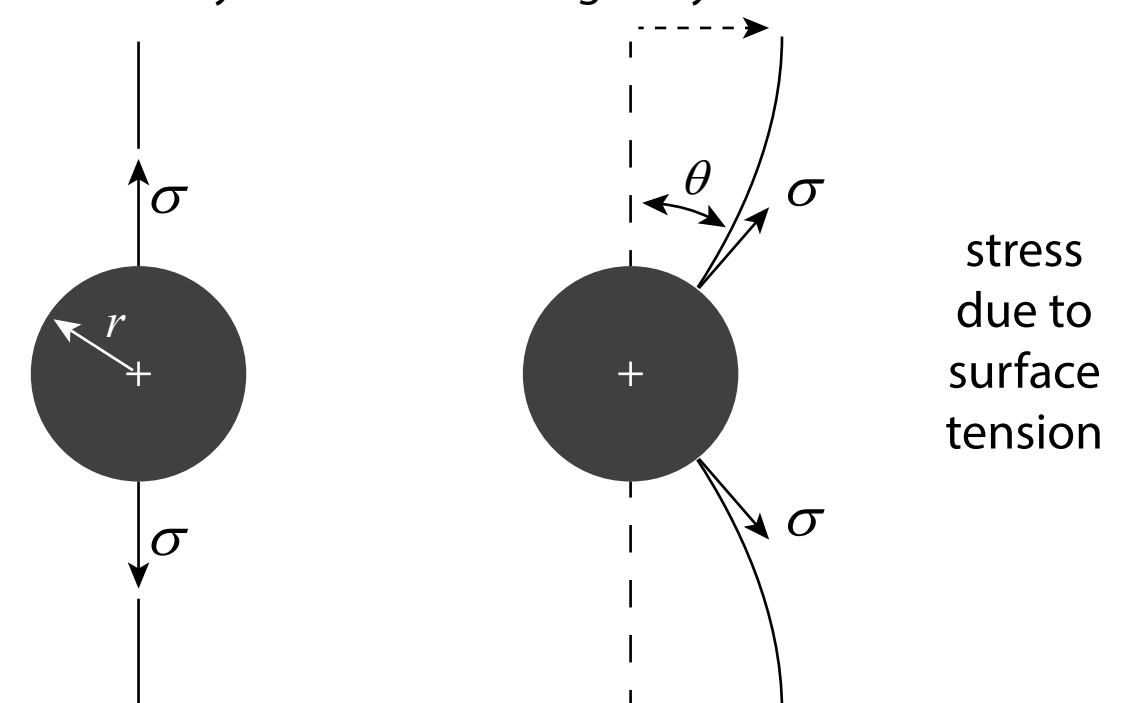
Hall-Petch hardness to grain size relationship: $H = H_0 + K_H d^{-1/2}$

second-phase inclusions at GBs pin the boundaries and inhibit GB mobility (recrystallization)



grain boundary

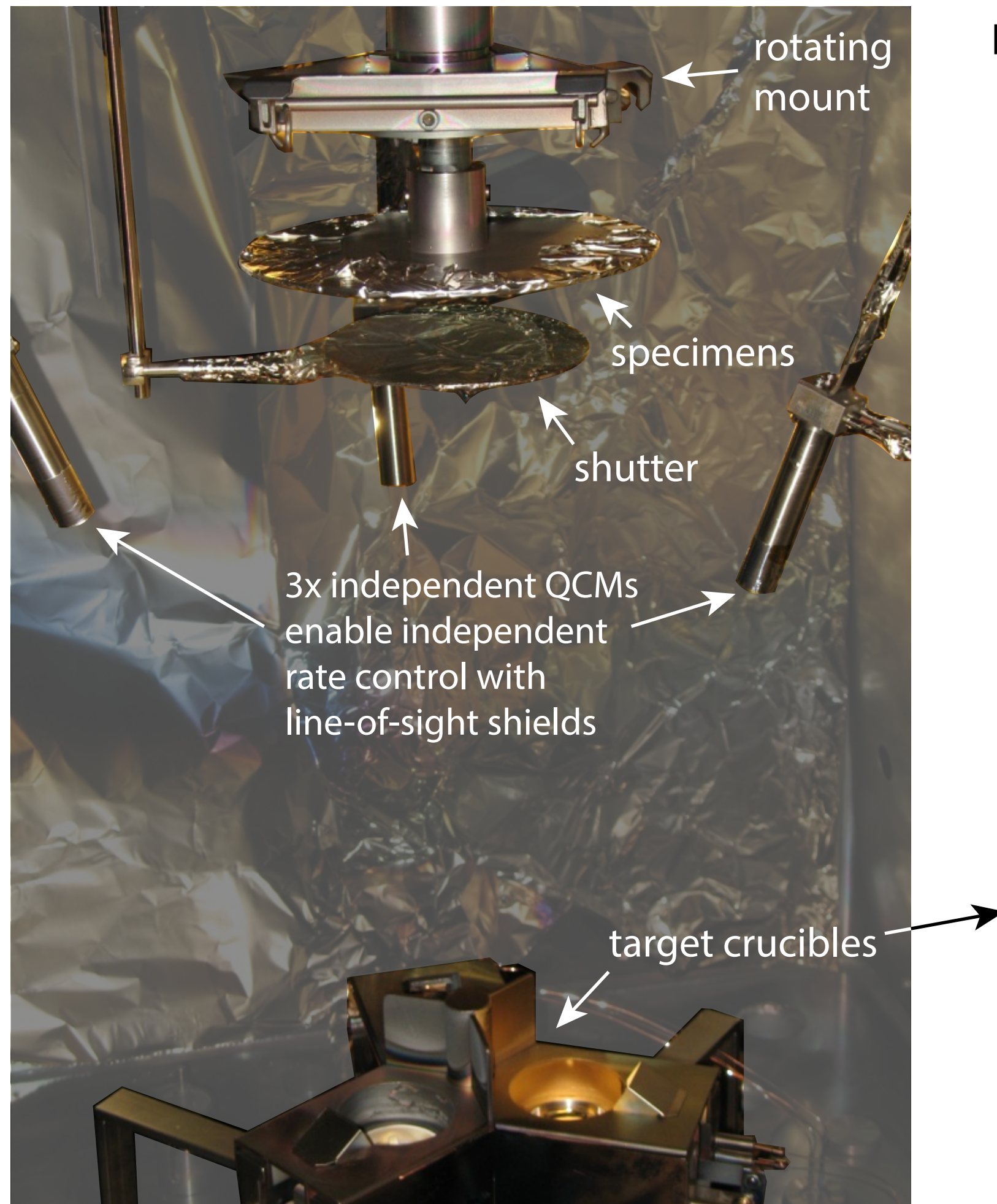
GB motion during recrystallization



drag force: $f_D = 2\pi r \sigma \cos \theta \sin \theta$

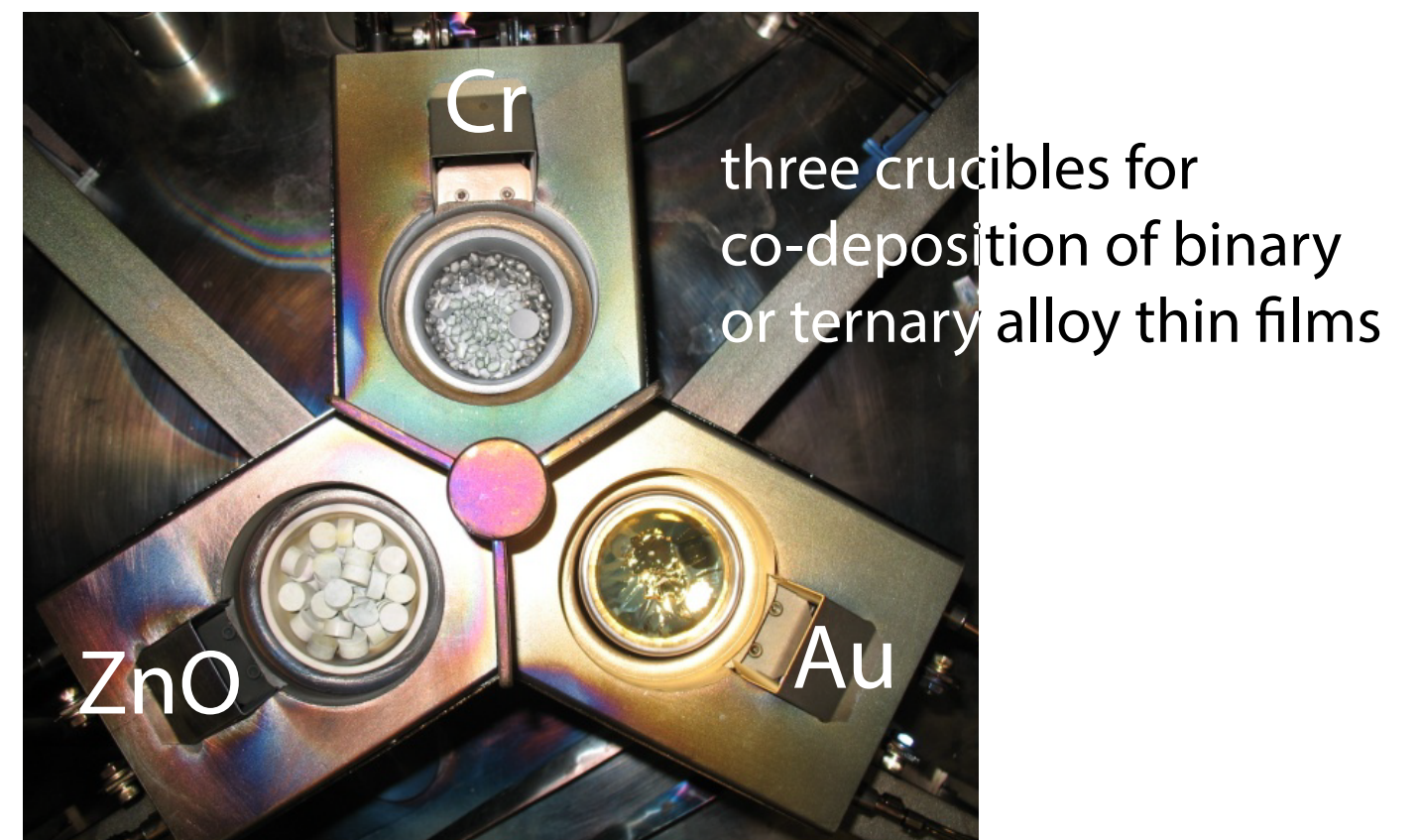
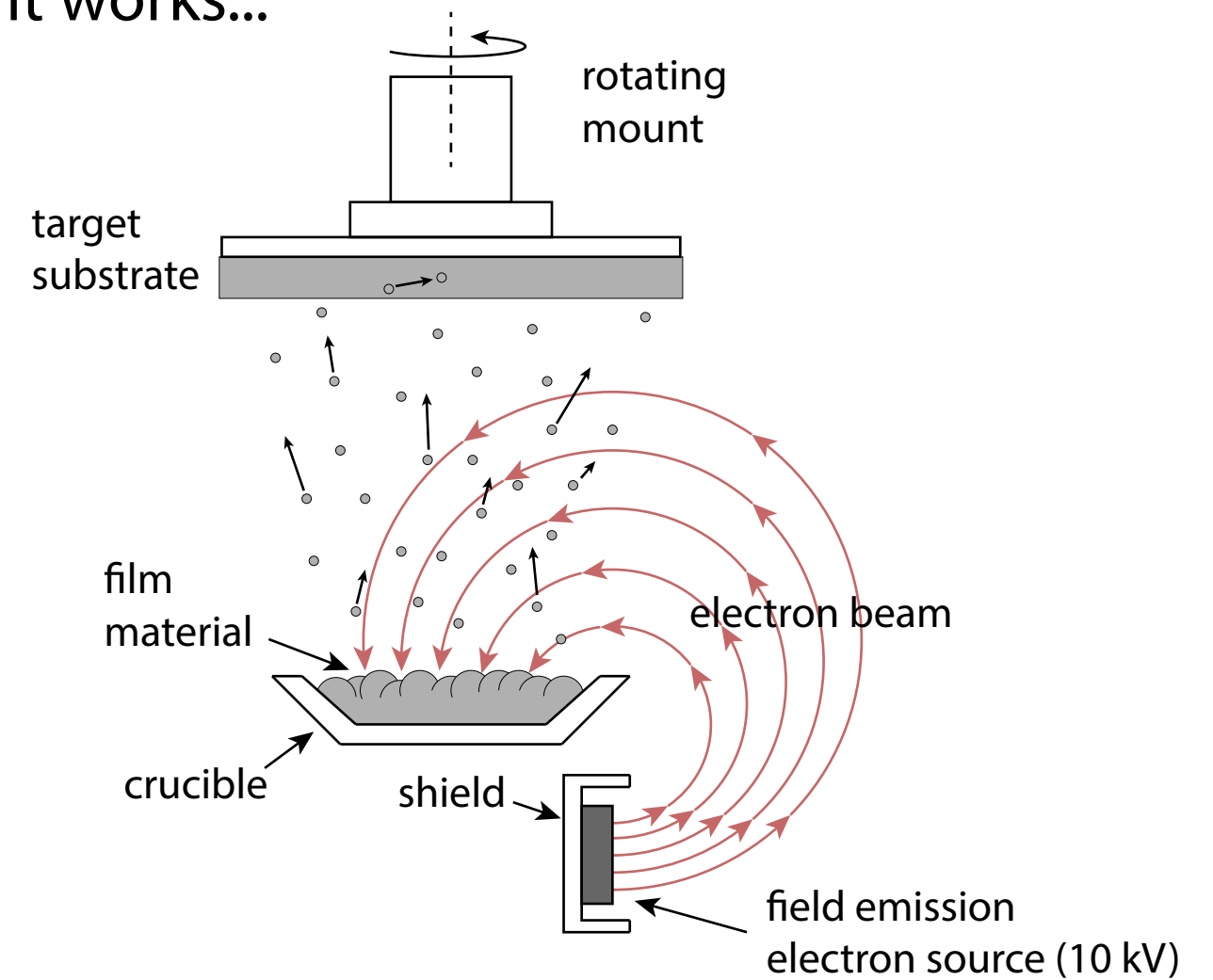
Electron beam deposition of metal-ceramic nanocomposite films

E-beam deposition chamber



Why e-beam? ppm level composition control

How it works...

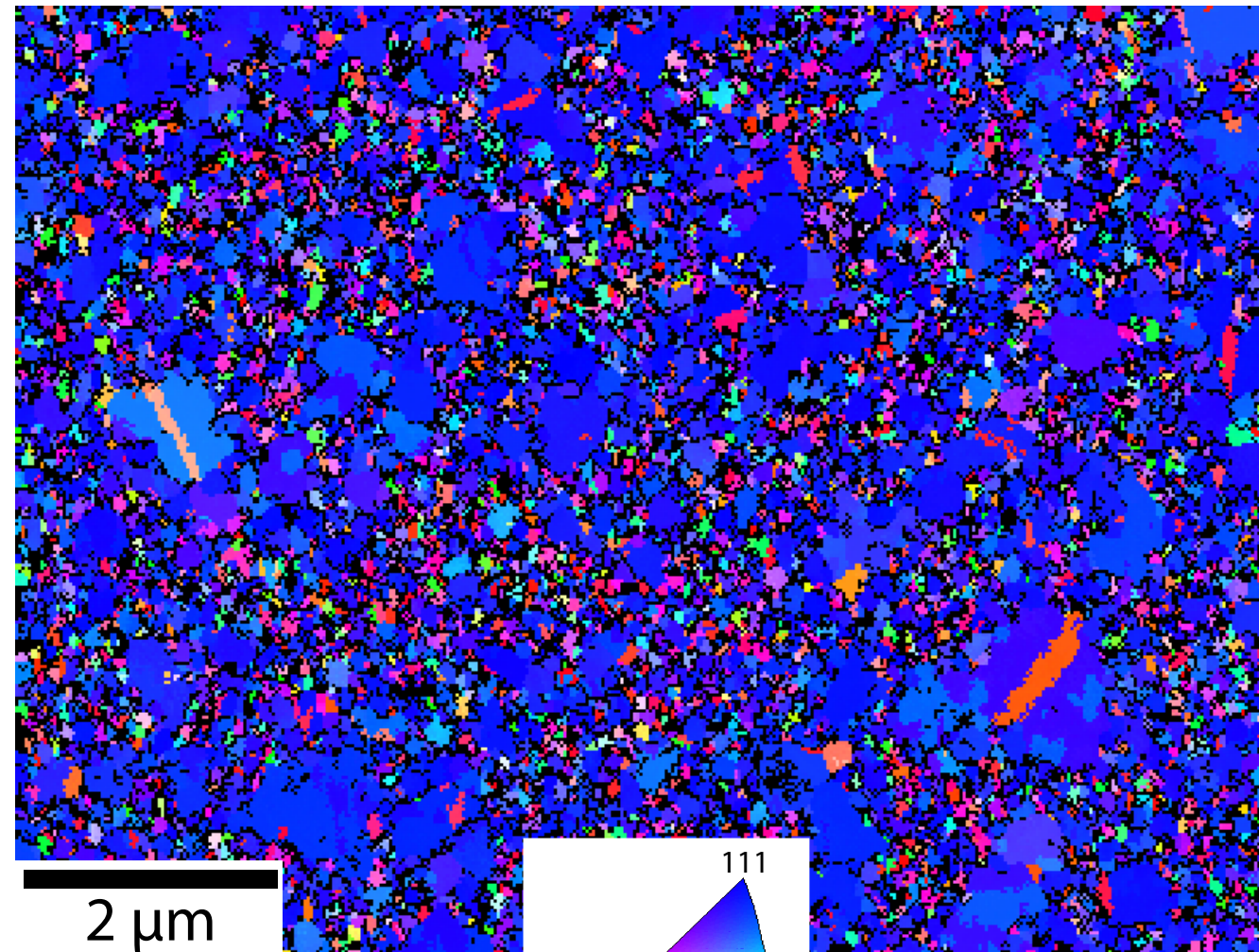


Electron backscatter diffraction maps showing grain refinement with alloying

(e-beam deposited films)

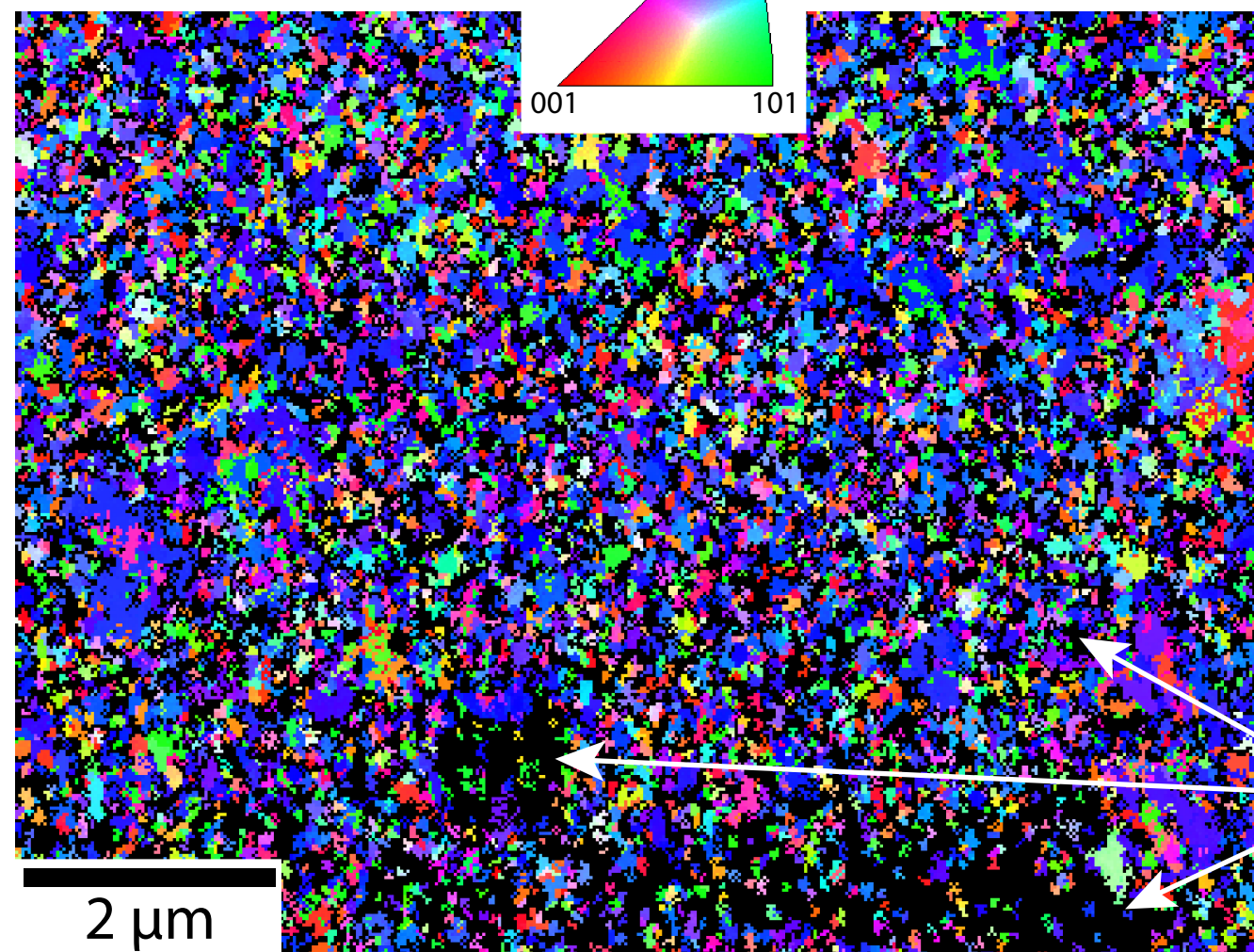
surface normal orientation

2 μm thick
pure e-beam
gold film



grain size was bimodal
and textured,
avg. grain size $> 500\text{ nm}$

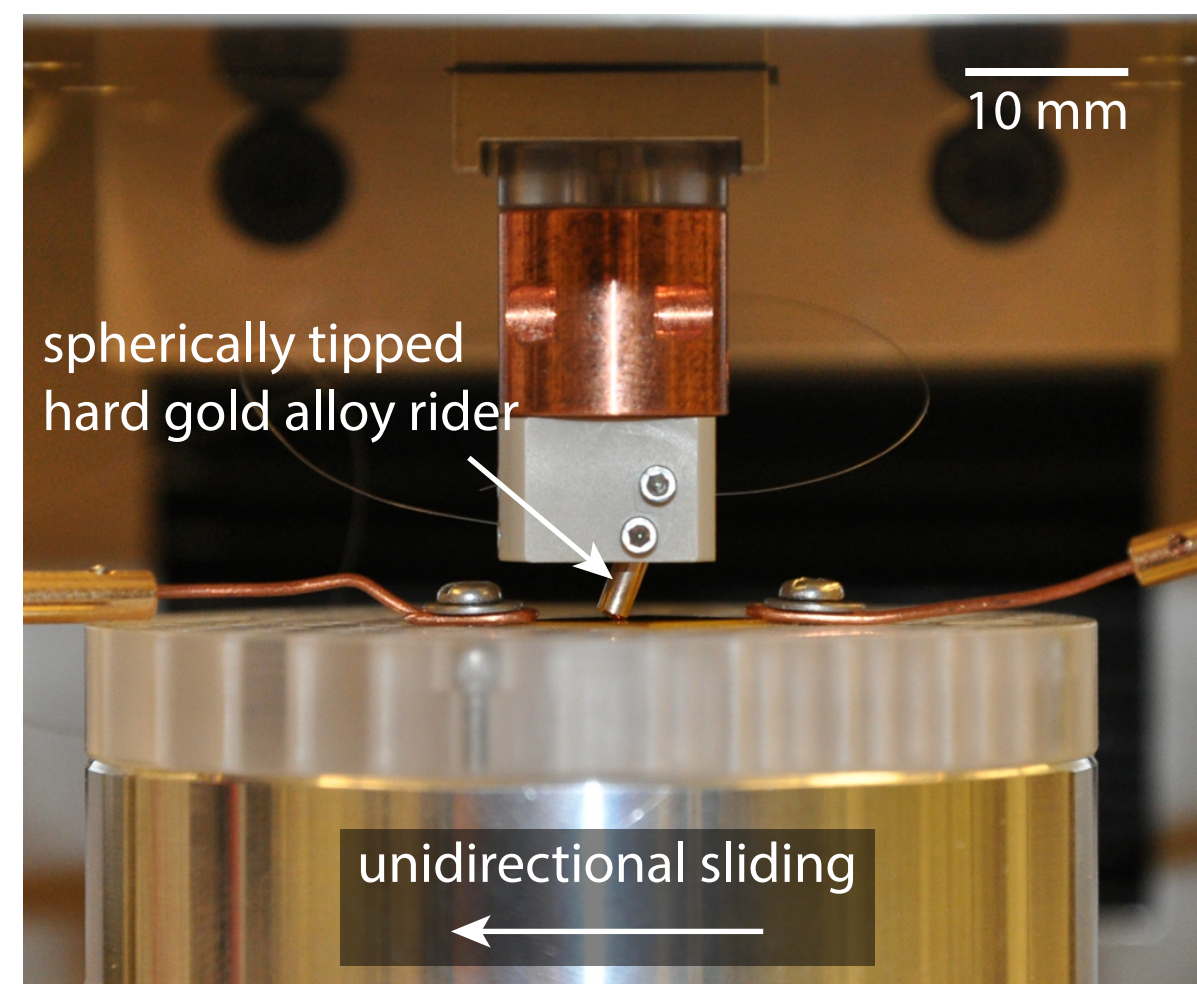
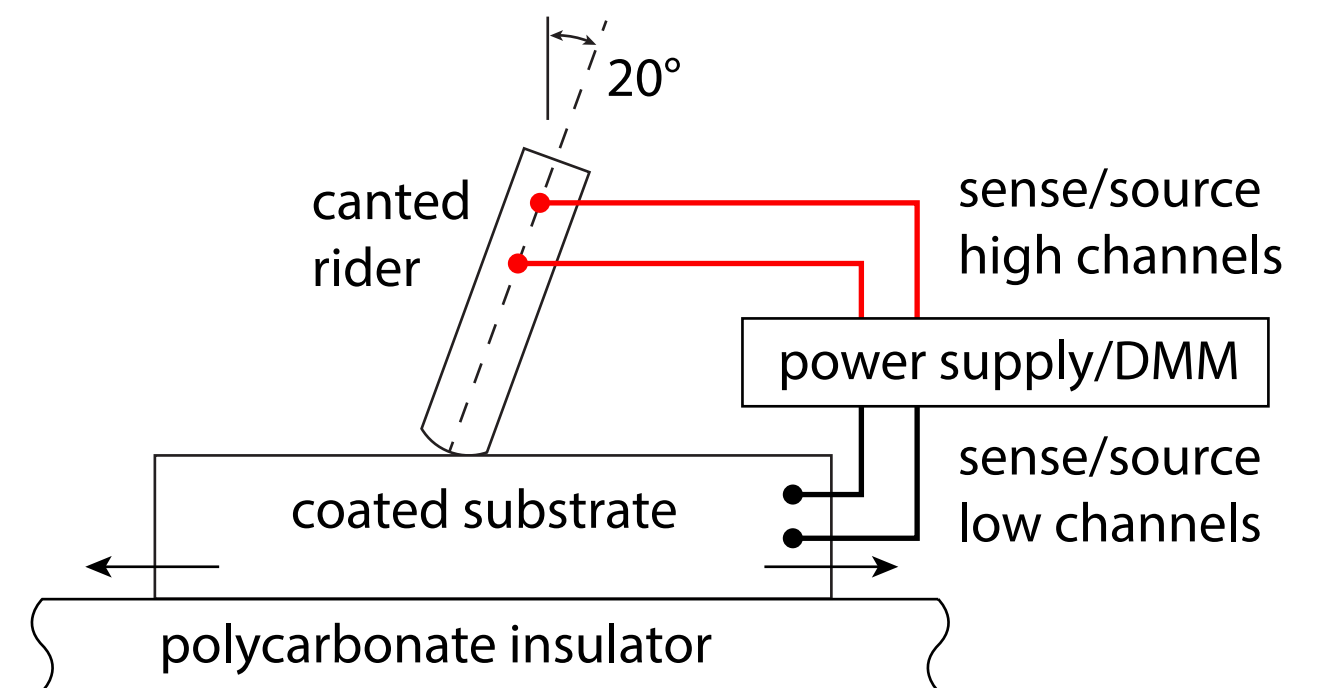
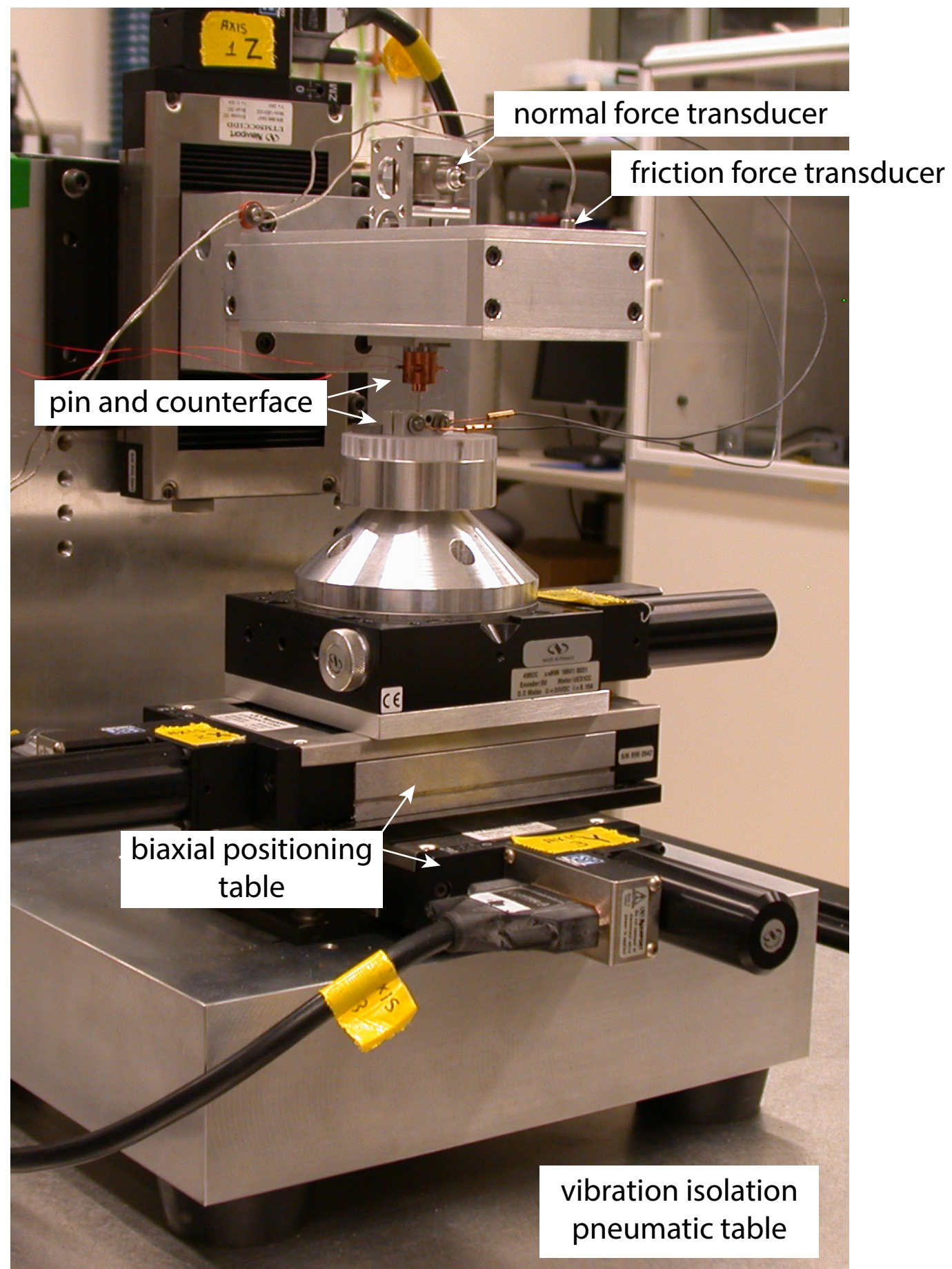
2 μm thick
0.1 vol. % ZnO
(0.03 wt. %)
gold film



grains are equiaxed,
not textured,
avg. grain size $\sim 100\text{ nm}$

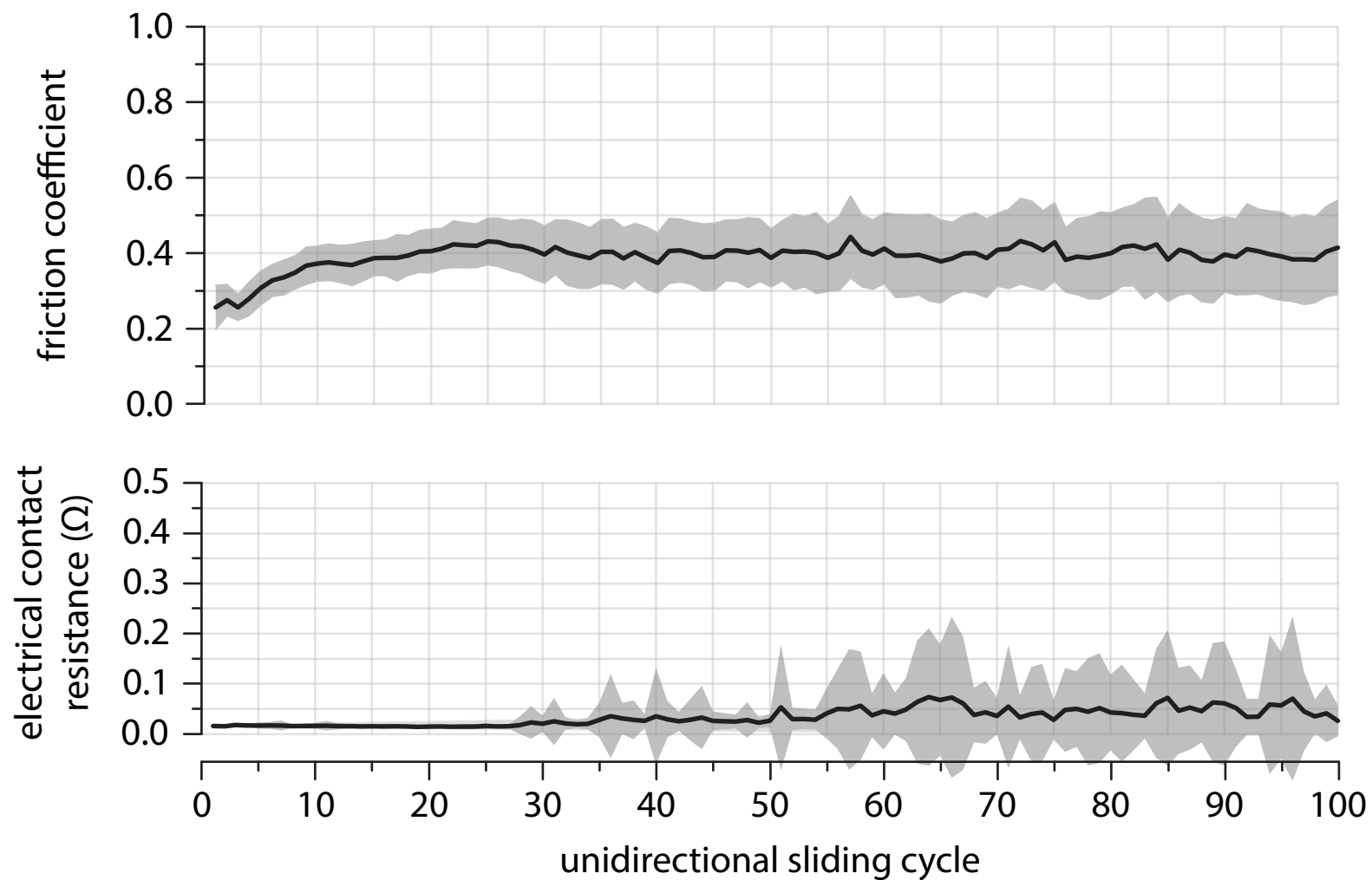
black pixels imply regions
with grain sizes $< 50\text{ nm}$

Sliding Electrical Contact Tester

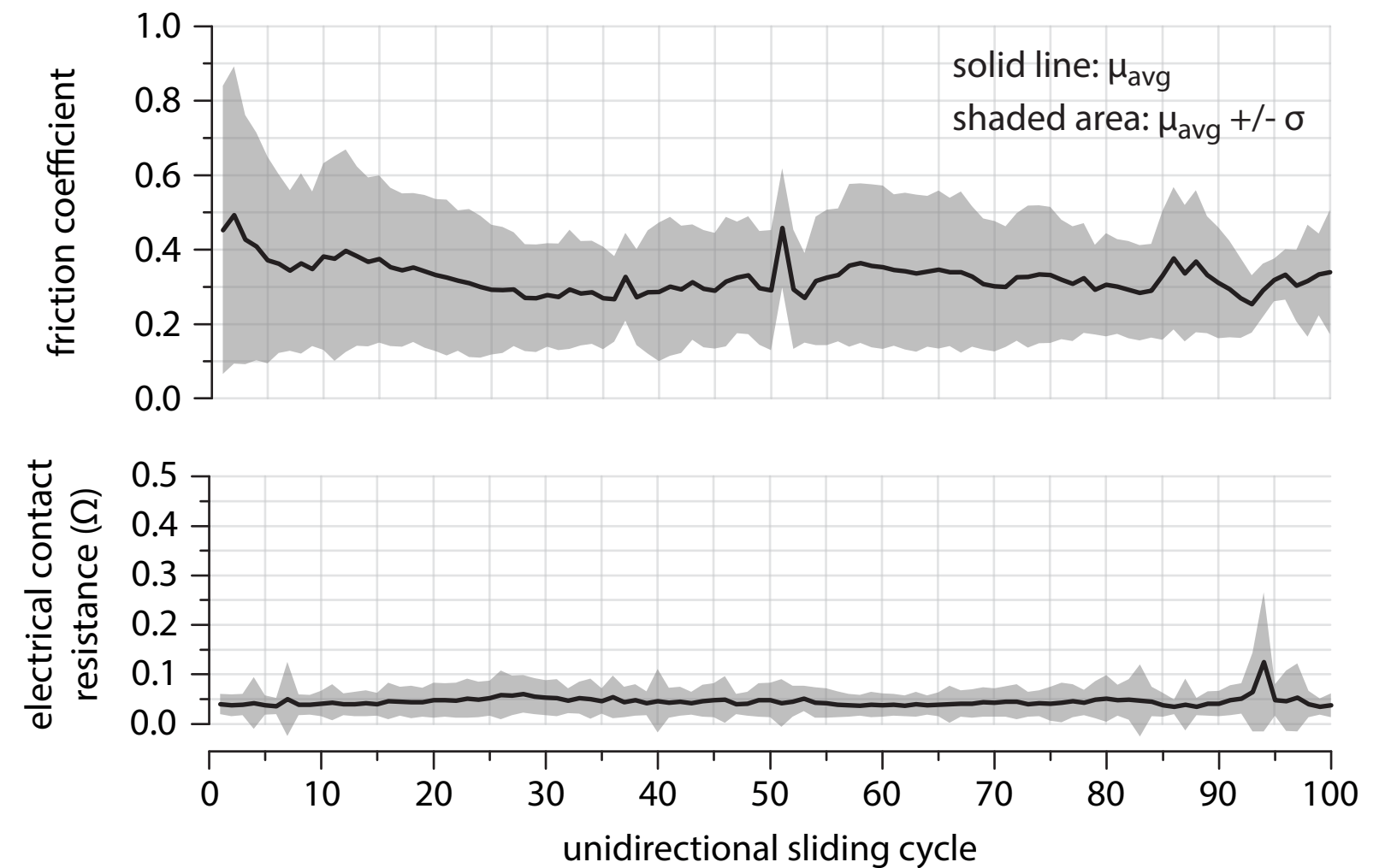


Au-ZnO shows similar tribological behavior to electroplated hard gold

electroplated type I Ni-hardened gold film



Au-2 vol. % ZnO composite film

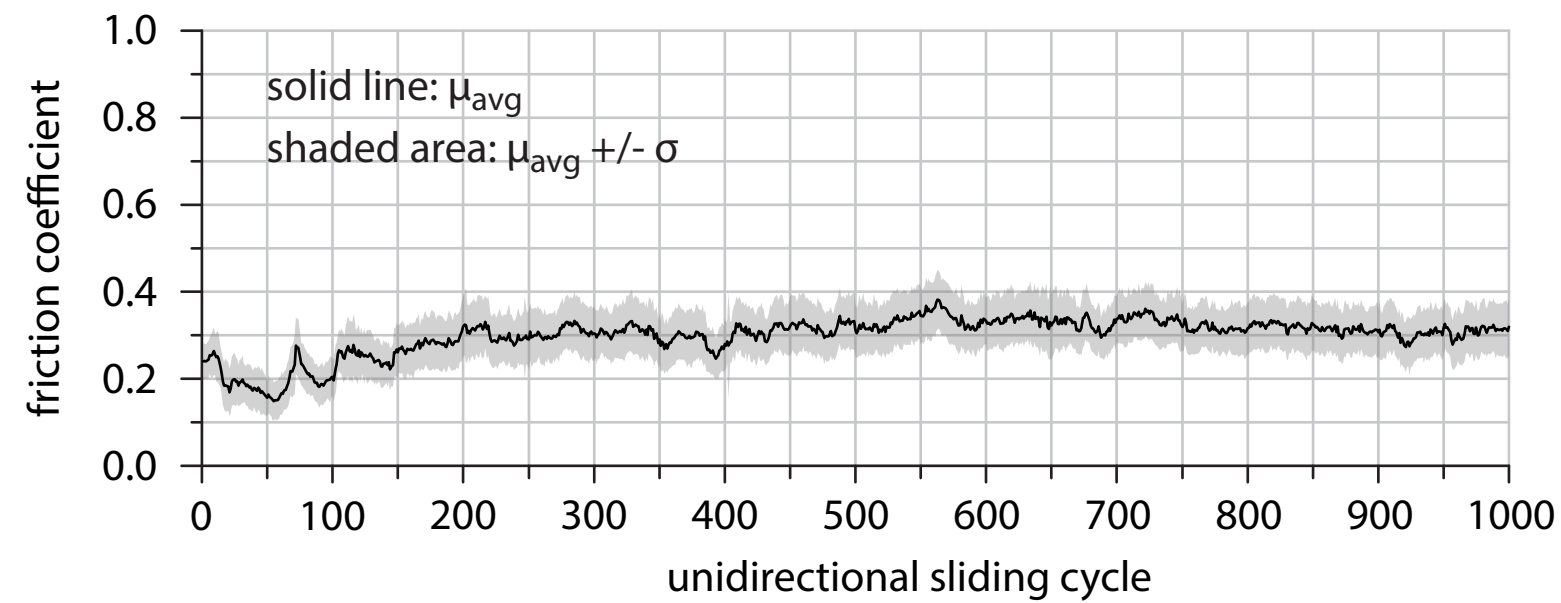


common testing parameters:

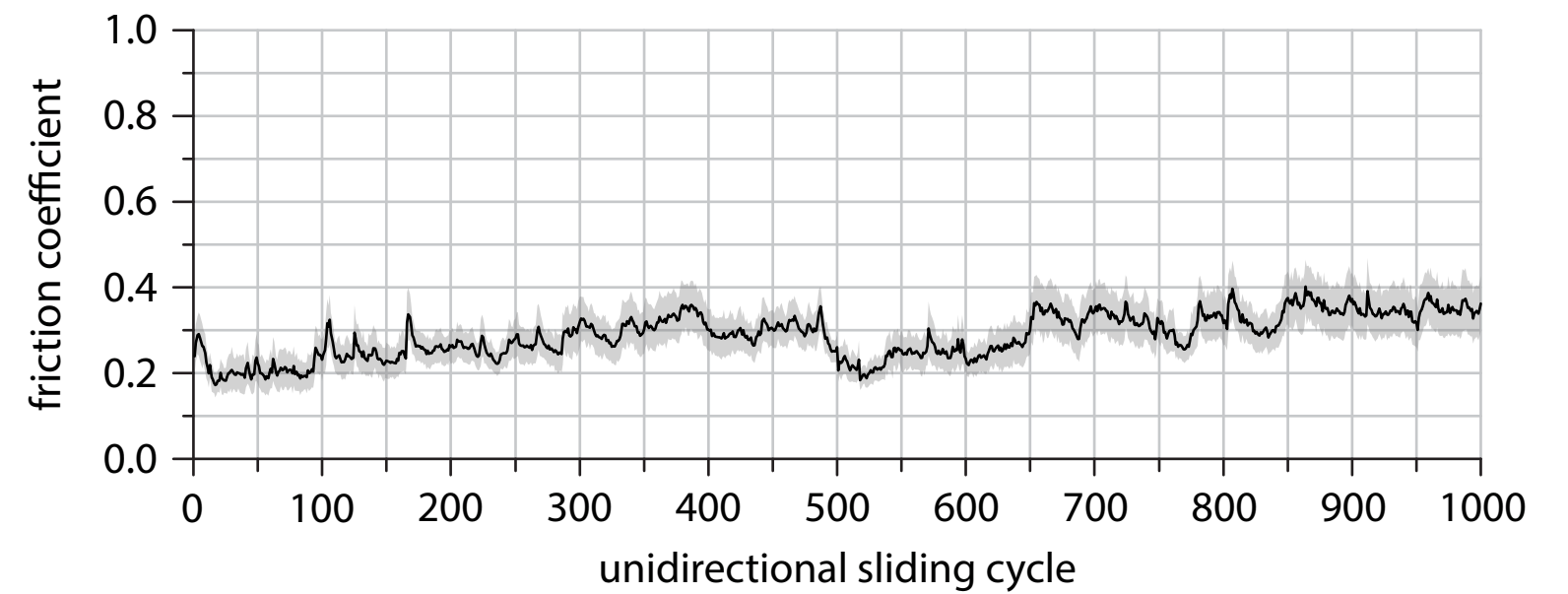
- sliding against a bulk hard gold alloy rider or pin (nominally 72-14-8-5-1 wt. % Au-Cu-Pt-Ag-Zn)
- rider tip radius was 3.175 mm
- contact force was 100 mN
- electrical probe current of 100 mA
- lab air at 21°C, sliding speed of 1 mm/s
- substrate material was alloy 52 (nominally 50/50 wt. % Fe/Ni)
- film thicknesses 2 - 5 μm ; Ti/Pt bonding layers

Wear comparison of electroplated hard gold and Au-ZnO -- against sapphire

electroplated type I hard gold sliding against sapphire



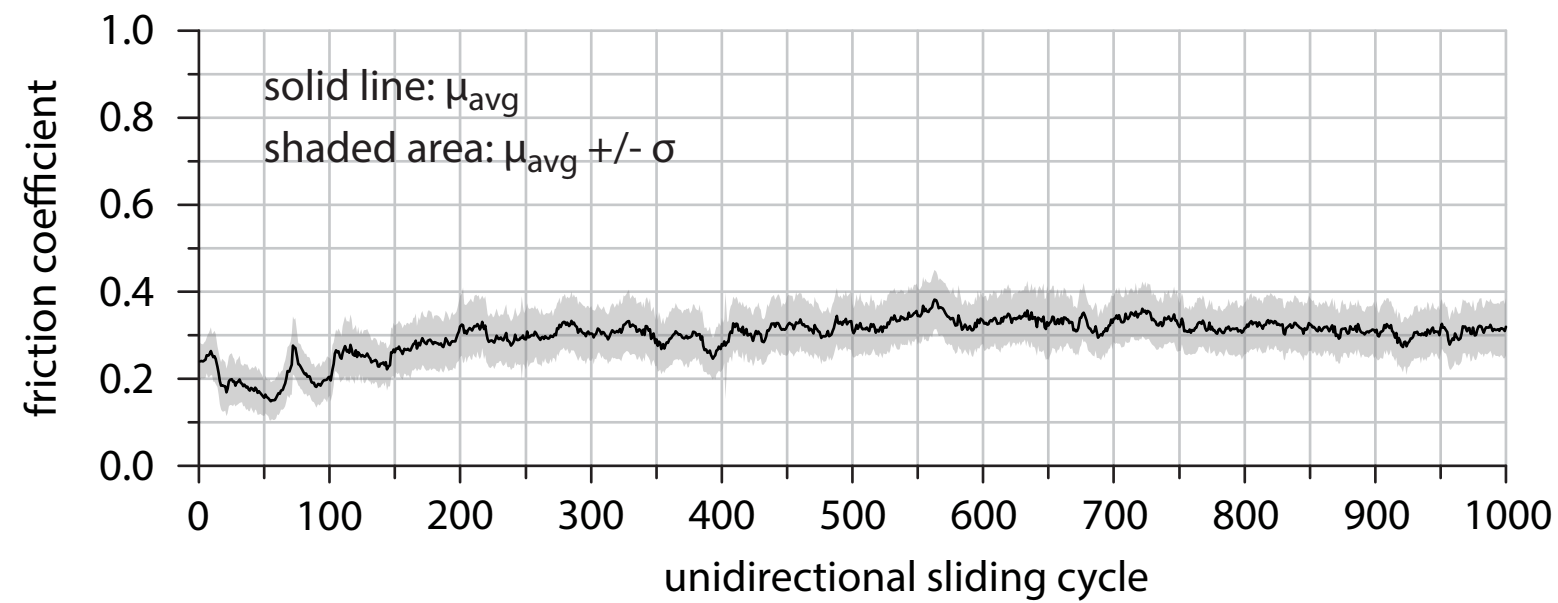
Au-5 vol. % ZnO sliding against sapphire



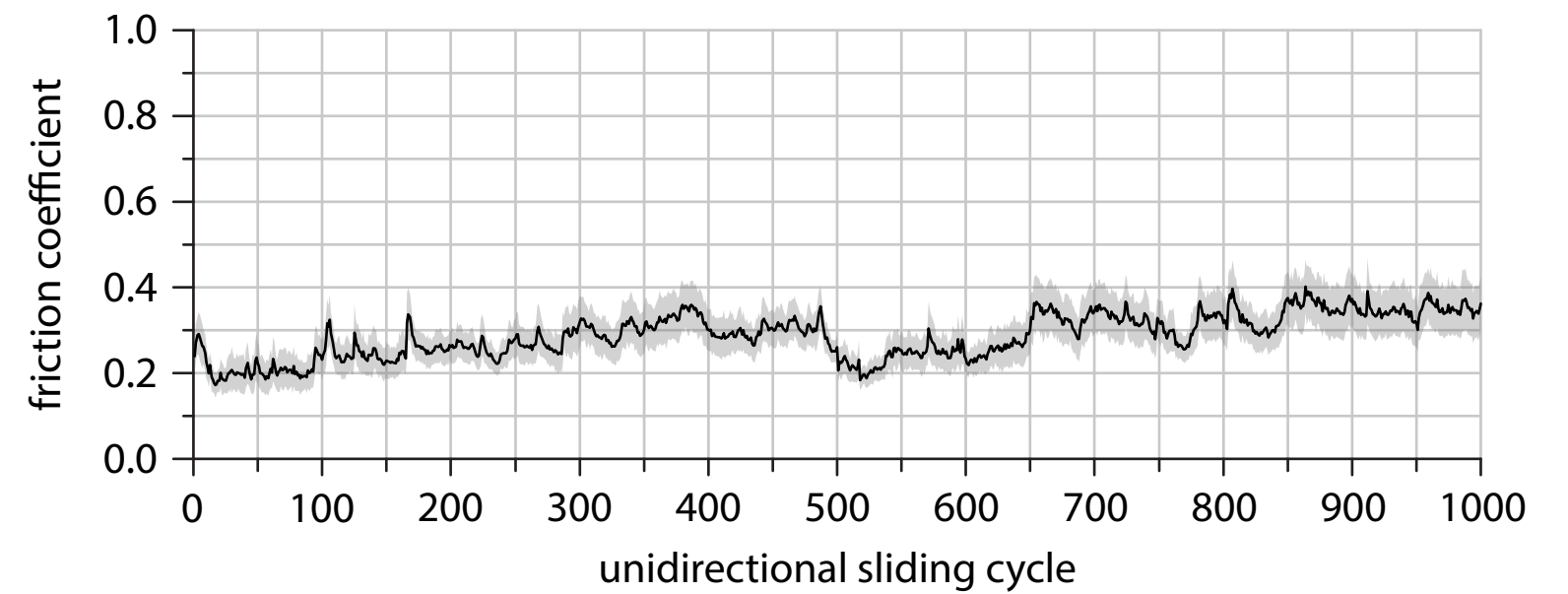
Now using 5 vol. % ZnO, sapphire ball radius of 1.59 mm, and contact force of 1N

Wear comparison of electroplated hard gold and Au-ZnO -- against sapphire

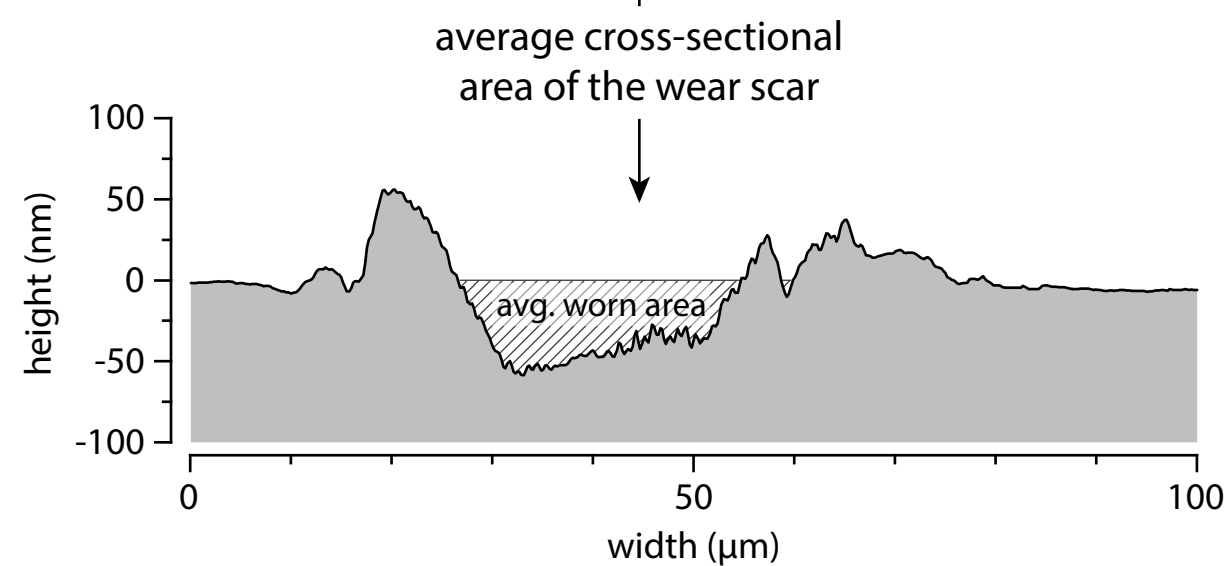
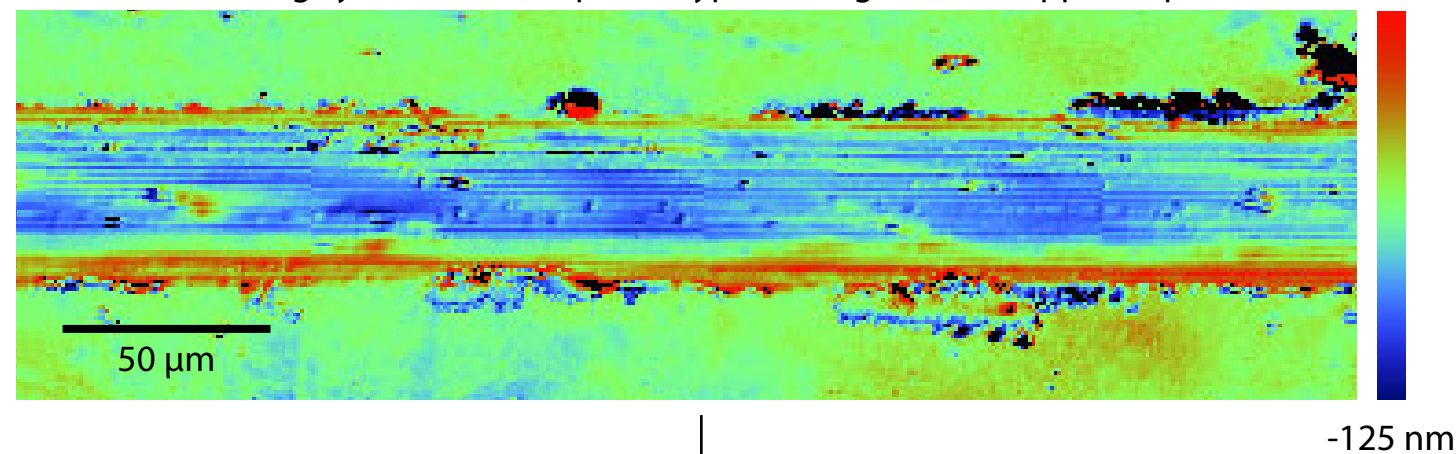
electroplated type I hard gold sliding against sapphire



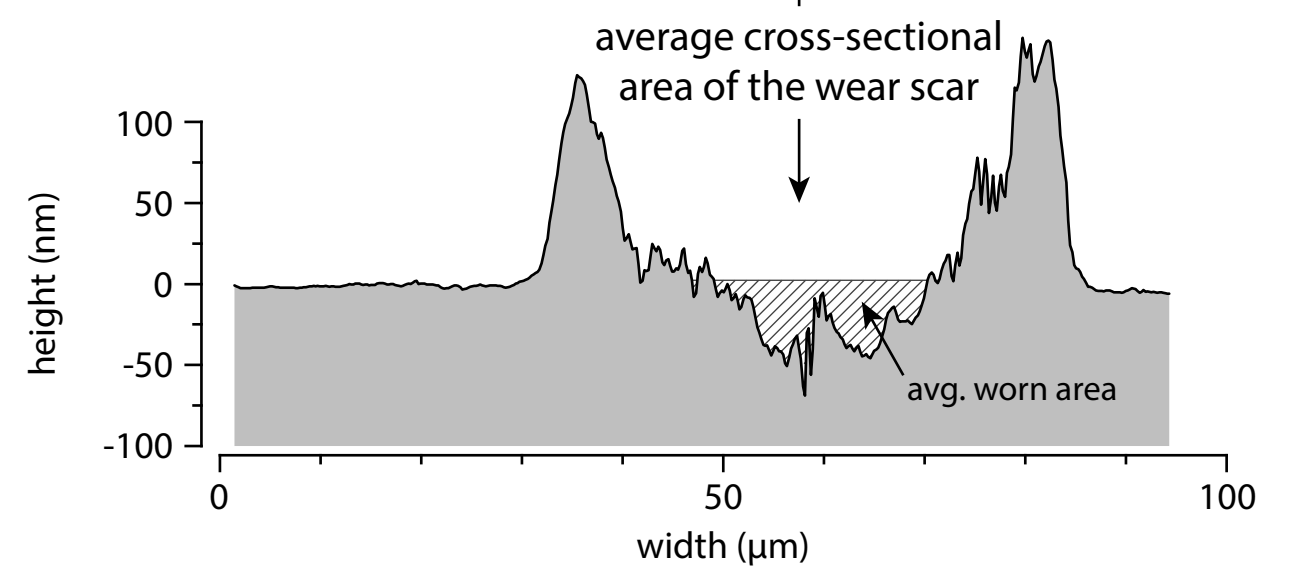
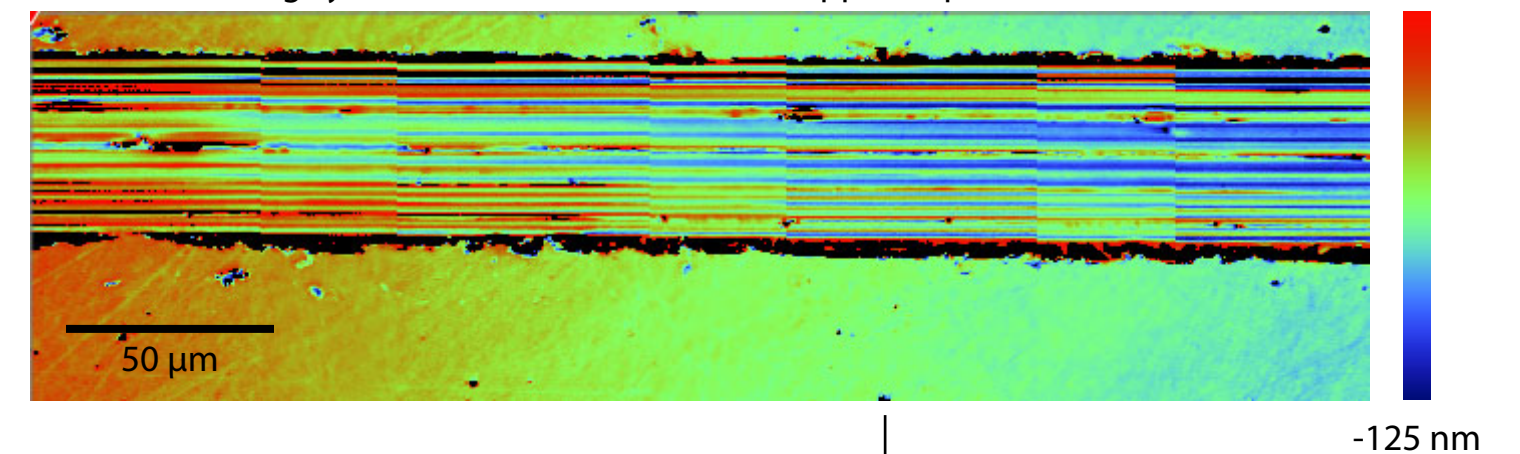
Au-5 vol. % ZnO sliding against sapphire



after 1,000 sliding cycles on electroplated type I hard gold with sapphire sphere

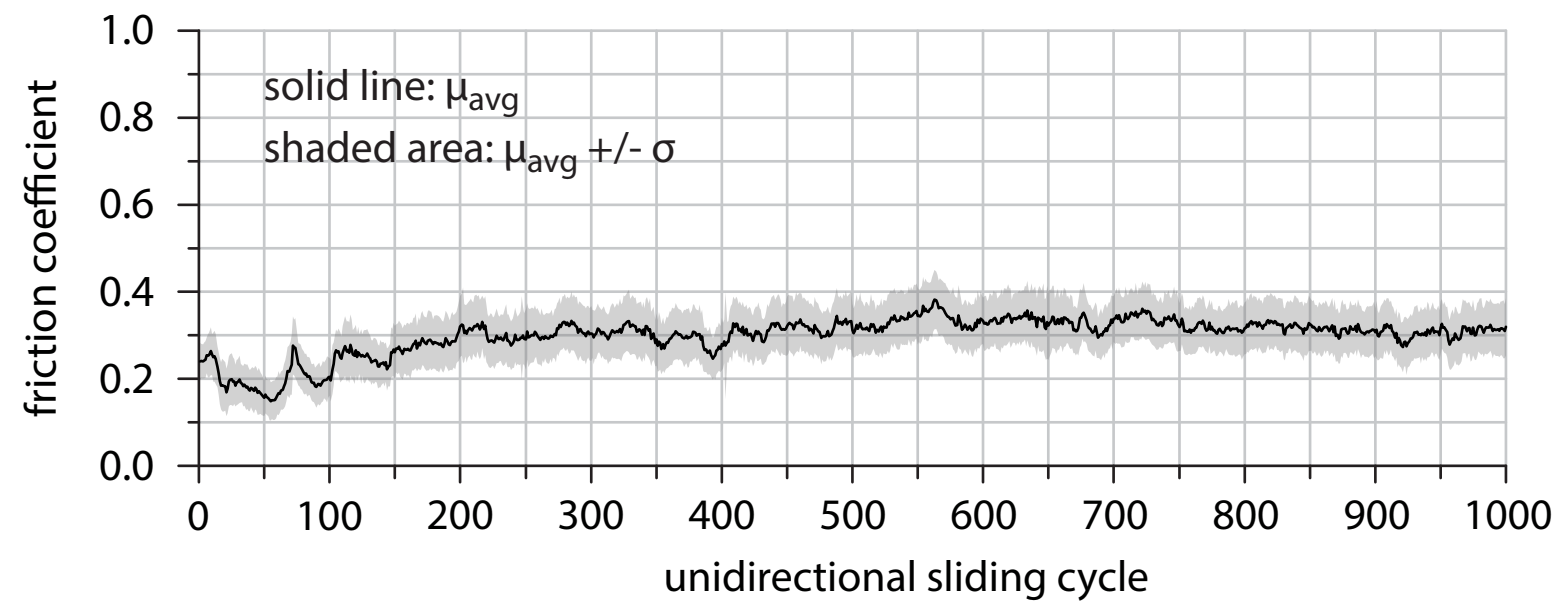


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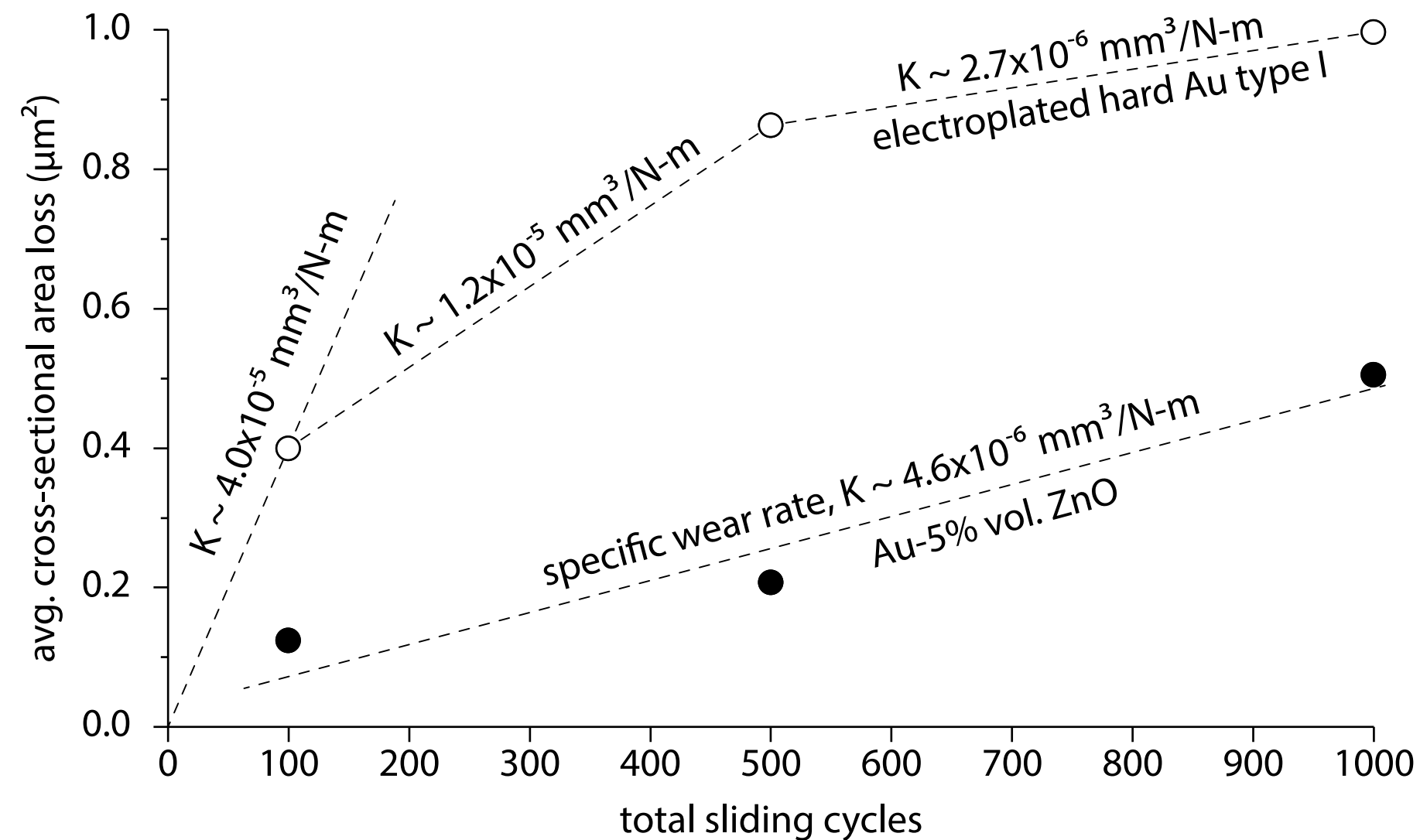
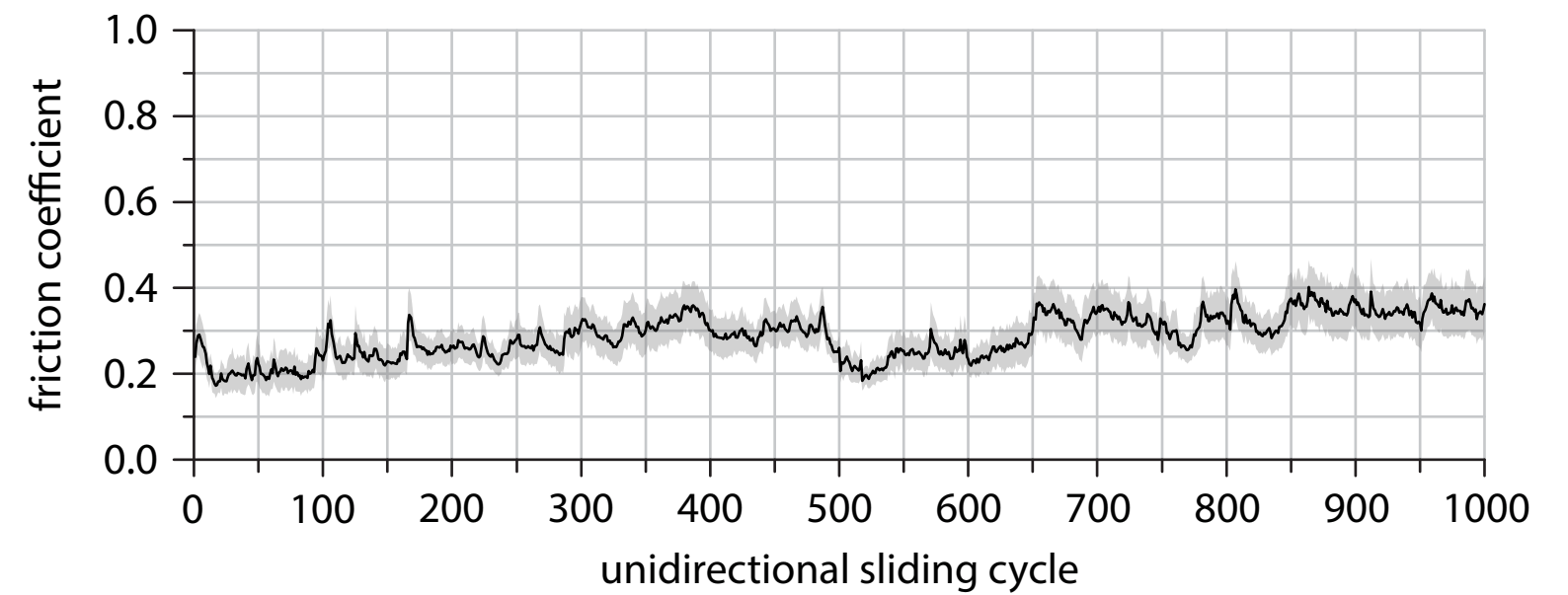


Au-ZnO nanocomposite shows similar wear behavior to electroplated hard Au

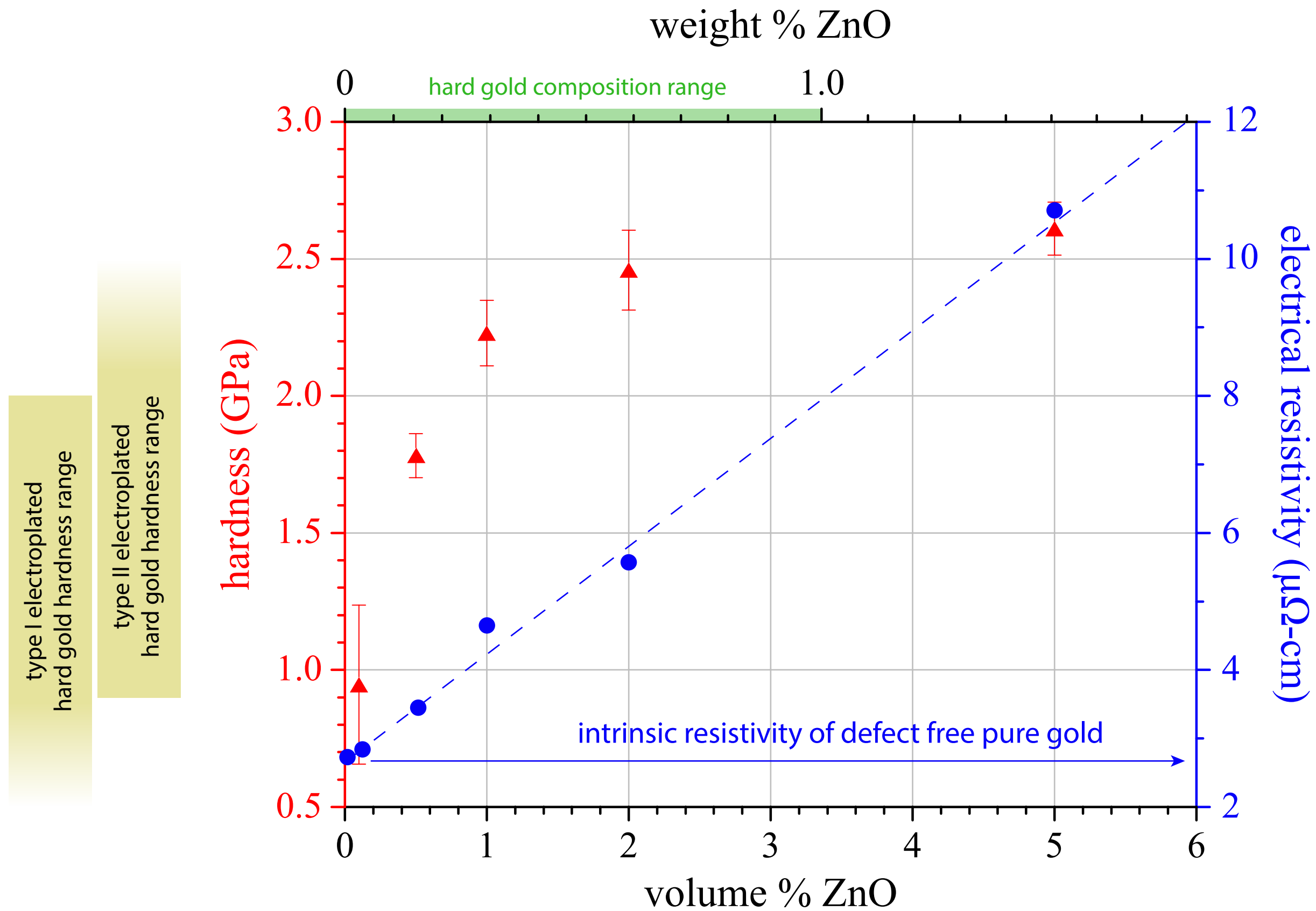
electroplated type I hard gold sliding against sapphire



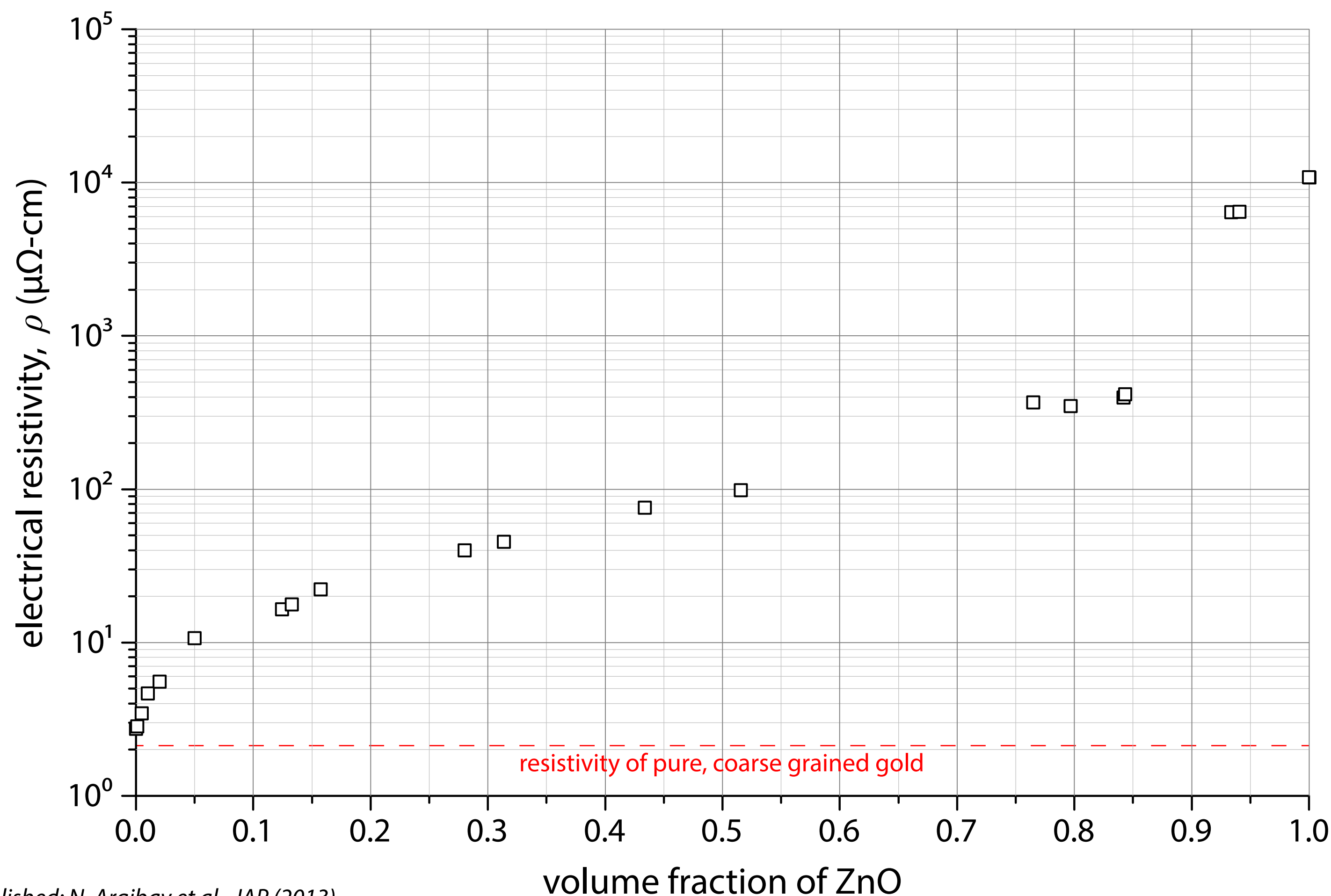
Au-5 vol. % ZnO sliding against sapphire



Hardness and electrical resistivity increase as function of composition

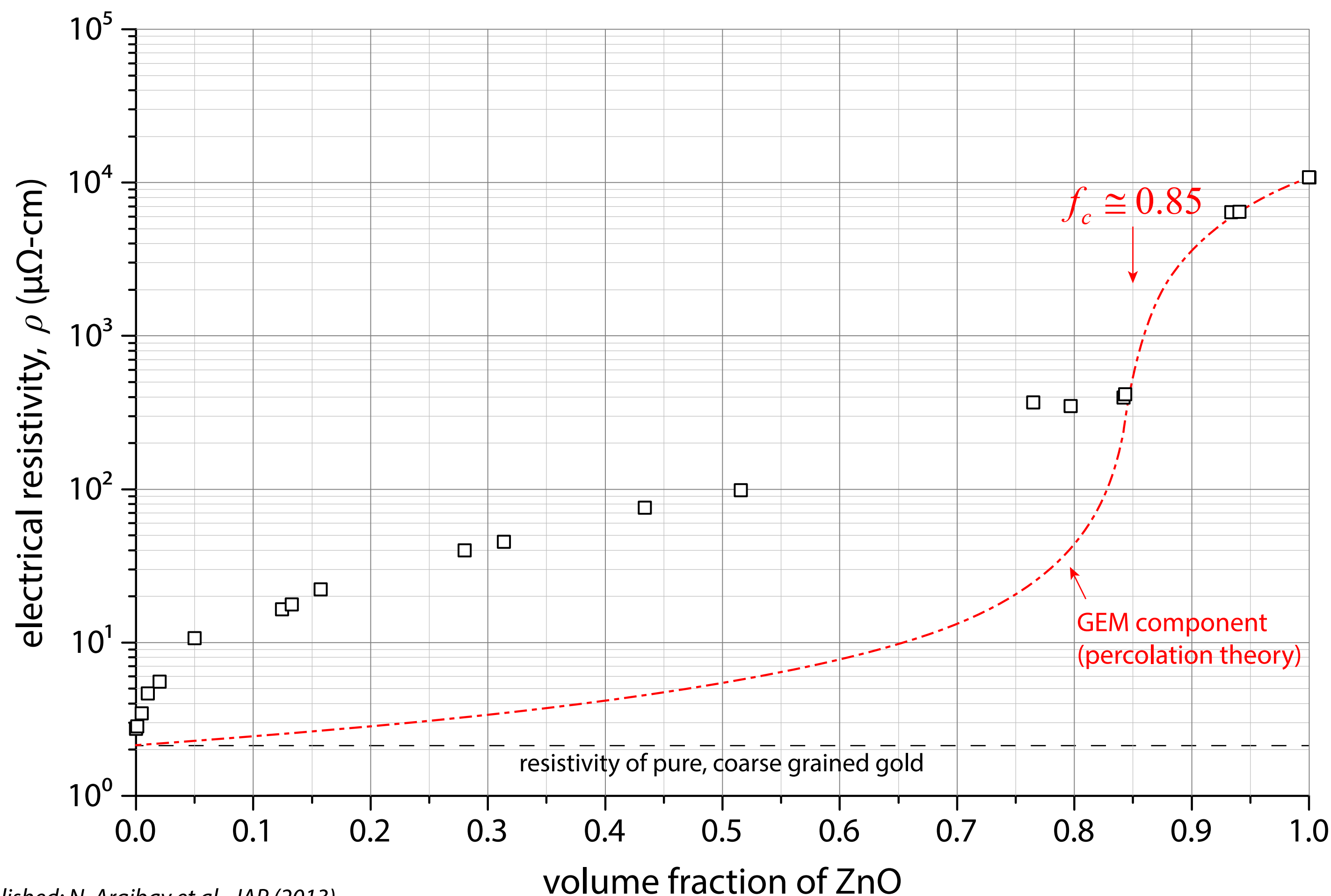


Au-ZnO Resistivity: combination of electron scattering at GBs and percolation theory



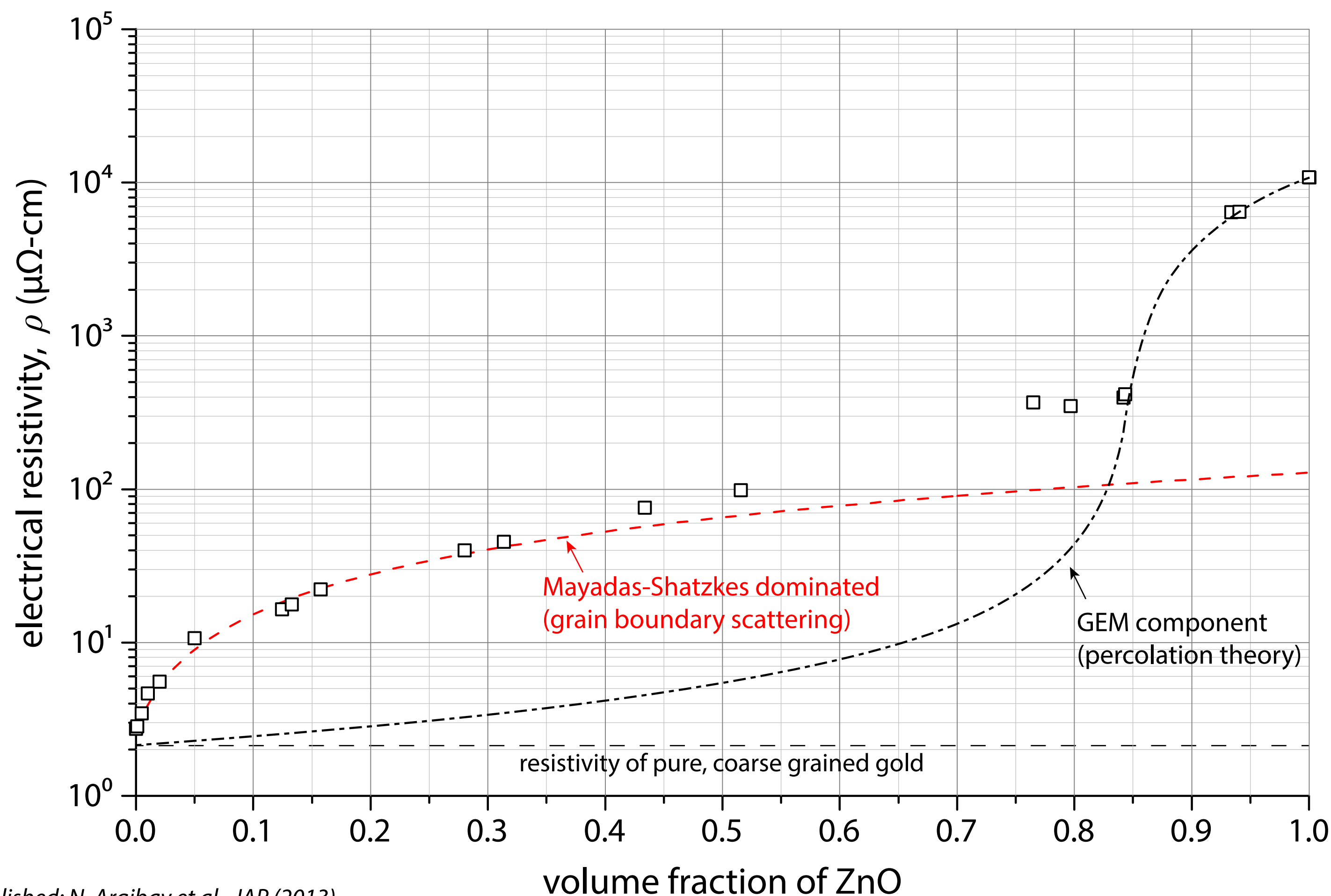
Published: N. Argibay et al., JAP (2013)

Au-ZnO Resistivity: combination of electron scattering at GBs and percolation theory



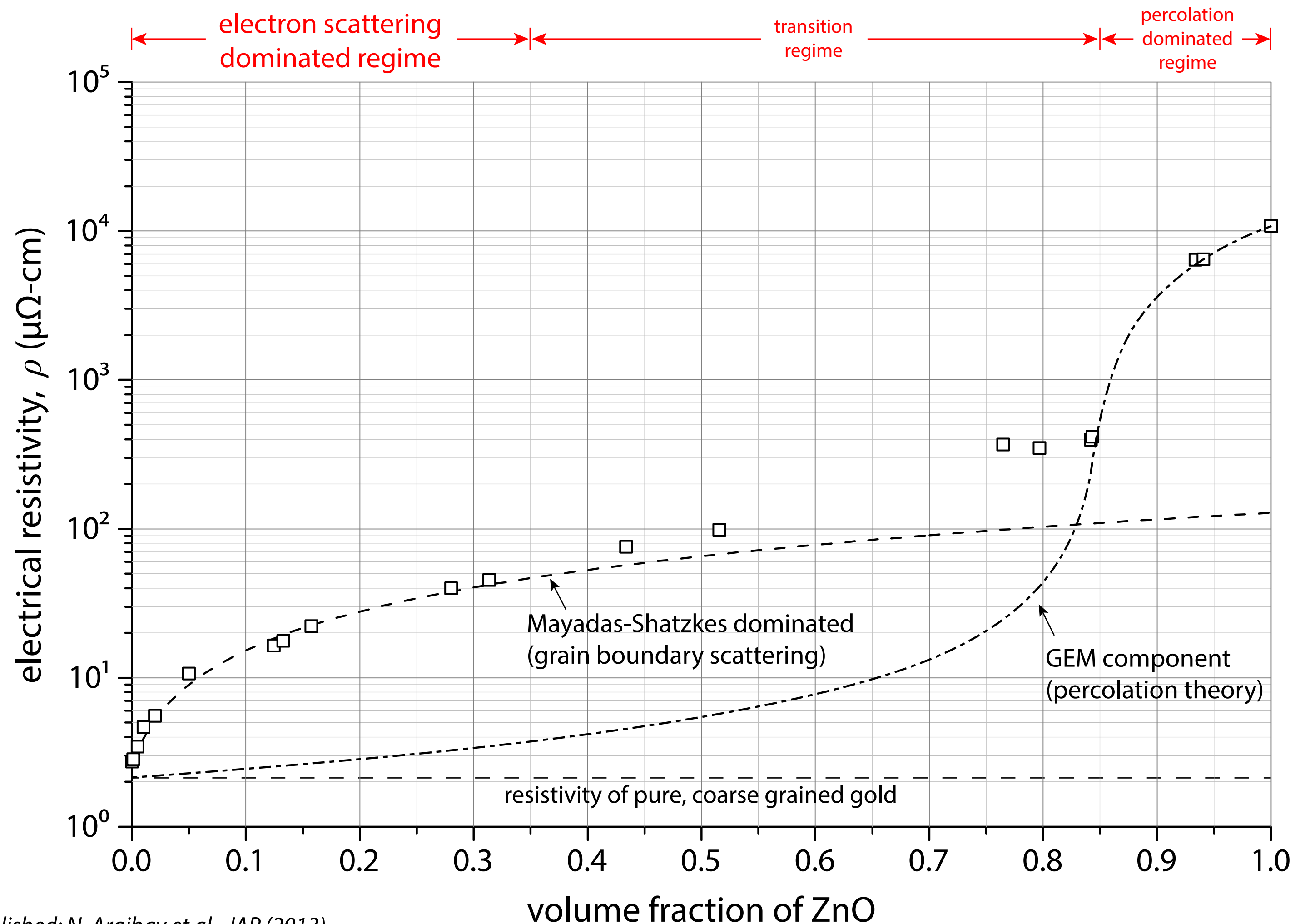
Published: N. Argibay et al., JAP (2013)

Au-ZnO Resistivity: combination of electron scattering at GBs and percolation theory



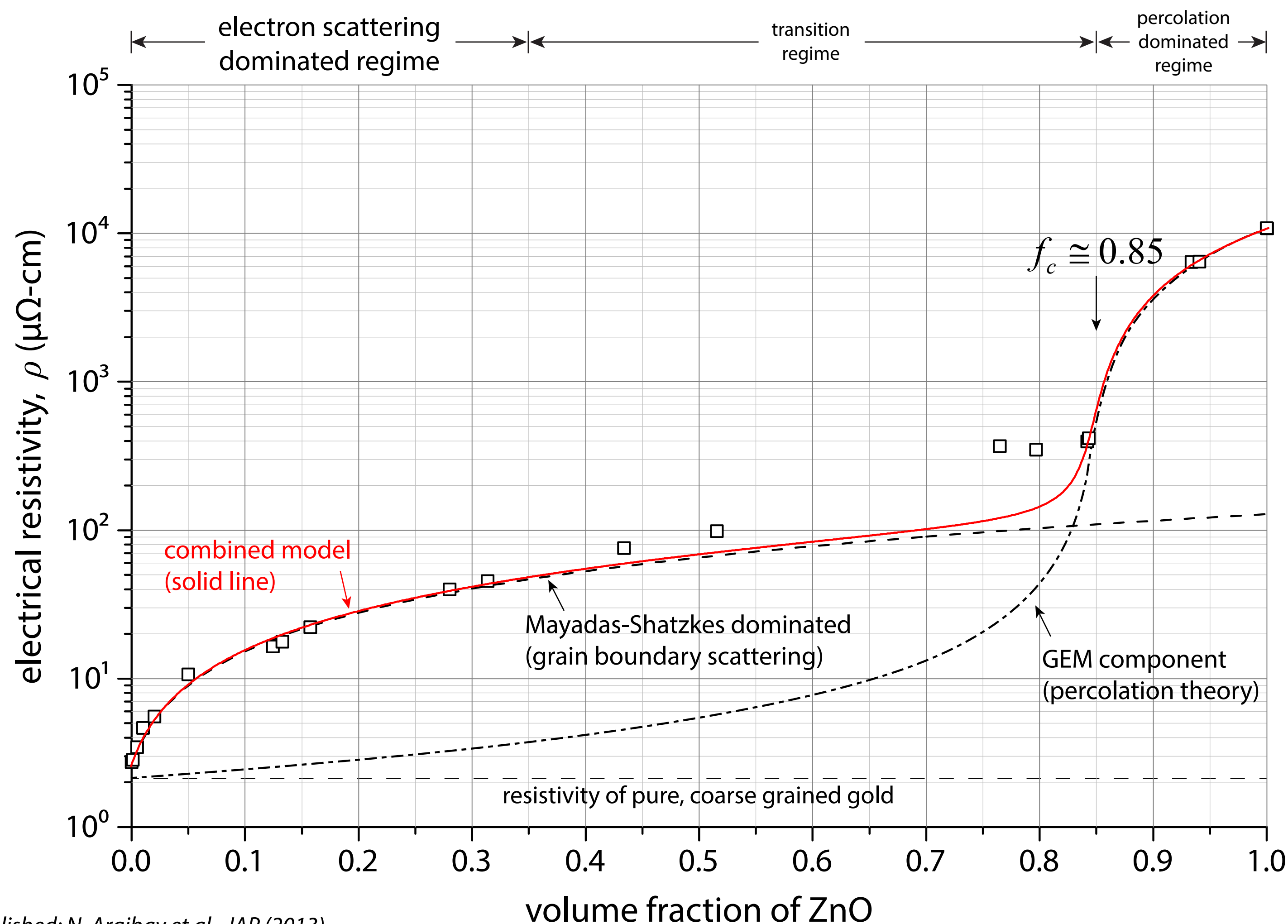
Published: N. Argibay et al., JAP (2013)

Au-ZnO Resistivity: combination of electron scattering at GBs and percolation theory



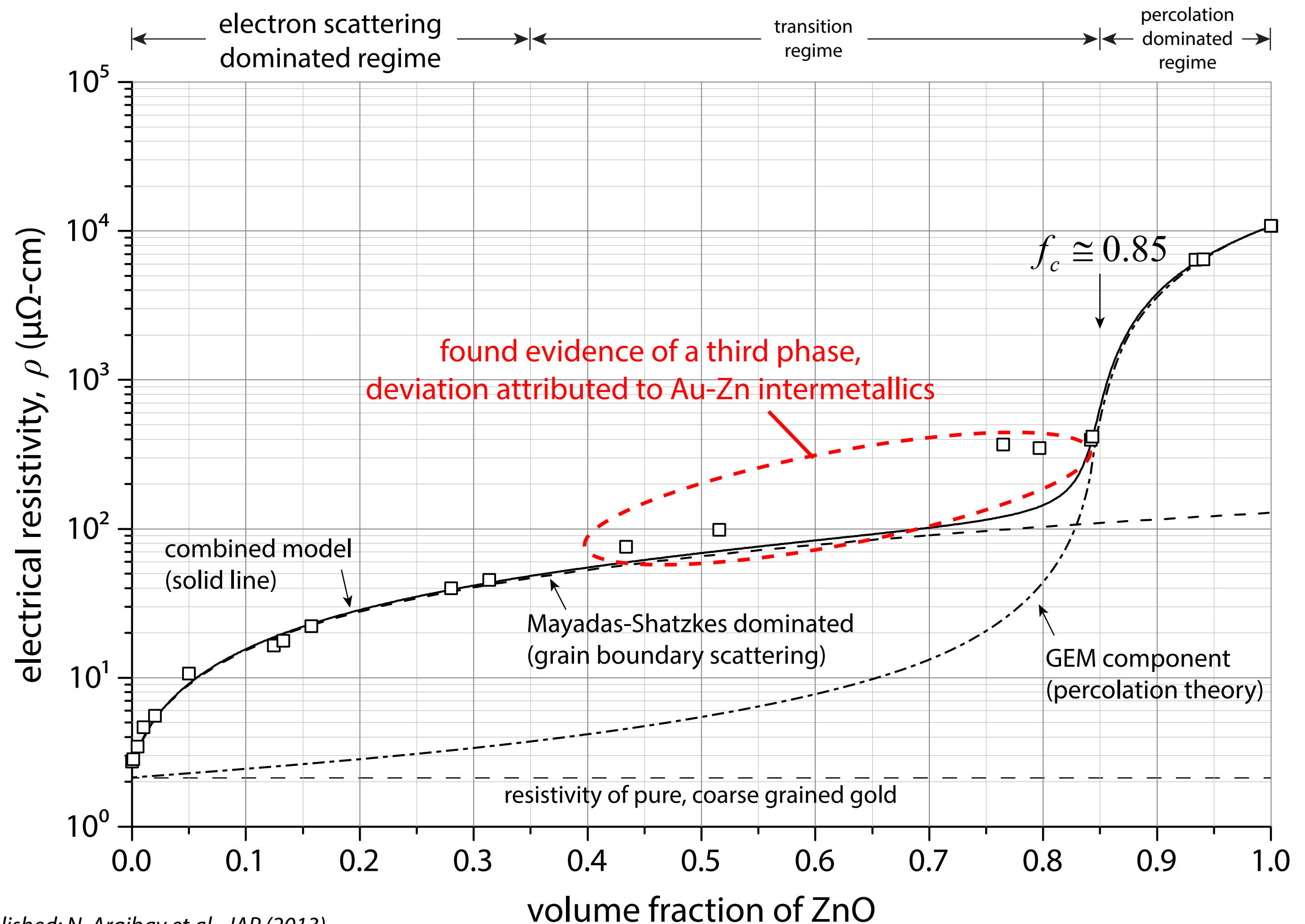
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Au-ZnO Resistivity: combination of electron scattering at GBs and percolation theory

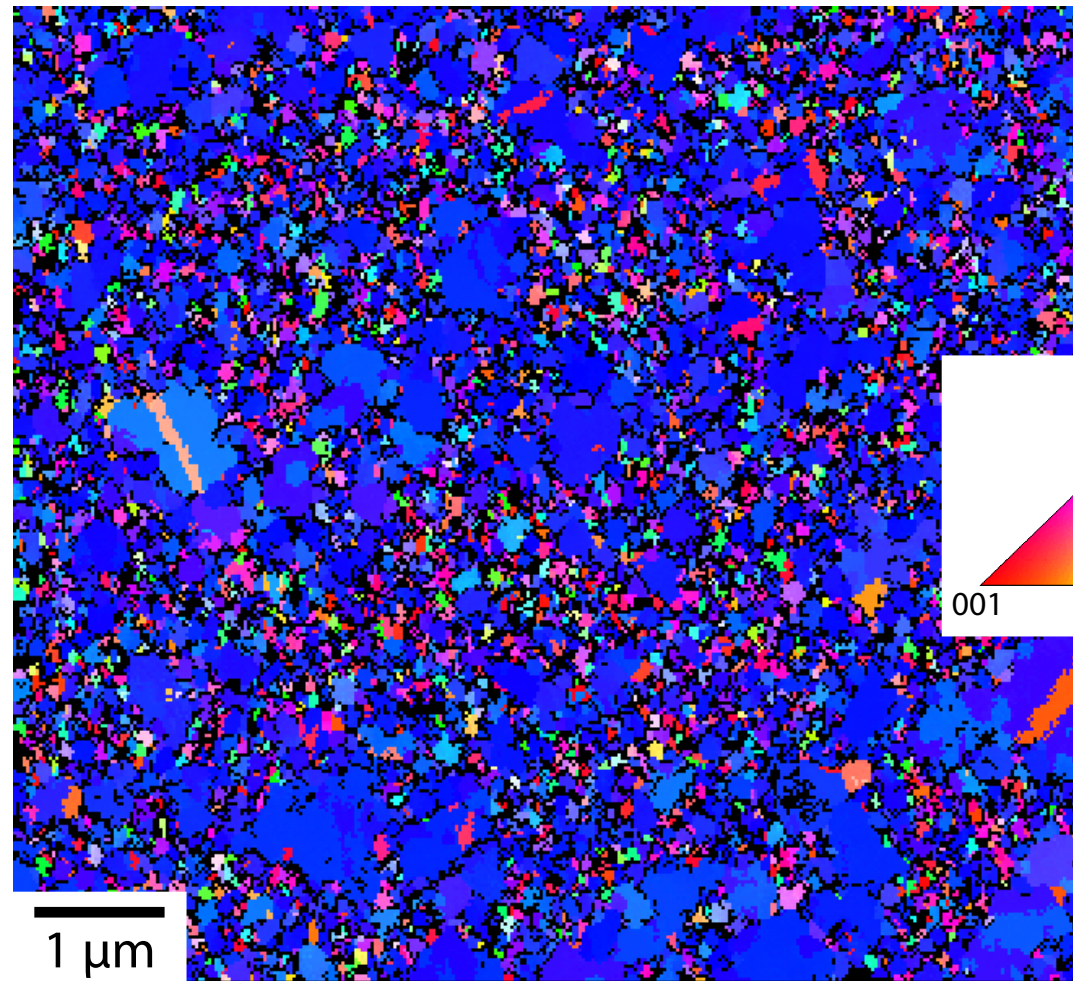


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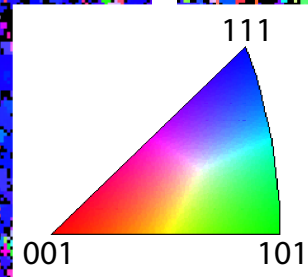
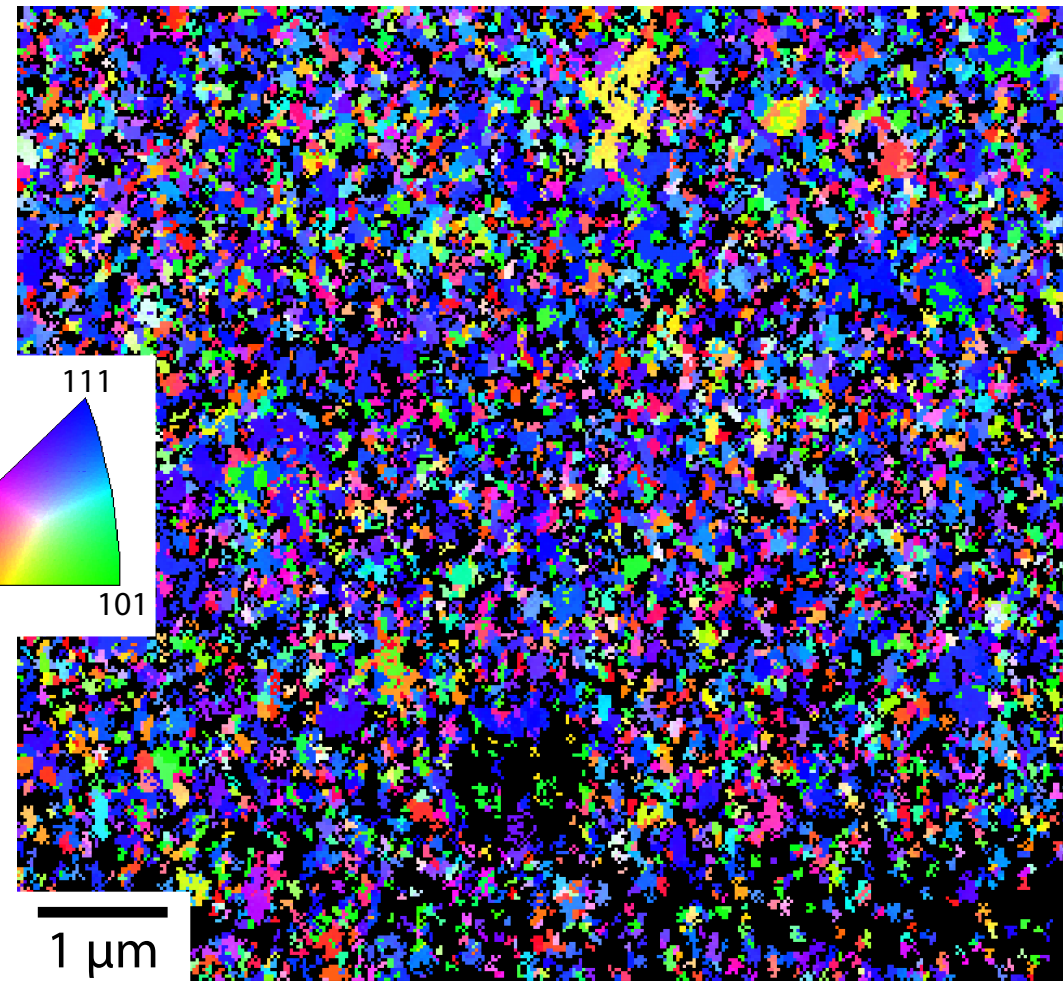
Determination of grain size with varying composition via microscopy

Film surface-normal EBSD mapping:

pure Au film

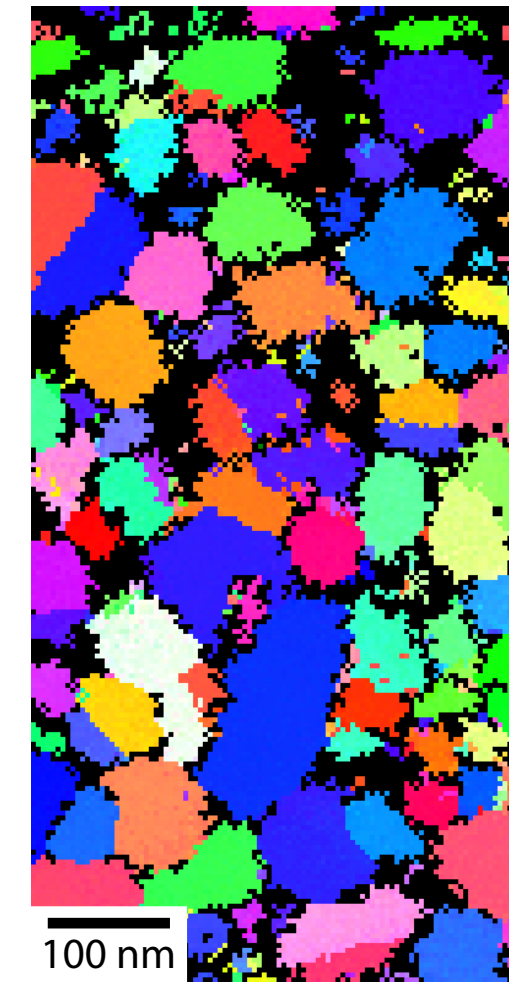


0.1 vol. % ZnO film

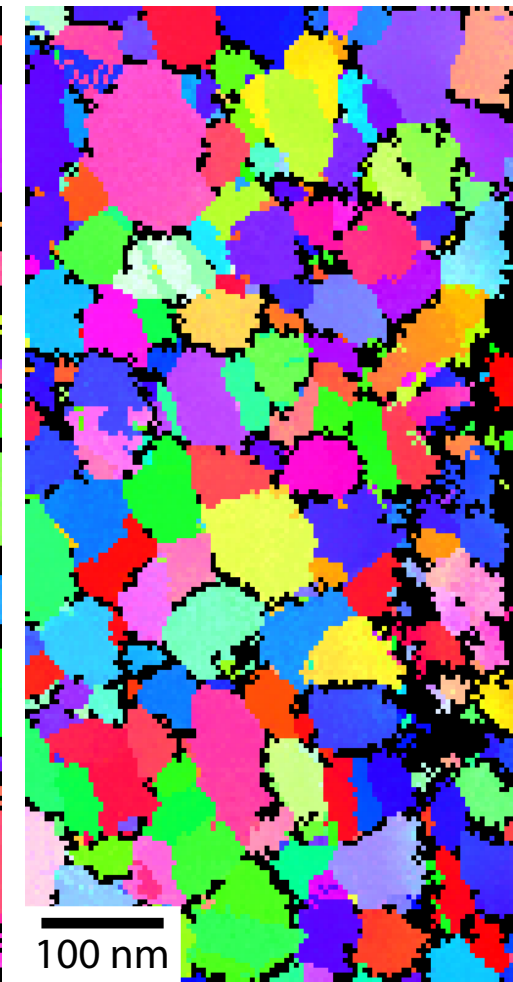


Transmission Kikuchi diffraction:

1.0 vol. % ZnO film

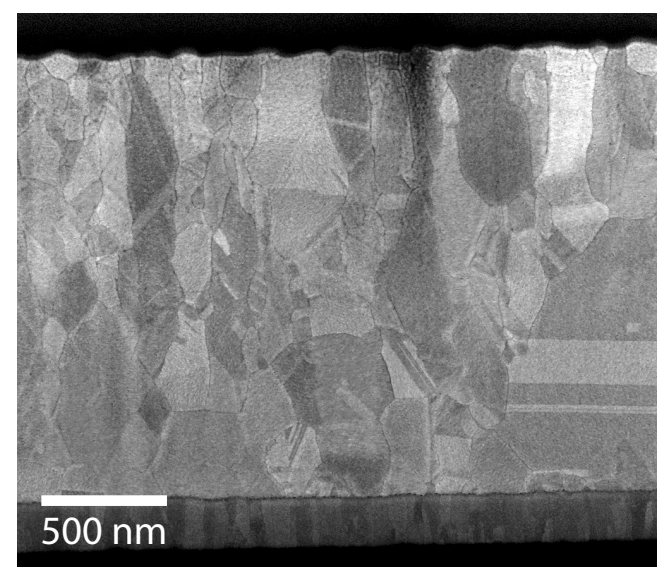


2.0 vol. % ZnO film

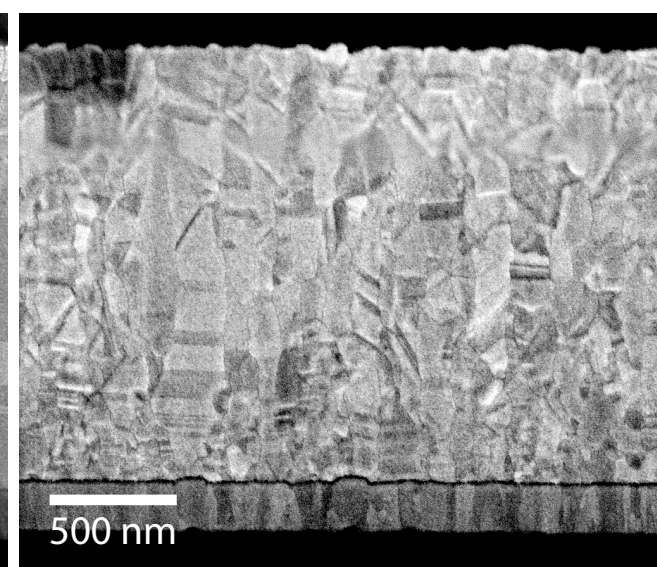


SEM of FIB milled and etched cross-sectional views:

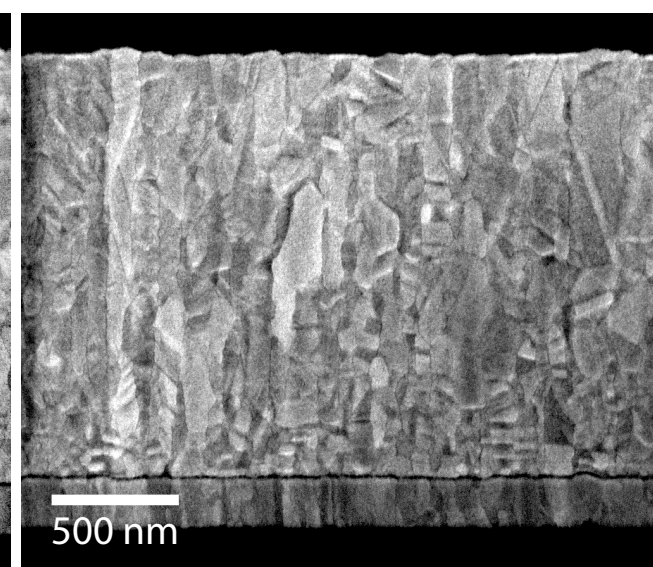
Increasing ZnO concentration →



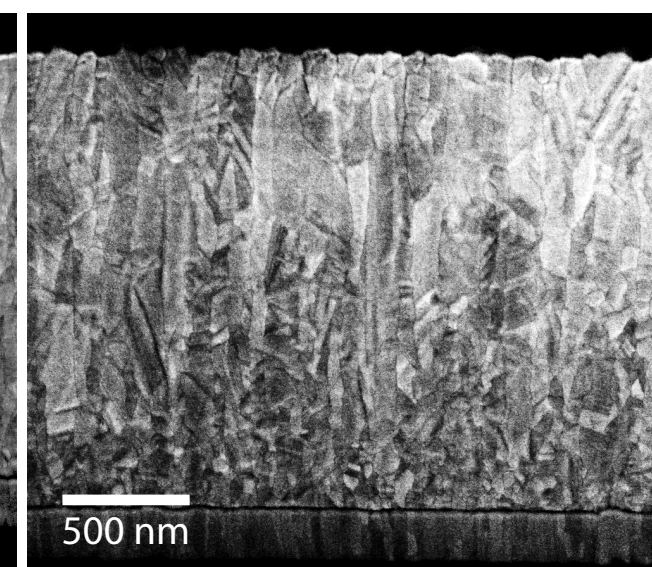
0.1 vol. % ZnO film



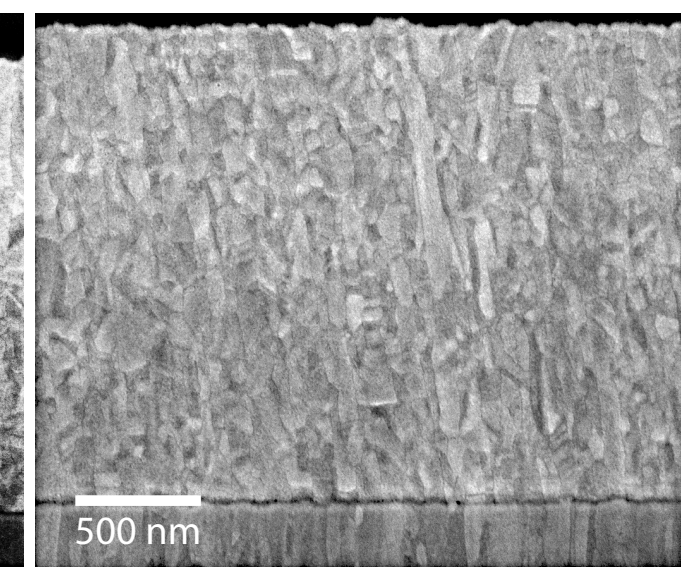
0.5 vol. % ZnO film



1.0 vol. % ZnO film



2.0 vol. % ZnO film



5.0 vol. % ZnO film

High throughput indirect method -- correlation b/w electrical resistivity/grain size

Mayadas-Shatzkes model (electron scattering at GBs):

$$\frac{\rho}{\rho_o} = \left[1 - \frac{3}{2}\alpha + 3\alpha^2 - 3\alpha^3 \ln\left(1 + \frac{1}{\alpha}\right) \right]^{-1}$$

Scattering parameter:

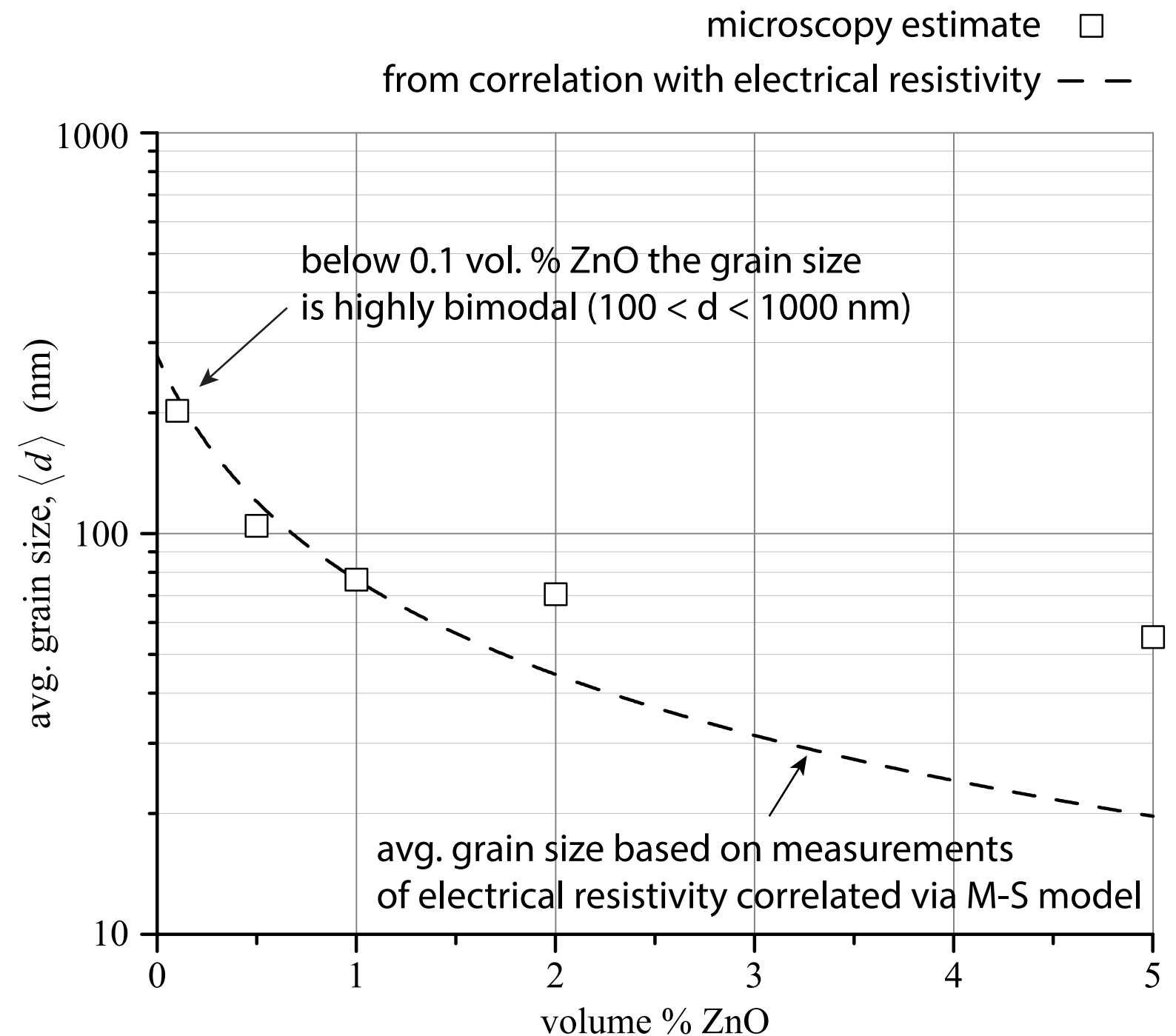
$$\alpha = \frac{\lambda}{d} \frac{R}{1-R}$$

Empirical relationship between scattering parameter and composition is linear:

$$\alpha = 43.19f + 0.165$$

Between 0 and 30 vol. % ZnO, M-S seems to fit well, corresponding to a range:

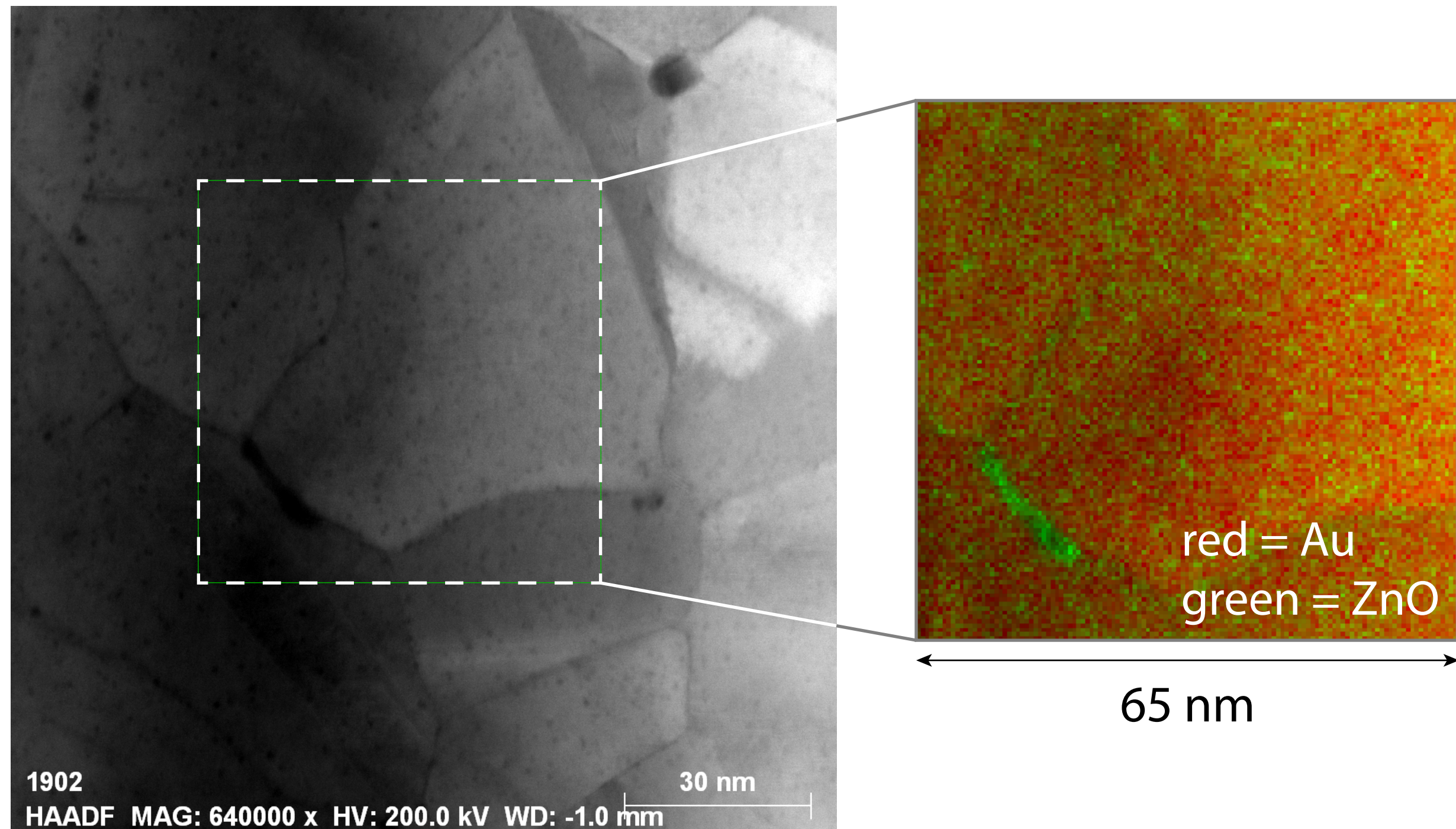
$$0.1 < \alpha < 10$$



Is it possible to confidently correlate grain size to resistivity via scattering parameter?

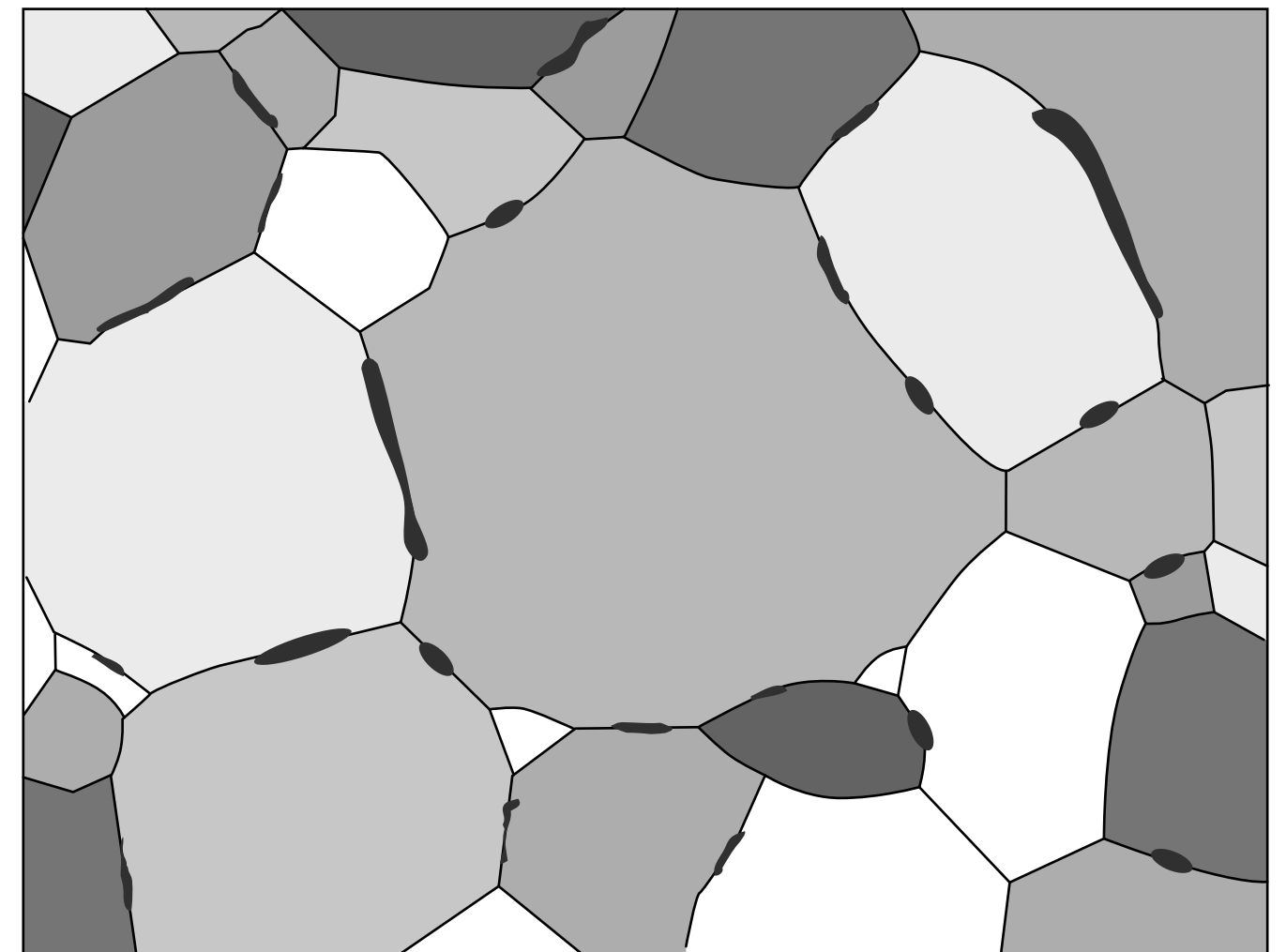
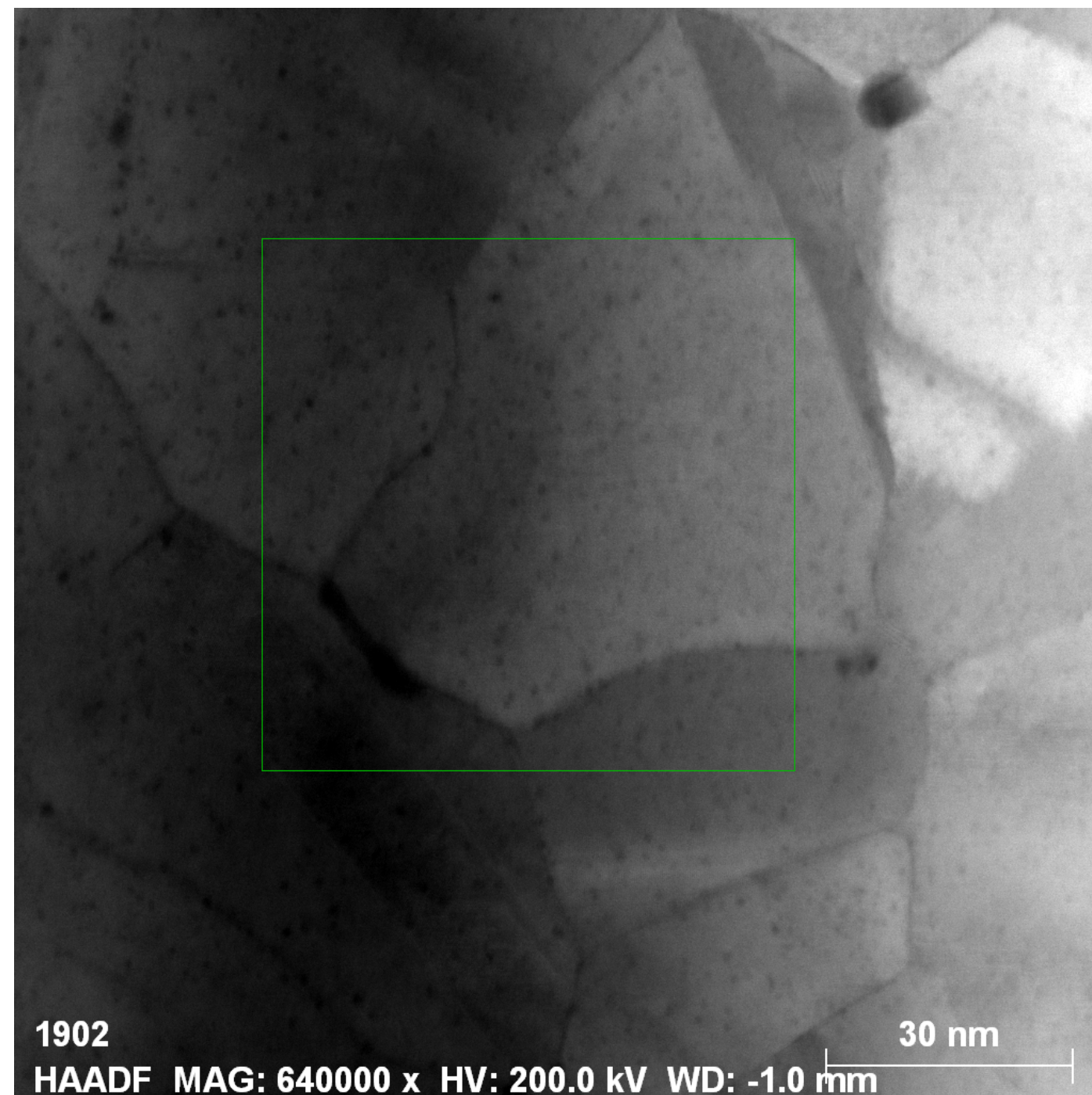
Film Surface-Planar STEM Composition Mapping -- Confirms GB Segregation

Cross-sectional composition map of a Au- 5 vol. % ZnO film showing grain boundary segregated ZnO in a Au matrix



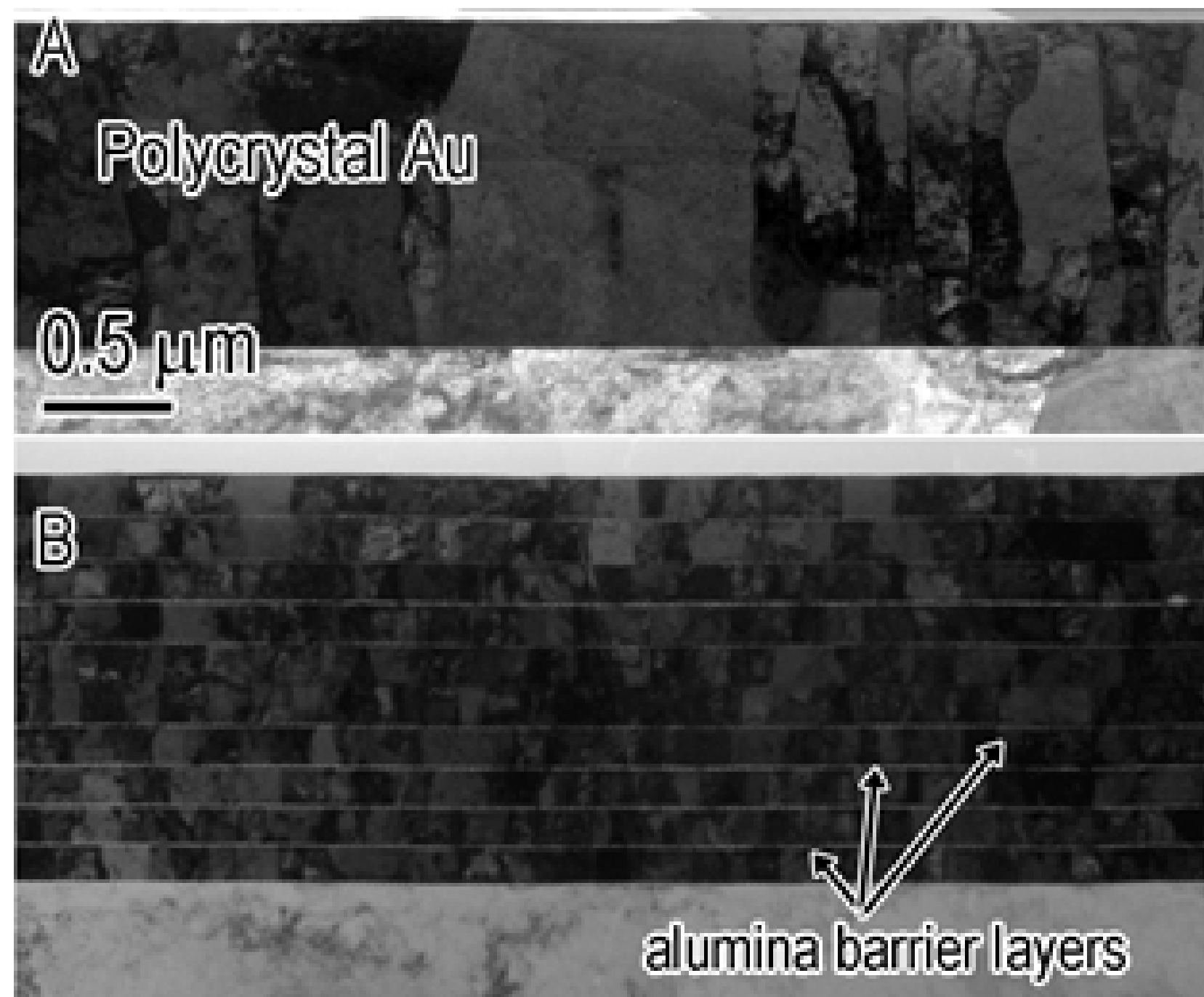
Zener pinning GB segregated second phase limits grain growth

Cross-sectional composition map of a Au- 5 vol. % ZnO film showing grain boundary segregated ZnO in a Au matrix



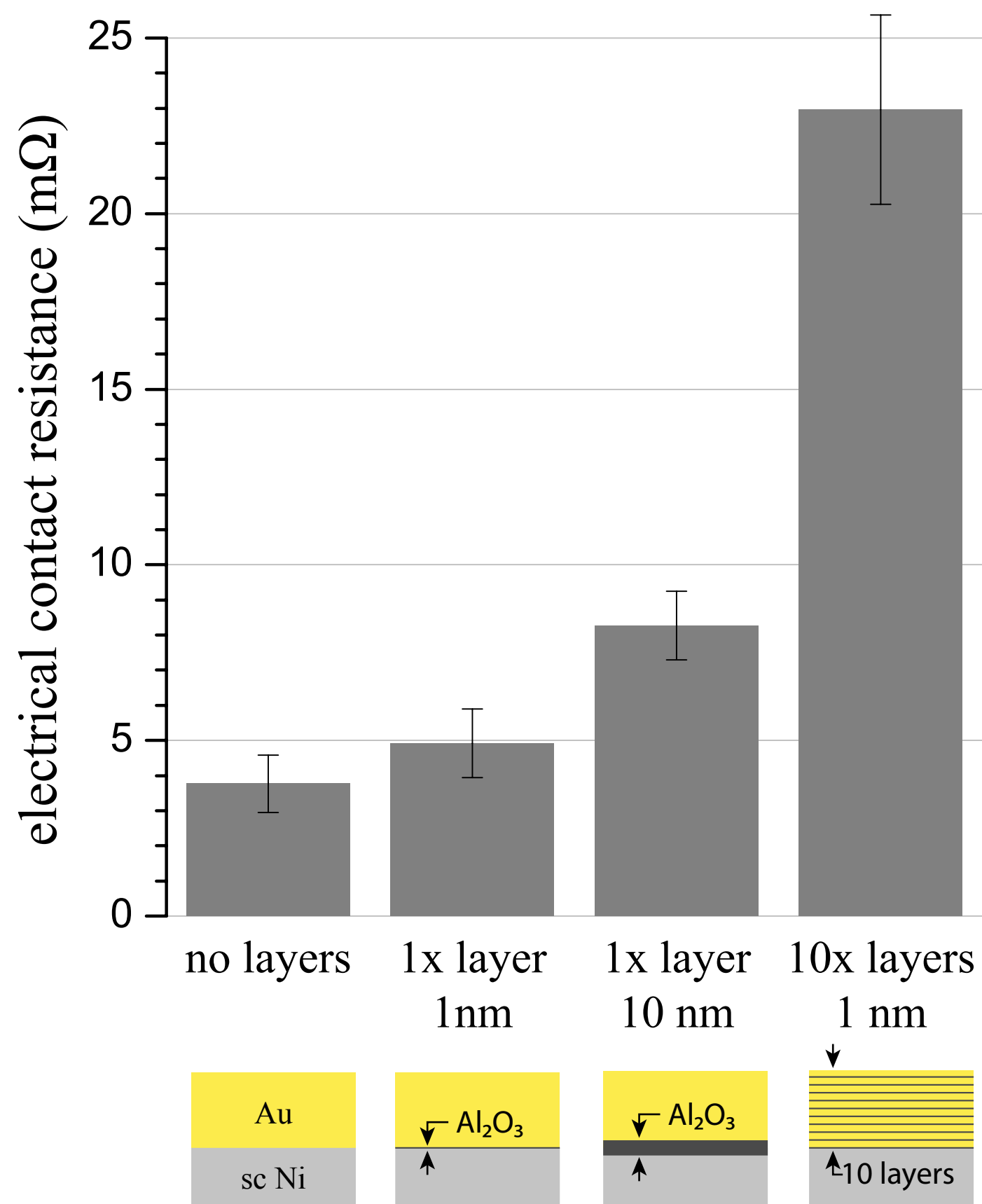
Investigation of ceramic diffusion barriers via pulsed laser deposition (PLD)

Au and Au/Al₂O₃ single and multi-layer films on PLD deposited onto single crystal nickel substrate

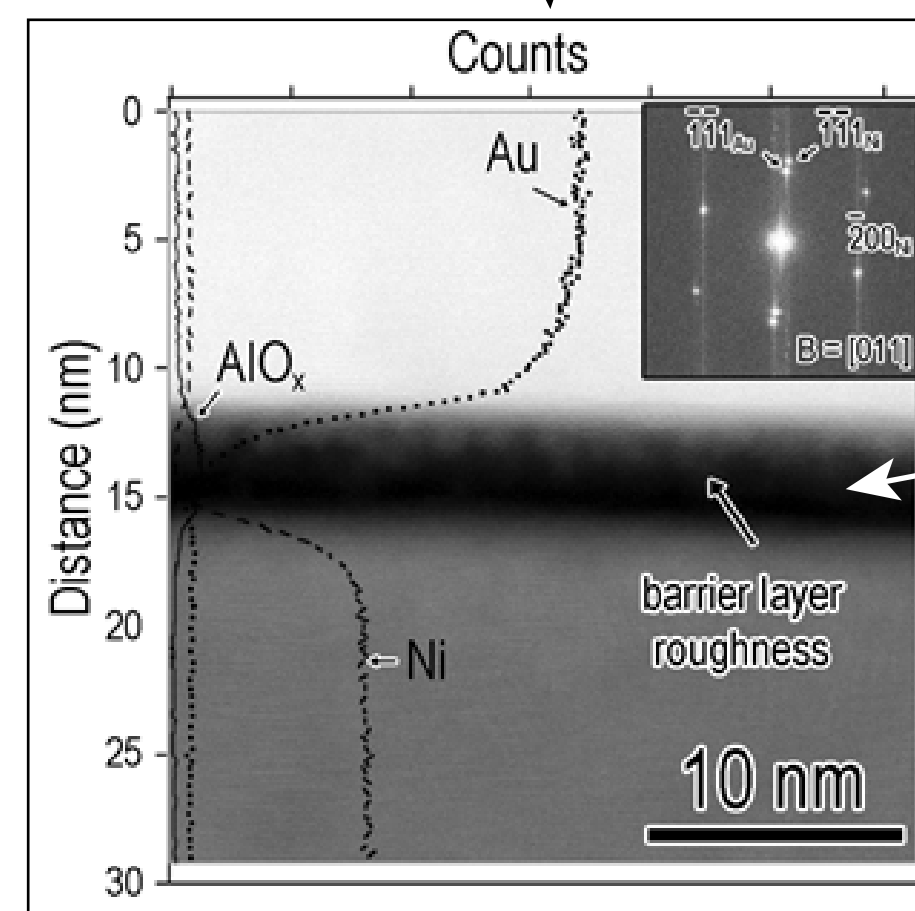
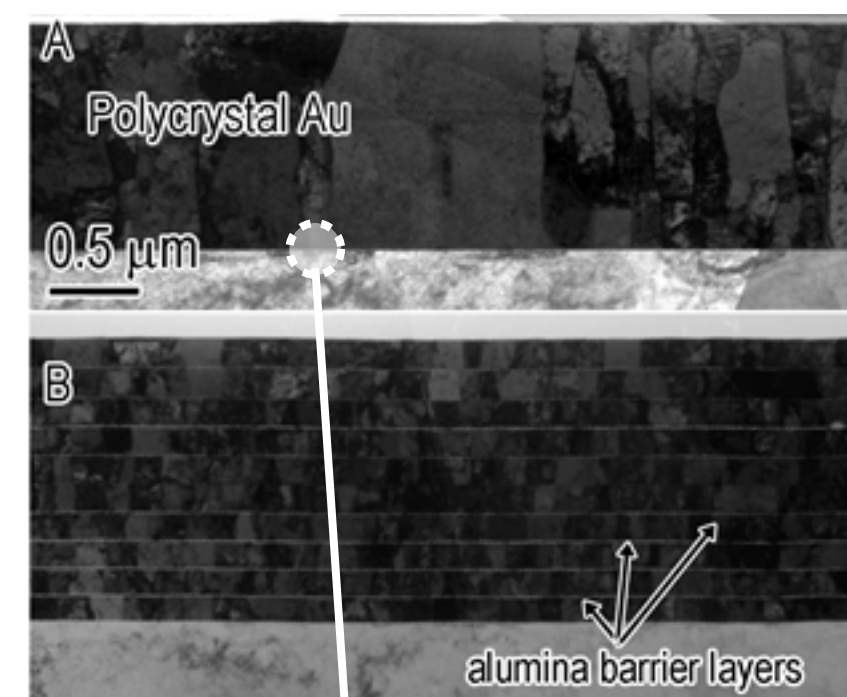


The ECR increase with oxide barrier (Al_2O_3) film was low

experimental data: contact resistance



Au and $\text{Au}/\text{Al}_2\text{O}_3$ single and multi-layer films on PLD deposited onto single crystal nickel substrate



... likely AlO_x

STEM image of $\text{Au}/\text{Al}_x\text{O}_y/\text{Ni}$ interface

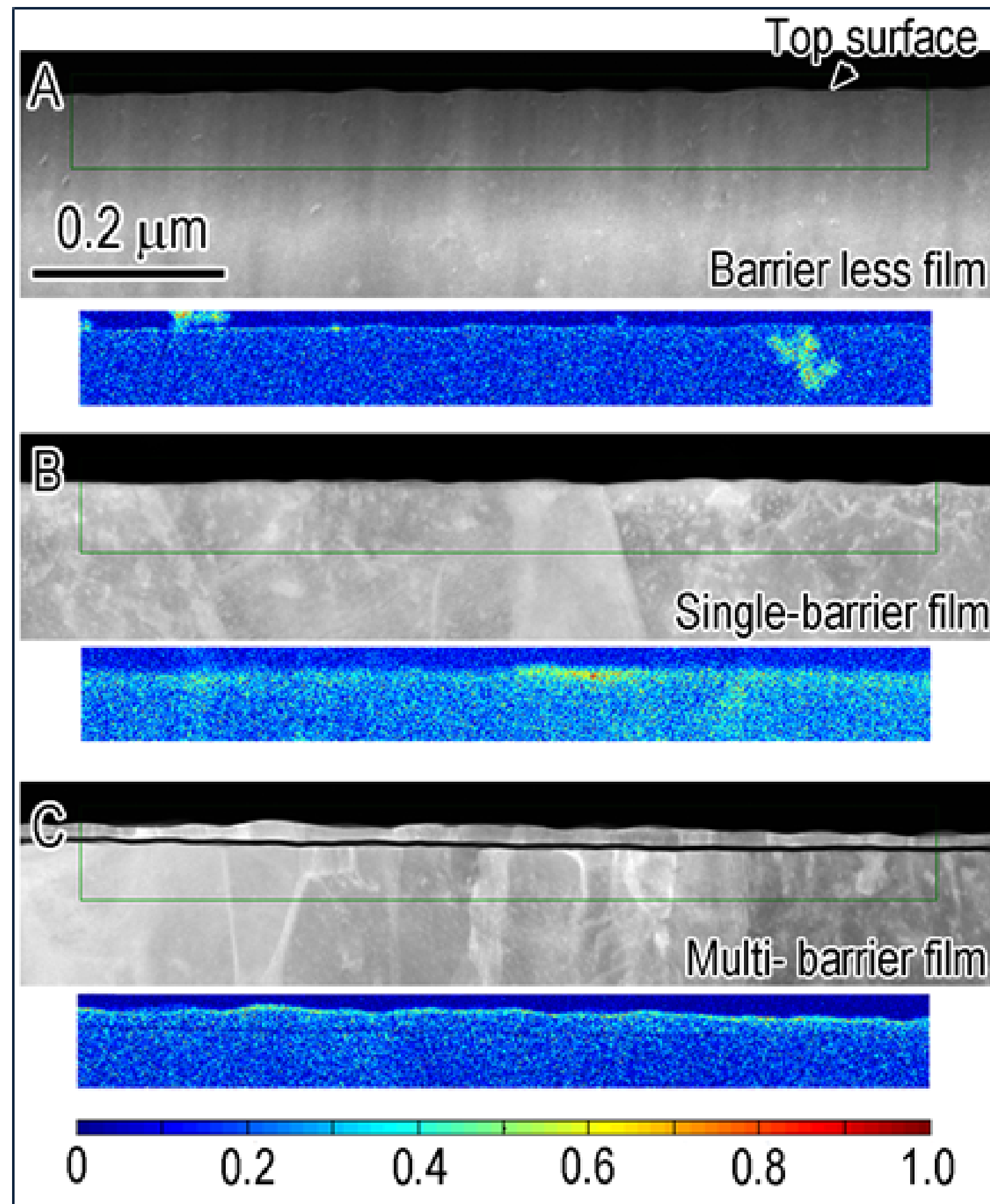
Surface accumulation of Ni reduced with alumina diffusion barrier layers

cross-section TEM of films after 5 day anneal at 250°C:

no barrier layer film,
but single crystal gold
(templated) top layer
on single crystal nickel
substrate

1 nm thick AlO_x barrier
layer, polycrystal Au
top layer

ten 1 nm thick AlO_x
barrier layers,
polycrystal Au
top layer

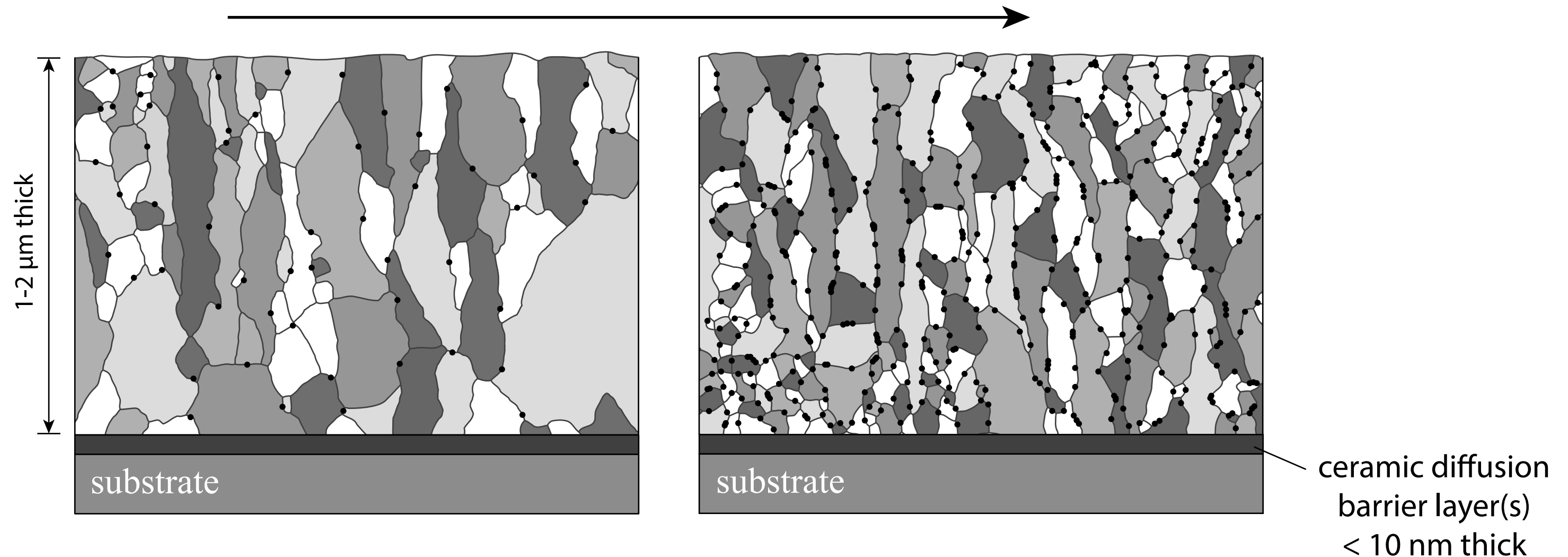


fractional concentration of Ni-O

Summary: E-beam codeposited Au-ceramic films and graded/layered structures

Nanocrystalline noble metal tribofilms strengthened via GB segregated codeposited ceramic phase(s)

reduced grain size (strengthening) with increasing ceramic phase concentration



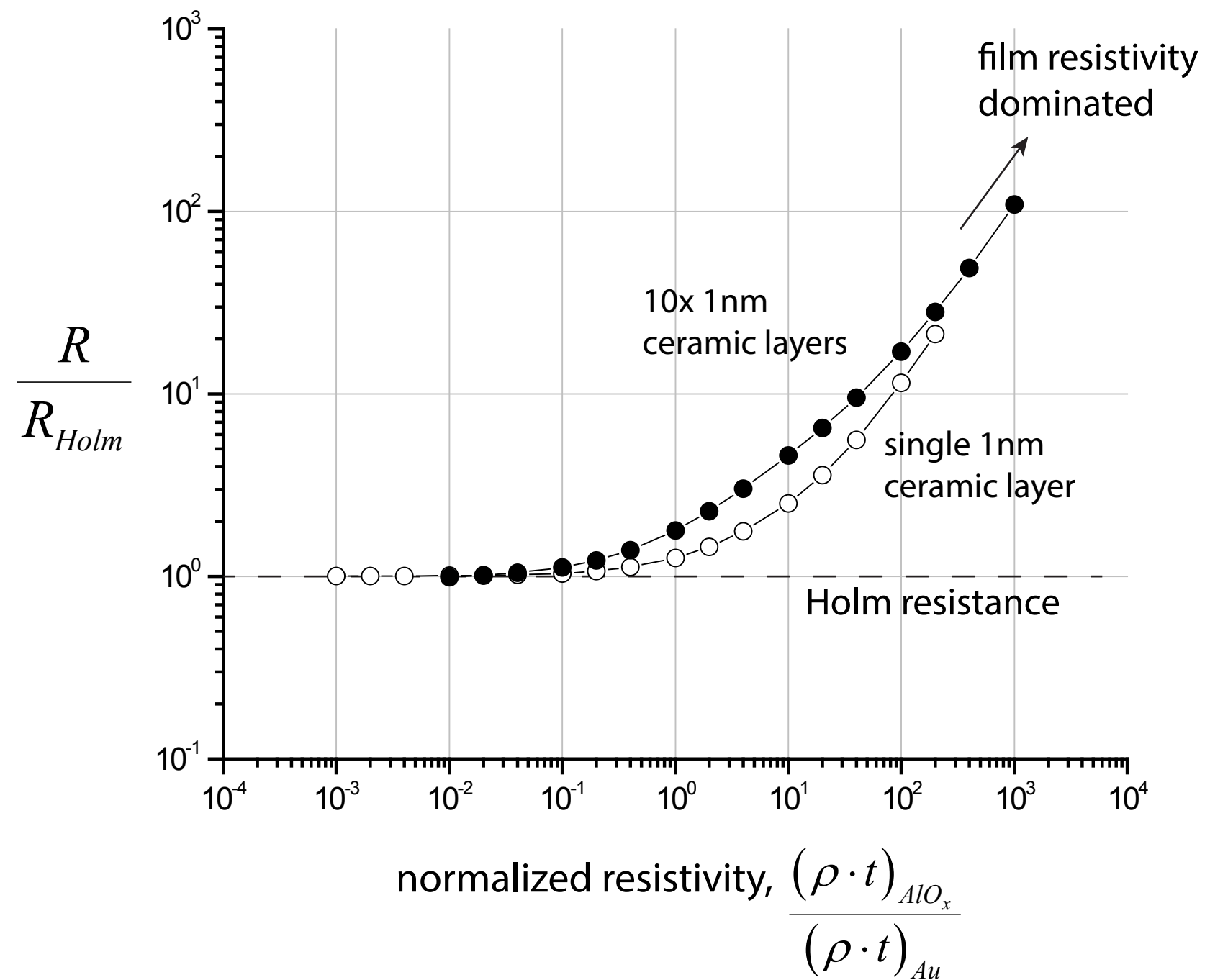
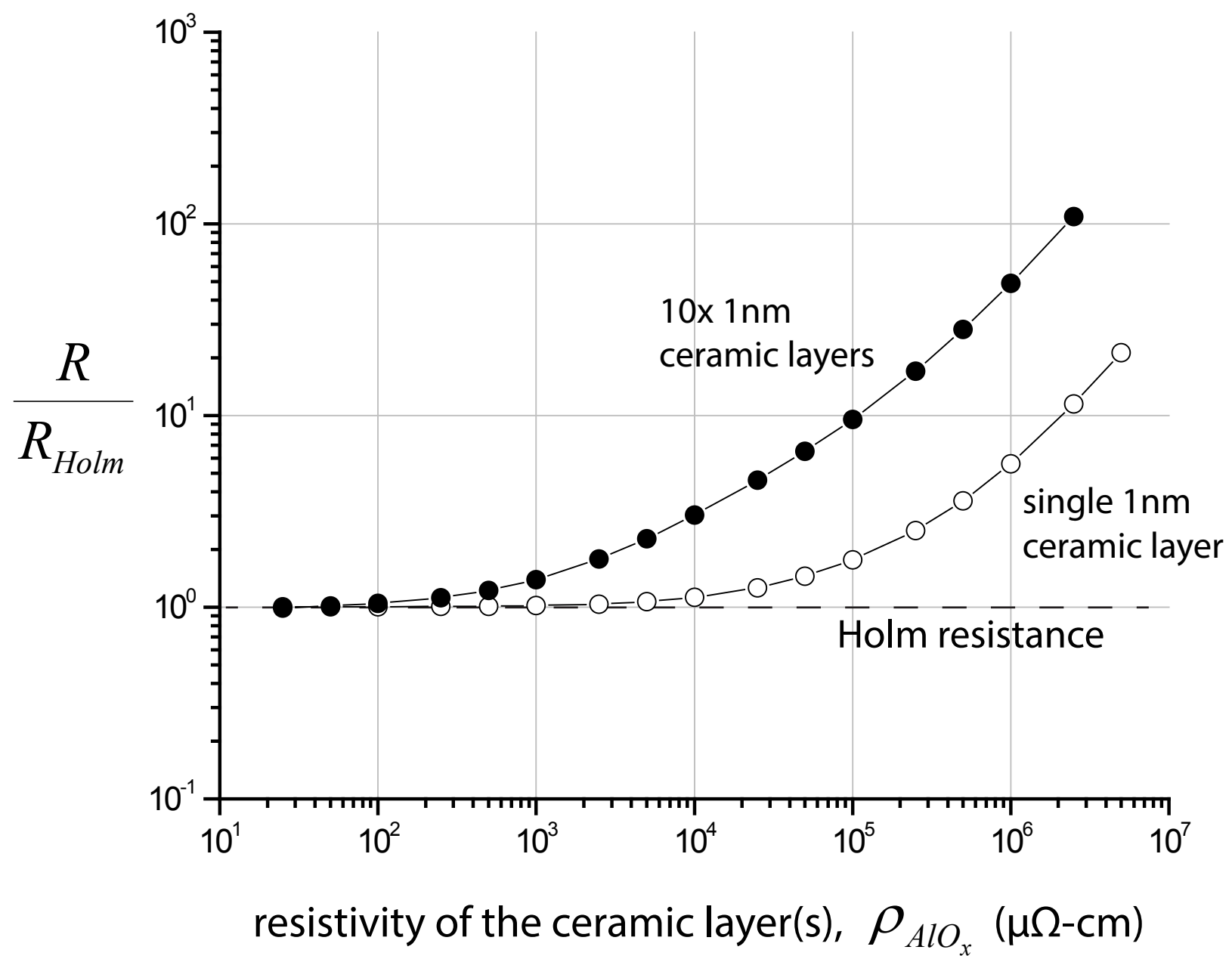
Acknowledgments

Rand Garfield for tribological test specimen preparation

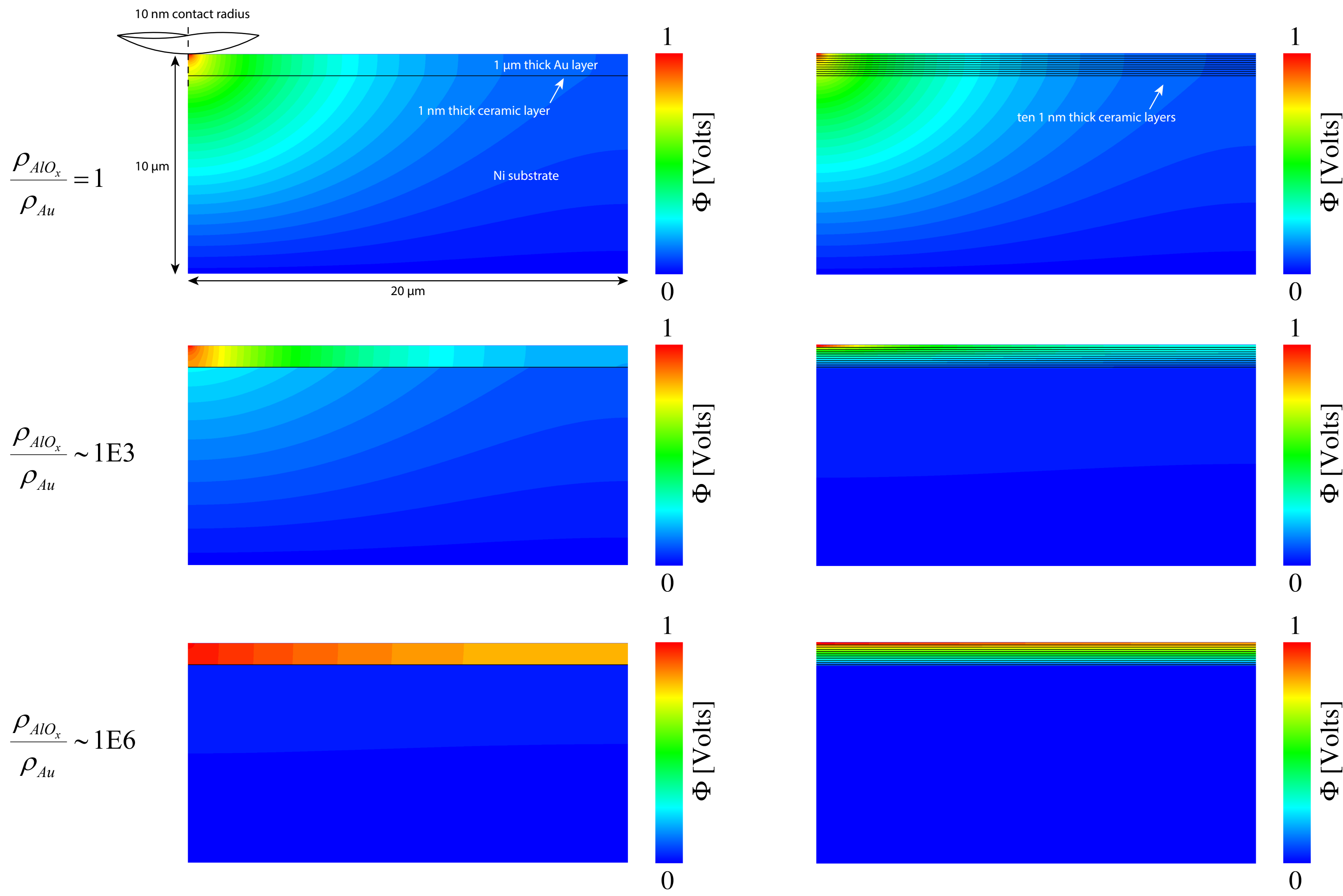
Bonnie McKenzie for SEM-EDS imaging

Michael Rye for diffraction composition mapping

Finite element modeling prediction of resistivity

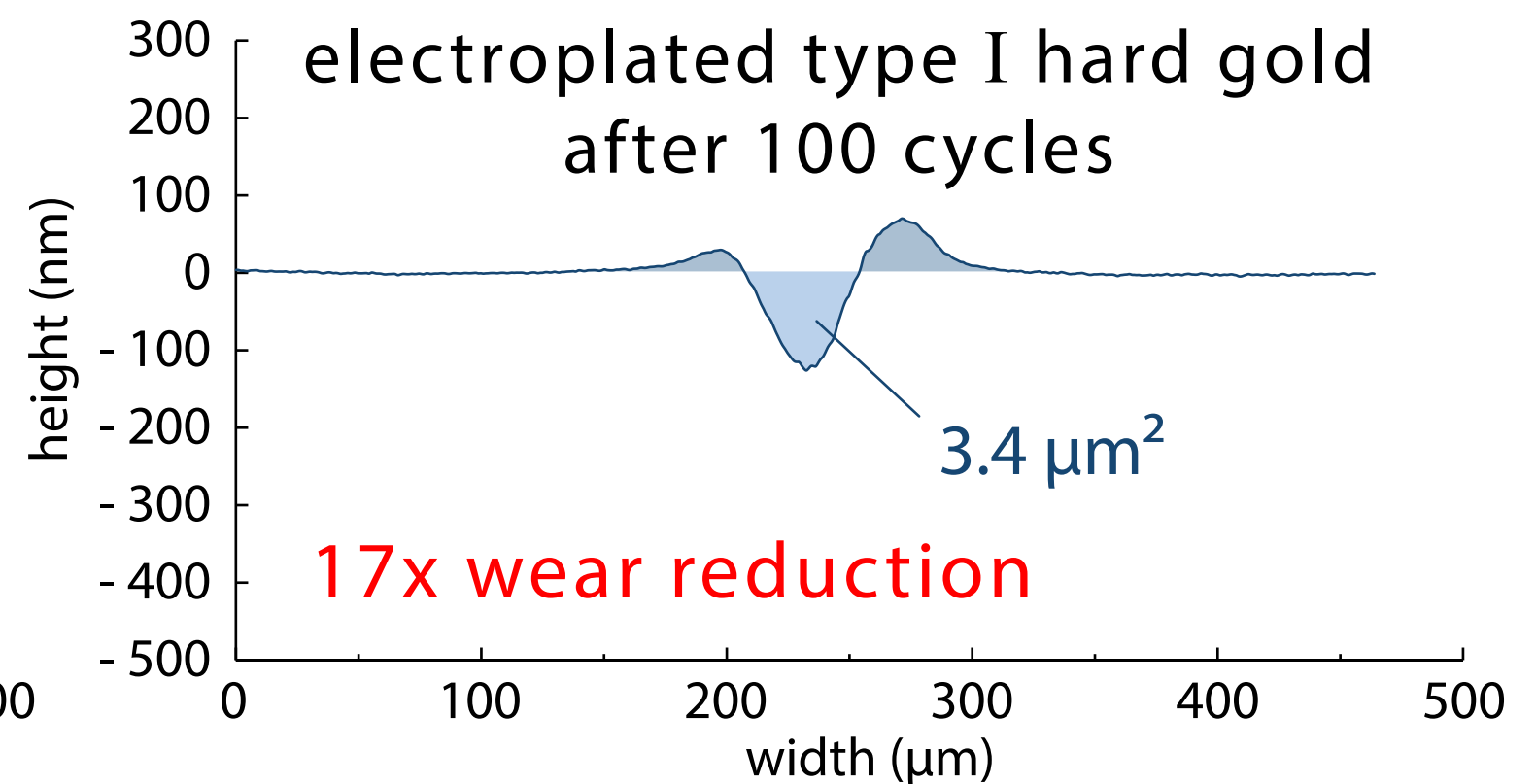
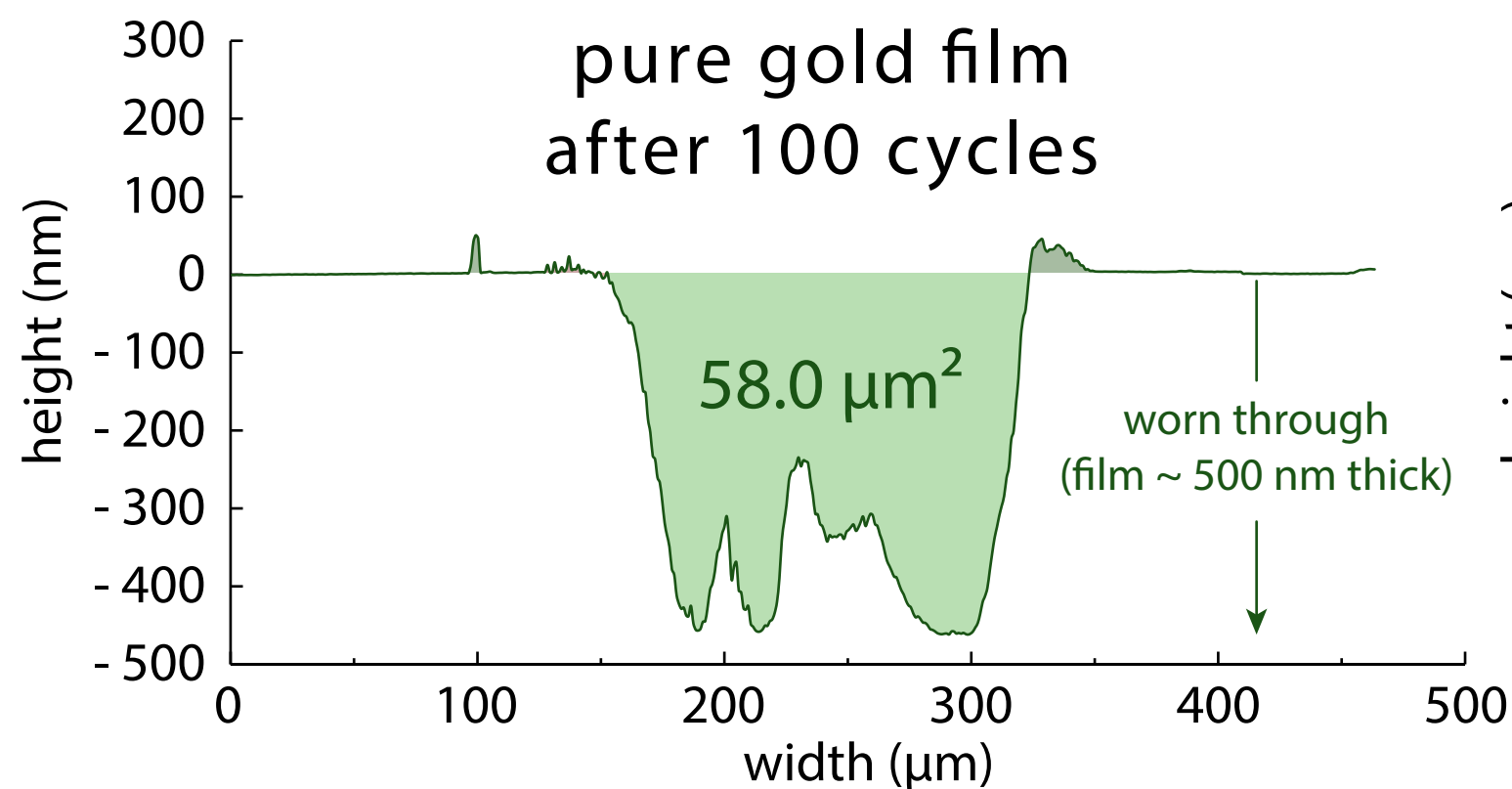


FEM isopotential maps

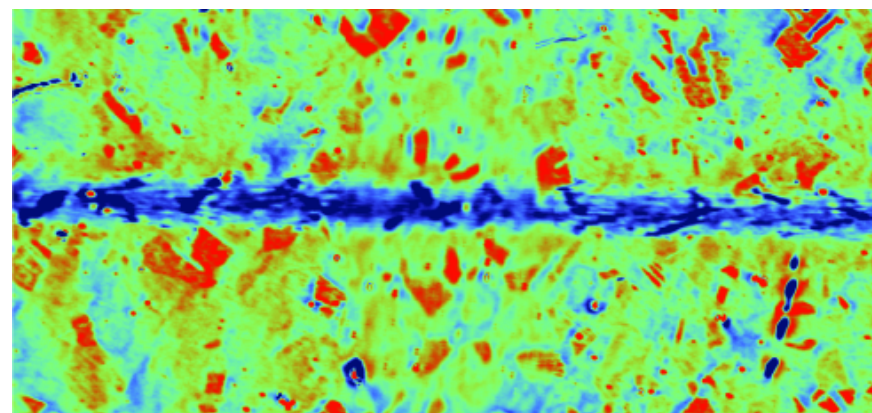


Hard gold is also highly wear resistant

average wear track cross-section in same sliding conditions against Neyoro G rider:



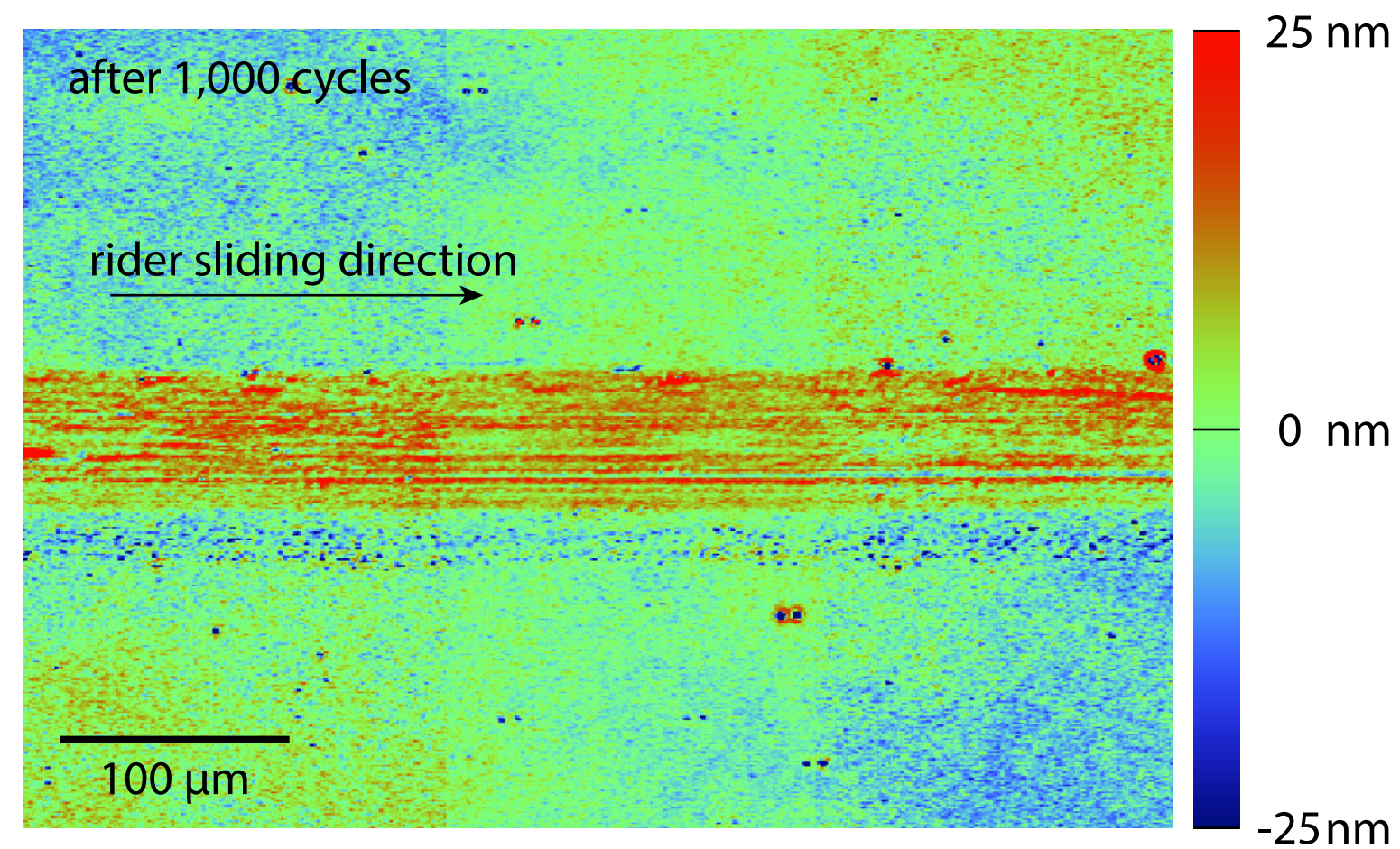
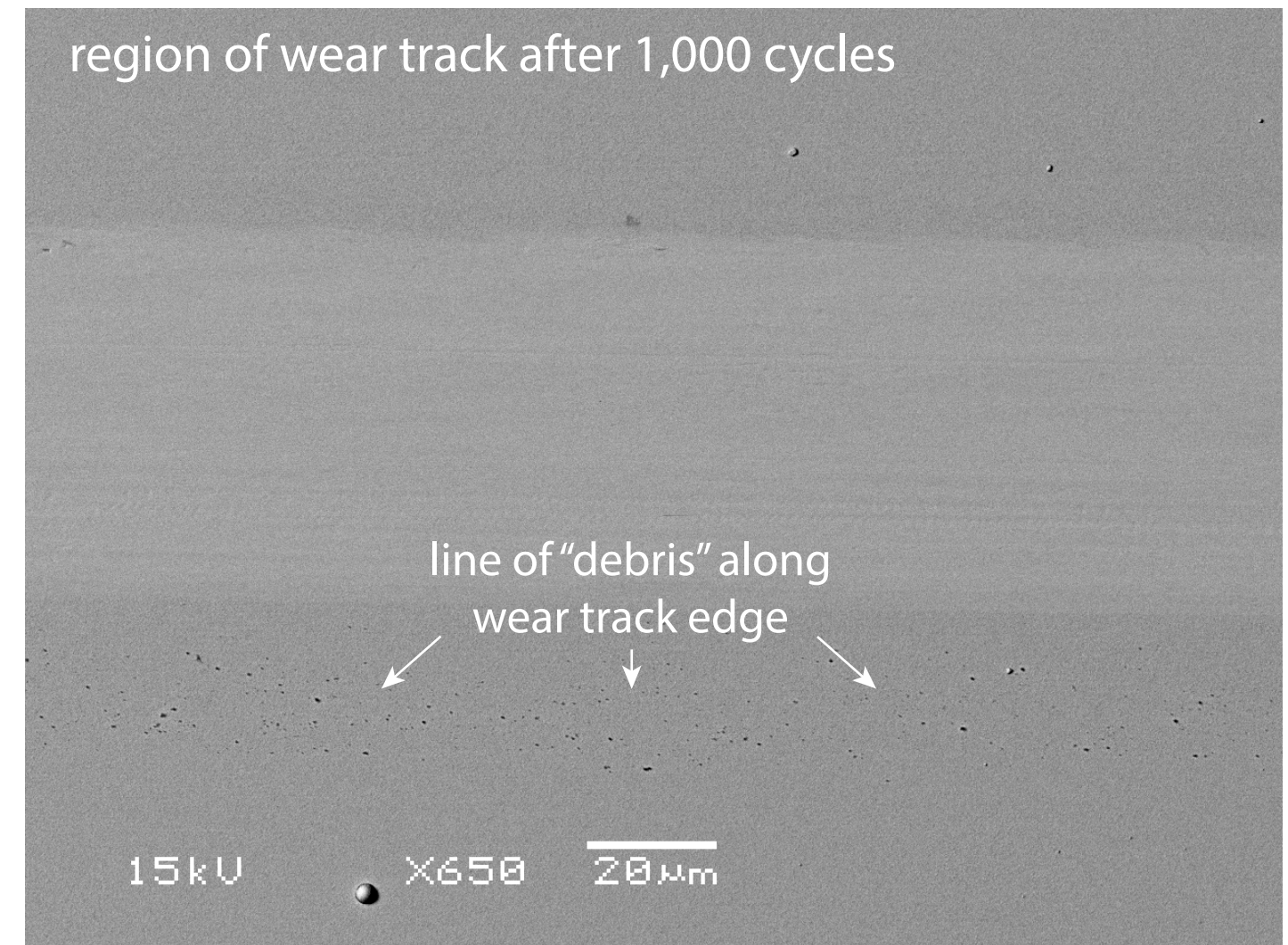
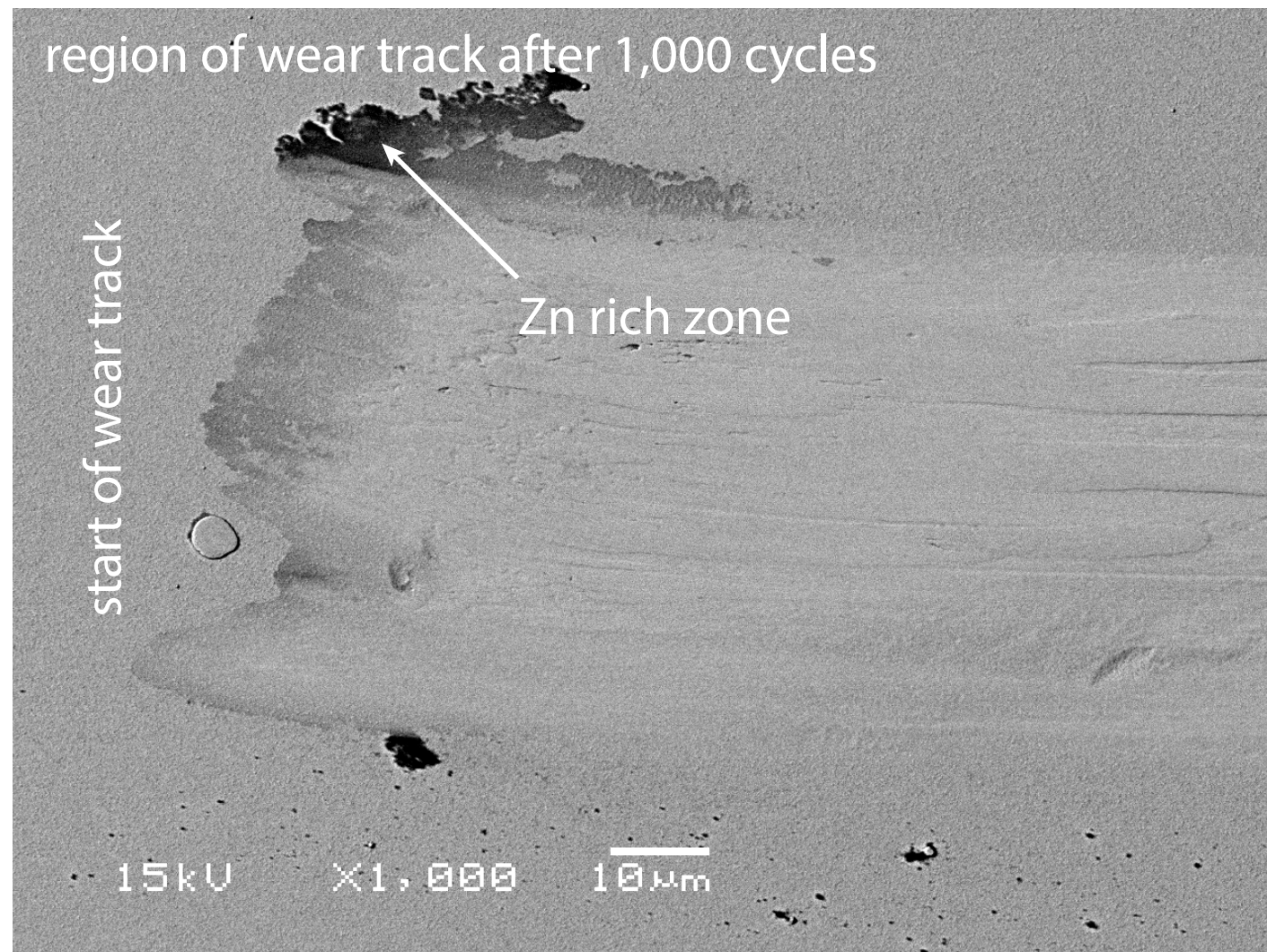
(example of topographical map)



500 μm

average linescans over
50% of wear track length

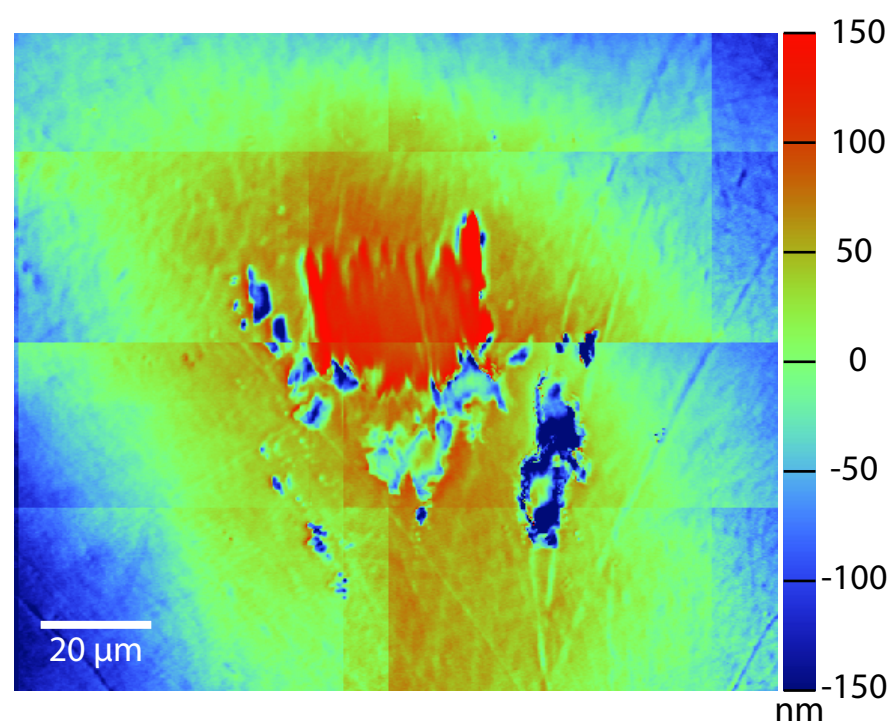
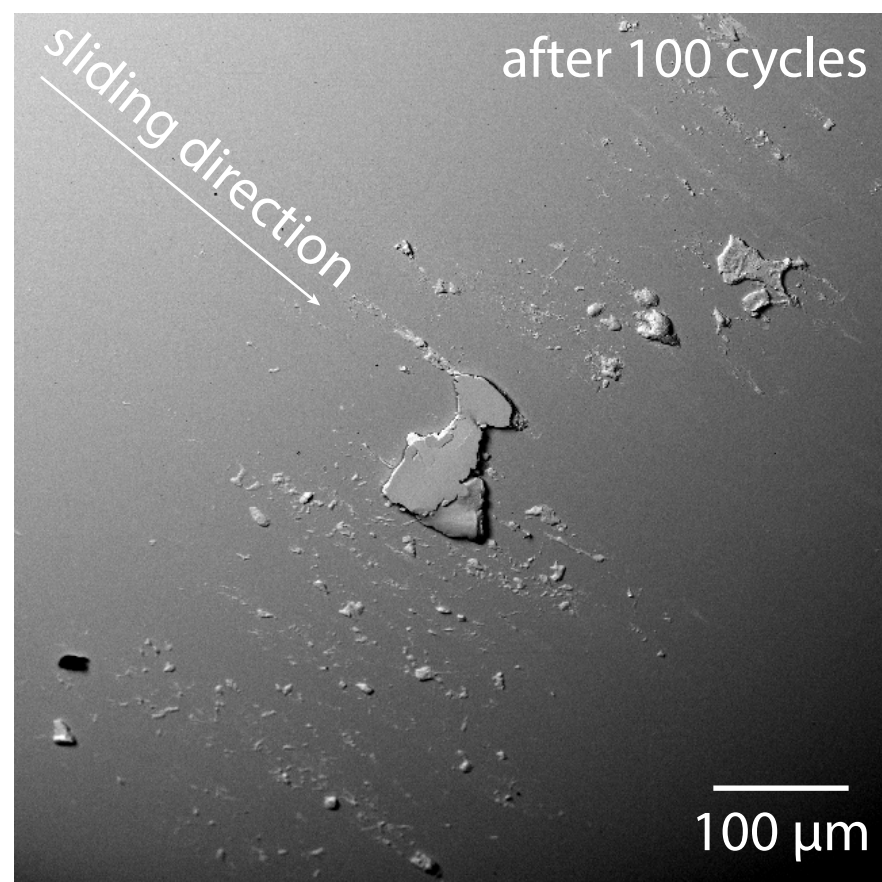
Effectively **zero wear** of the 2% ZnO gold nanocomposite



The 2% ZnO gold film wore the (hard!) Neyoro G pin

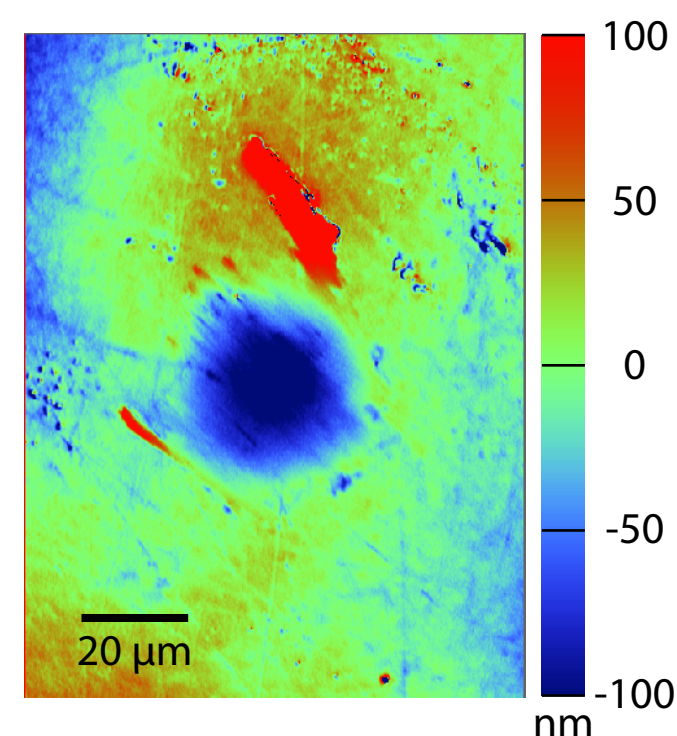
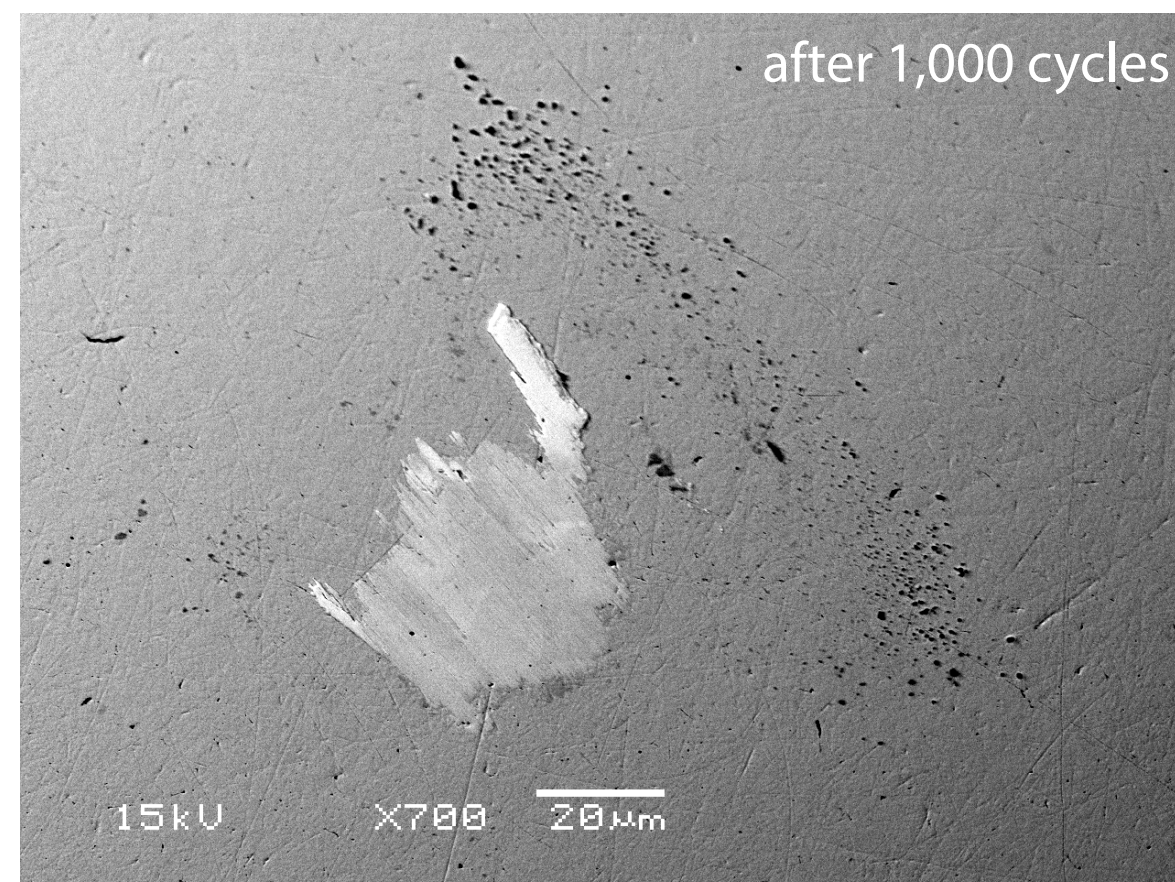
SEM of rider surface

sliding against
pure Au



SEM of rider surface

sliding against
2 % ZnO-Au



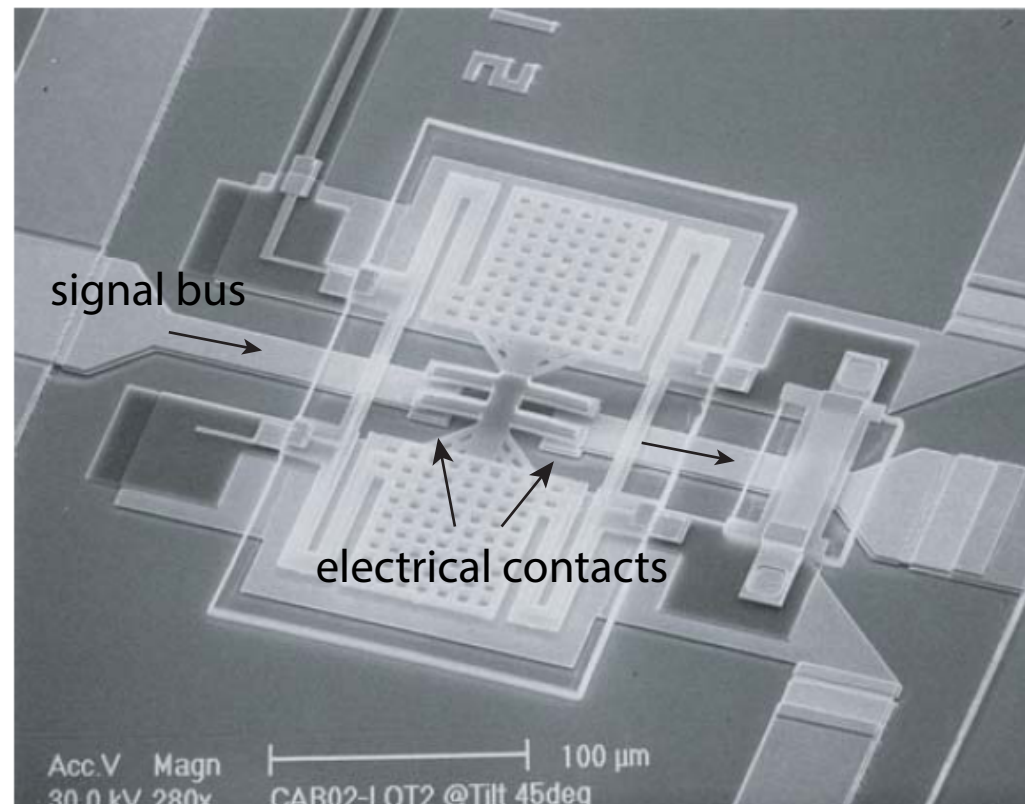
Neyoro G rider is **HARD** (~ 250 Knoop, or ~ 2.5 GPa)

reference: the hardest "hard gold" is in the 2.0 to 2.5 GPa range

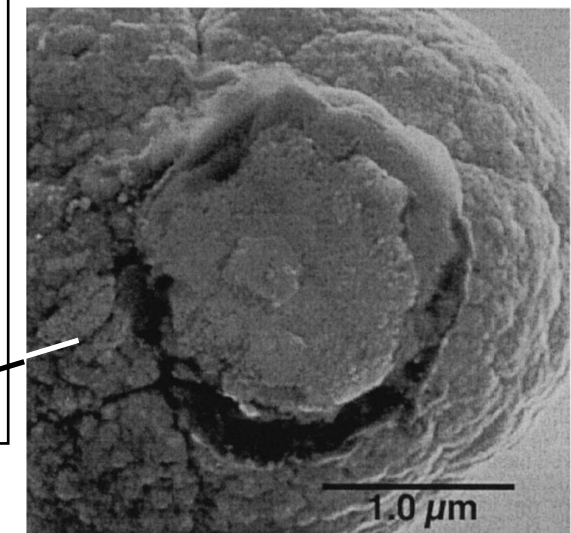
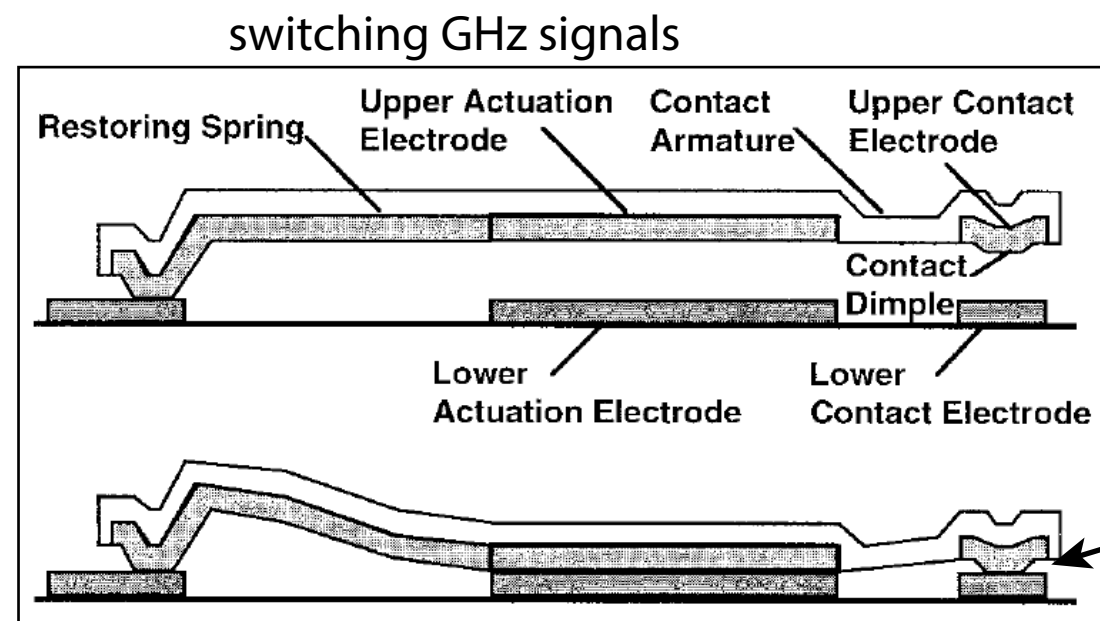
preliminary result via nanoindentation, 0.1% strain : 1% ZnO-Au hardness ~ 2.6 GPa

What are some examples of mechanical-electrical contacts?

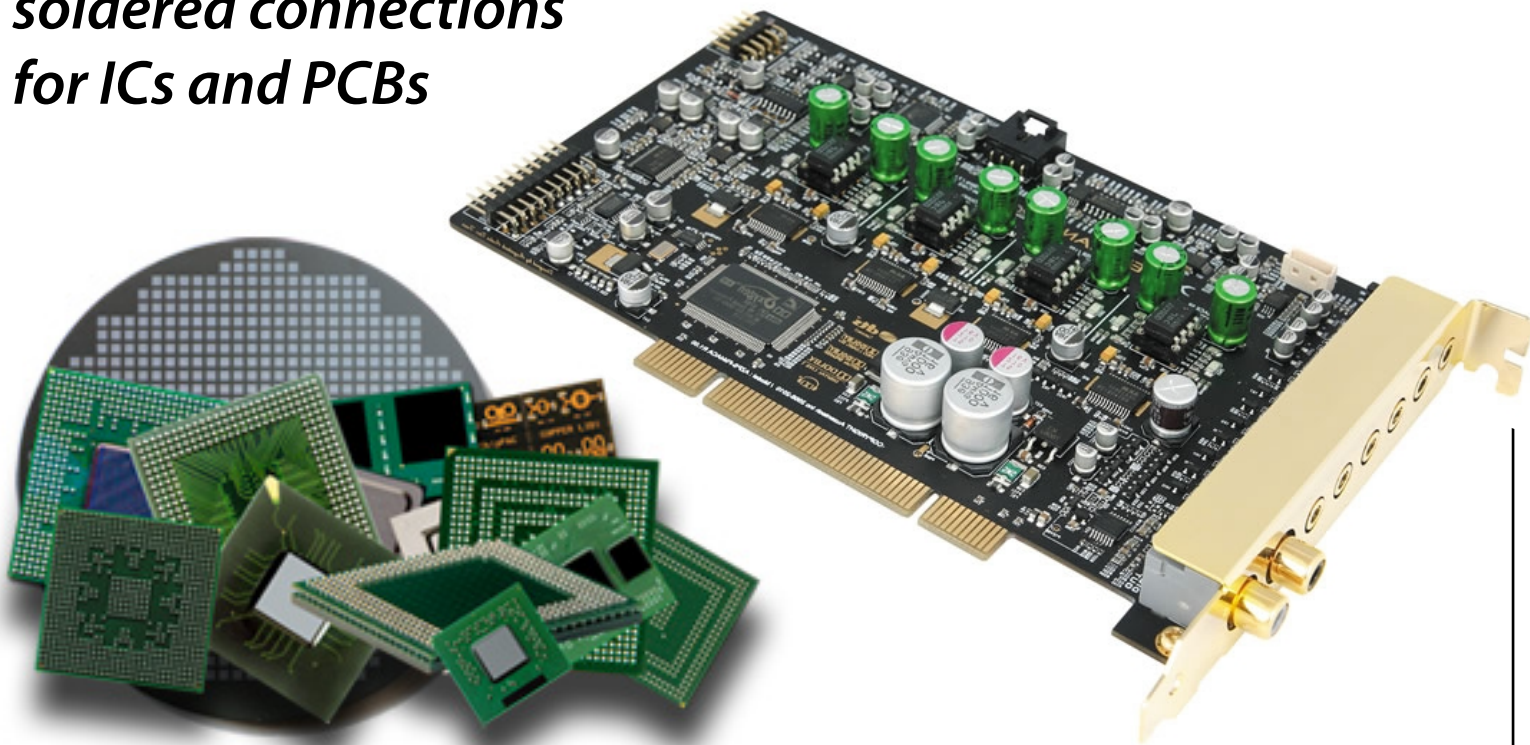
MEMS



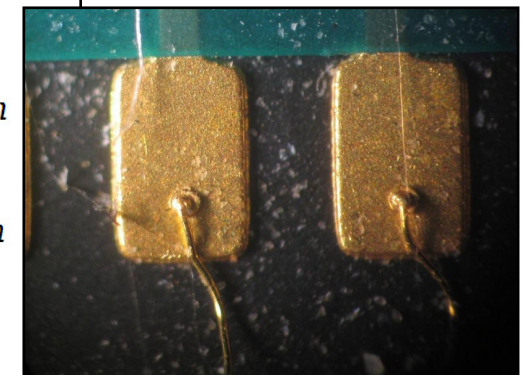
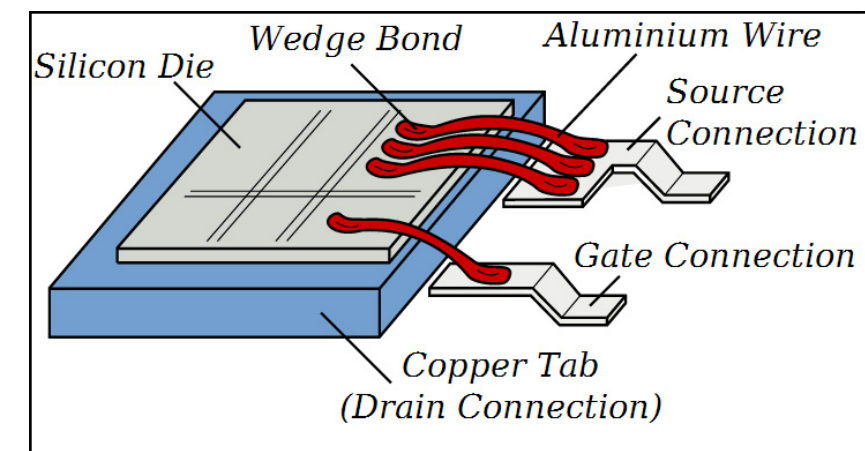
Rockwell Scientific metal-metal switch



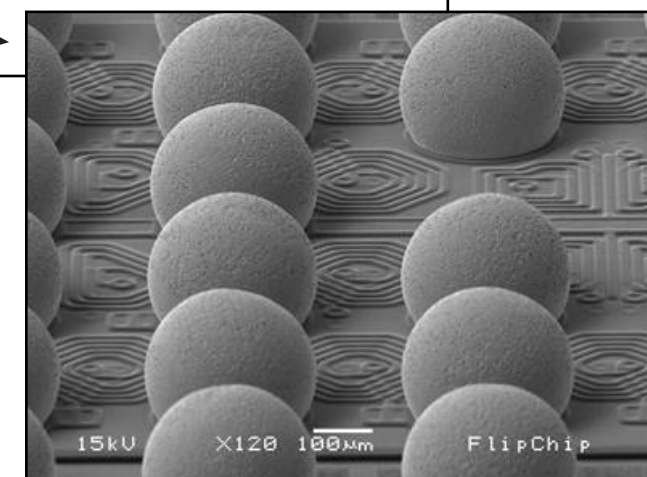
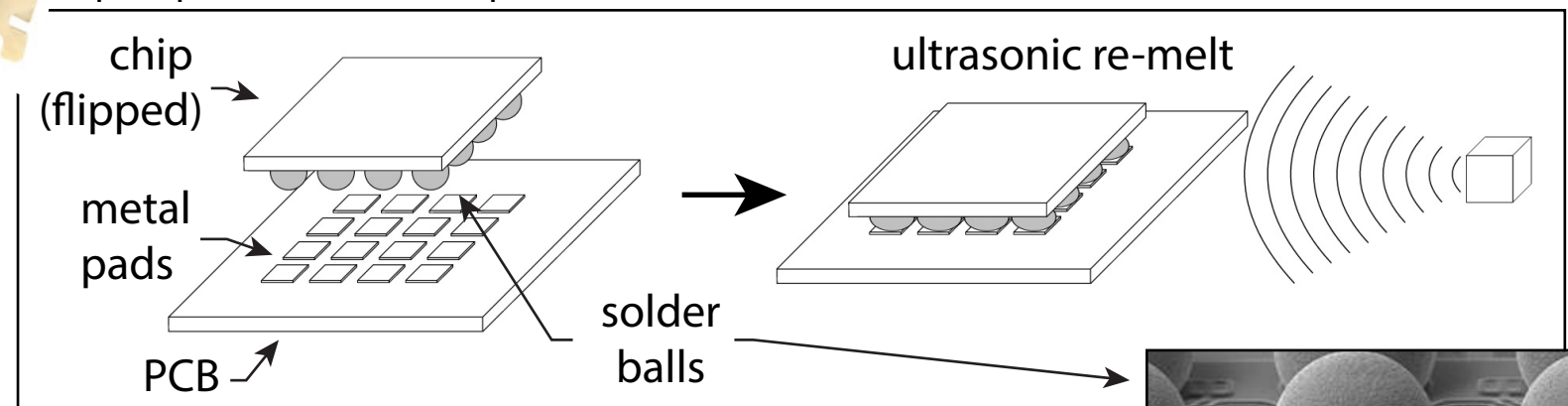
soldered connections for ICs and PCBs



wire bonding of ICs



flip chip (solder balls b/w pads, no wires)



When electricity is required to pass through a contact, the surfaces are metallic (conductivity!)